FABRICATION AND CHARACTERIZATION OF NANOSTRUCTURED CERAMIC THIN FILMS FOR ELECTROCHEMICAL STUDIES

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ABSTRACT

This work describes some general procedures for the synthesis and characterization of monometallic and heterobimetallic single source precursors [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1), $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ ·THF (2), [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (3), $[Mn(dmae)_2(TFA)_4]$ (4) and $[Sn(dmae)(OAc)]_2$ (5) and their disposal for the growth of thin films for electrochemical applications. The complexes have been characterized by m.p, elemental analyses, FT-IR, TG/DTG and single crystal X-ray analysis. The precursors (1), (2) and (3) were applied as a single source for the fabrication of CuO-2TiO₂ and CoTiO₃-TiO₂ composites and MgTi₂O₅ solid solution thin films, whereas film precursor (4) has been applied as a dual source along with Ag(I) acetate for the deposition of Ag-Mn₂O₃ composite thin film by aerosol assisted chemical vapour deposition (AACVD). The electric field directed aerosol assisted chemical vapor deposition technique (EFDAACVD) was used to make thin films of SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO and PbO from precursor (5) and their respective acetates. Further CuPbI₃ was synthesized by heating co-precipitated mixture of copper(I) iodide and lead(II) iodide in an evacuated Pyrex ampule at 630 °C. The films of CuPbI₃ were decorated by electrophoretic deposition method. The phase purity, particle size and crystallinity of deposited thin films were examined by X-ray powder diffraction (XRPD) and Raman spectroscopy, while X-ray photoelectron spectroscopy (XPS), field emission scanning electron microscopy and energy dispersive X-ray spectroscopy (EDX) were used to investigate the oxidation states, electronic structure, surface morphology, shape and elemental composition of the involved elements. In the case of mesoporous nanostructure of SnO₂ microballs surface area 136 m²g⁻¹ was determined by BET. The optical band gaps of films were determined by UV-visible spectrophotometry and found to be were 1.8, 3.4, 3.8, 1.2, 2.2, 1.9, 0.9, 3.2, 2.2, 1.9 and 1.82 eV for Ag-Mn₂O₃, MgTi₂O₅, SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO and CuPbI₃ films, respectively. The applicability of fabricated CuO-2TiO₂ and CoTiO₃-TiO₂ composite electrodes in electrochemical sensors has been investigated towards the sensitive and selective detection of NO₂⁻ ions and dopamine (DA), respectively. The CuO-2TiO₂ electrode showed the limit of detection (LoD) of 16.6 nM with the linear range of 10 to 200 μ M at +1.0 V due to the oxidation of NO₂⁻ions. The CoTiO₃-TiO₂ electrode showed good electrocatalytic activity for DA with the (LoD) of 0.083 µM and a linear range of 20 to 300 μ M. The SnO₂ micro balls provide unique network pores that could be easily penetrated by the electrolyte to give high reversible recycling stability for application in lithium ion batteries. The photoelectrochemical activity (PEC) of Ag-Mn₂O₃, MgTi₂O₅, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO and CuPbI₃ thin films determined by the linear sweep voltammetry (LSV) show photocurrent densities of 3, 0.4, 1.2, 0.12, 0.23, 0.13, 0.23, 0.26, 0.20 and 0.25 mAcm⁻² at 0.7 V vs Ag/AgCl/3M KCl, respectively. The improved photoelectrochemical behaviour of Ag-Mn₂O₃, MgTi₂O₅, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO and CuPbI₃ electrodes was attributed to the increased photon absorption ability, increased surface area, and more efficient electron/hole transfer which were confirmed by LSV, Chronoamperometery, electrochemical impedance spectroscopy and Mott-Schottky plot.

ABSTRAK

Kerja ini menerangkan beberapa prosedur umum untuk sintesis dan pencirian prekursor monologam dan heterodwilogam [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1), [Co₂Ti₄(µ-O)₆(TFA)₈(THF)₆]•THF (2), [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (3), $[Mn(Dmae)_2(TFA)_4]$ (4) dan $[Sn (Dmae)(OAc)]_2$ (5) dan penggunaan precursorprekursor ini untuk pertumbuhan filem nipis untuk aplikasi elektrokimia. kKompleks yang disintesis ini telah diciri melalui analisis takat lebur, unsur, FT-IR, TG / DTG dan sinar-X hablur tunggal. Prekursor (1), (2) dan (3) digunakan sebagai sumber tunggal untuk fabrikasi komposit CuO-2TiO₂ dan CoTiO₃-TiO₂ dan filem nipis larutan pepejal MgTi₂O₅ melalui pemendakan wap kimia dibantu aerosol (AACVD) manakala prekursor (5) digunakan sebagai sumber dwi bersama-sama dengan Ag(I) asetat untuk pemendapan filem nipis komposit Ag-Mn₂O₃ oleh AACVD. Teknik pemendapan wap kimia dibantu aerosol diarah oleh medan elektrik (EFDAACVD) telah digunakan untuk fabrikasi filem nipis SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO dan PbO, daripada asetat masingmasing dan precursor (4) telah digunakan untuk fabrikasi serbuk bebola nano SnO₂ dan filem nipisnya atas substrat kaca FTO. Seterusnya, CuPbI₃ telah disintesis melalui pemanasan campuran ko-mendakan plumbum(II) iodida dan kuprum(I) iodida dalam ampule pyrex tervakum pada 620° C. Filem CuPbI₃ dihiasi dengan teknik pemendapan elektroforetik. Fasa ketulenan, saiz zarah dan penghabluran filem nipis termendap diuji dengan pembelauan sinar-X (XRD) dan spektroskopi Raman, manakala spektroskopi fotoelektron sinar-X (XPS), mikroskop elektron imbasan pemancaran medan dan spektroskopi tenaga serakan X-ray (EDX) digunakan untuk menyiasat keadaan pengoksidaan, struktur elektron, morfologi permukaan, saiz habluran, bentuk dan komposisi unsur bagi unsur-unsur yang terlibat. Dalam kes struktur nano bebola mikro SnO₂ yang berliang meso, luas permukaan yang ditentukan oleh BET didapati ialah 136 m² g⁻¹. Jurang jalur optik bagi semua filem-filem yang difabrikasi diuji oleh

spektrofotometri UV dan didapati adalah 1.8, 3.4, 3.8, 1.2, 2.2, 1.9, 0.9, 3.2, 2.2, 1.9 dan 1.82eV masing-masing bagi filem Ag-Mn₂O₃, MgTi₂O₅, SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO dan CuPbI₃. Aplikasi elektrod komposit CuO-2TiO₂ dan CoTiO₃-TiO₂ yang difabrikasi dalam sensor elektrokimia telah disiasat terhadap pengesanan senstif dan terpilih masing-masing bagi ion NO₂ dan dopamin (DA). Elektrod CuO-2TiO₂ menunjukkan had pengesanan (LoD) sebanyak 16.6 µM dengan julat linear dari 10 hingga 200 µM pada +1.0 V disebabkan oleh pengoksidaan ion NO₂. Elektrod CoTiO₃-TiO₂ menunjukkan aktiviti electromangkinan yang baik untuk DA dengan (LoD) sebanyak.0.083 µM dan julat linear dari 20 hingga 300 µM. Bebola mikro SnO₂ menyediakan liang-liang rangkaian unik yang mudah ditembusi oleh elektrolit untuk memberi kestabilan kitaran semula berbalik yang tinggi untuk aplikasi dalam bateri ion litium. Aktiviti fotoelektrokimia (PEC) filem nipis Ag-Mn₂O₃, MgTi₂O₅, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO dan CuPbI₃ seperti ditentukan oleh voltammetri penyapuan linear (LSV) masing-masing menunjukkan ketumpatan arus foto sebanyak 3, 0.4, 1.2, 0.12, 0.23, 0.13, 0.23, 0.26, 0.20 dan 0.25 mA cm⁻² pada 0.7 V vs Ag/AgCl/3M KCl. Peningkatan sifat fotoelektrokimia bagi elektrod Ag-Mn₂O₃, MgTi₂O₅, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO dan CuPbI₃ adalah disebabkan oleh peningkatan keupayaan penyerapan foto, peningkatan luas permukaan, dan pemindahan elektron/lubang yang lebih cekap yang telah disahkan oleh pengukuran voltammetri penyapuan linear, kronoamperometri, spektroskopi impedans elektrokimia dan plot Mott-Schottky.

DEDICATION

То

HAZRAT MUHAMMAD (PEACE BE UPON HIM)

WHO IS THE LAST MESSENGER OF ALLAH

То

LOVING PARENTS, WHOSE

UTMOST EFFORTS AND PRAYERS ARE ALWAYS WITH ME

То

RESPECTED TEACHERS, WHOSE

KIND GUIDANCE AND ENCOURAGEMENT HELPED ME TO REACH AT THIS STAGE

То

THOSE, WHO INSPIRED ME TO SEEK KNOWLEDGE FOR THE WELFARE OF MANKIND

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LIST OF SYMBOLS AND ABBREVIATION

μΑ		Microampere
μΜ		Micromolar
Å	:	Angstrom
AA	:	Ascorbic acid
AACVD	:	Aerosol assisted chemical vapor deposition
AP	:	Acetaminophen
APCVD	:	Atmospheric pressure chemical vapour deposition
BET	:	Brunauer–Emmett–Teller
BJH	:	Barrett-Joyner-Halenda
СВ	:	Conduction band
CBM	:	Conduction band maxima
CHN	:	Carbon hydrogen nitrogen analysis
cm	:	Centimeter
cm ³	:	Cubic centimeter
CNTs		Carbon nanotubes
CPE	:	Carbon paste electrode
CV	:	Cyclic voltammetry
CVD	:	Chemical vapor deposition
DA	:	Dopamine
dmae	:	N,N-Dimethylaminoethanolate
dmaH	÷	N,N-Dimethylaminoethanol
DMFC	:	Direct methanol fuel cell
DSSC	:	Dye sensitized solar cells
Е	:	Energy
e.g	:	exempli gratia
ECSA	:	Electrochemical surface area
EDX	:	Energy dispersive X-ray
EFDAACVD	:	Electric field directed aerosol assisted chemical vapor deposition
EPD	:	Electrophoretic deposition
Eg	:	Bandgap
EIS	:	Electrochemical Impedance spectroscopic
EPD	:	Electrophoretic deposition
et al	:	et alia

Etc	:	et cetra
eV	:	Electron volt
FESEM	:	Field emission scanning electron microscopy
FIB		Focussed ion beam
\mathbf{f}_{max}	:	Frequency peak maximum
FTIR	:	Fourier transform infrared
FTO	:	Fluorine doped tin oxide
g	:	Gram
GCE		Glassy carbon electrode
GO	:	Graphene oxide
Н	:	Magnetic field
ICDD	:	International center for diffraction data
IR	:	Infrared
J	:	Photocurrent density
Κ	:	Kelvin
LACVD	:	Laser assisted chemical vapor deposition
LEDs	:	Light emitting diodes
LIBs	:	Lithium ion batteries
LoD	:	Limit of detection
LSV	:	Linear Scan voltammetry
mA	:	Milliampere
Me	:	Methyl
min	·	Minute
mL		Milliliter
MOCVD	:	Metal-organic chemical vapor deposition
MOD	:	Metal organic deposition
mol	:	Mole
mp	:	melting point
nm	:	Nanometer
nM	:	nanomolar
NMR	:	Nuclear magnetic resonance
OAc	:	Acetate
°C	:	Degree centigrade
PEC	:	Photoelectrochemical
PECVD	:	Plasma enhanced Chemical vapor deposition

PEMFC	:	Polymer electrolyte membrane fuel cell
PZT	:	Lead zirconate titanate
Rct	:	Charge transfer resistance
RGO	:	Reduced graphene oxide
SOFCs	:	Solid oxide fuel cells
SPR	:	Surface plasmon resonance effect
SPT	:	Spray pyrolytic technique
SSP	:	Single source precursor
T _c	:	Curie temperature
TFA	:	Trifluoroacetato
TFAH	:	Trifluoroacetic acid
TGA	:	Thermogravimetric analysis
THF	:	Tetrahydrofuran
Trp	:	Tryptophan
Ttip	:	Titanium (IV) isopropoxide
UA	:	Uric acid
UV	:	Ultraviolet
V	:	Volume
VB	:	Valence band
VBM	:	Valence band minimum
Vis	:	Visible
XPS	:	X-ray photoelectron spectroscopy
XRD	:	X-ray diffraction
YSZ	:	Yittria stabilized zirconia

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PREFACE

The thesis entitled "Fabrication and Characterization of Ceramic thin films for Electrochemical Studies" is divided into five different chapters

The chapter 1 describes the scope of ceramic thin films for electrochemical applications in field of science and technology. The chapter 2 comprises of a detailed studies of background to ceramic materials, their properties and suitable techniques for the deposition of ceramic thin films. A detailed history of deposition techniques, characterization and electrochemical applications of thin films have been described. The materials used and method adopted for the synthesis of precursors and their utilization in the deposition of thin films by AACVD, EFDAACVD and EPD methods have been described in chapter 3.

The chapter 4 is further divided into seven sections. The first four sections deal with discussion on the chemistry of precursors and their conversion to composite oxide thin films by AACVD technique. The fifth and sixth sections elaborate the deposition of metal oxide thin films by EFDAACVD method. The last part describe the deposition of metal halide films by EPD technique. After a proper discussion on characterization each section ends with a brief discussion of electrochemical sensing, optical and photoelectrochemical results of films. At the end of the thesis, conclusions regarding this research work have been given in chapter 5.

CHAPTER 1: INTRODUCTION

Ceramic films deposited on substrates exhibit versatile properties and have revolutionized many technological areas specially the energy (Harrison, Levene, Rajeshwar, McConnell, & Licht, 2008) and environmental sectors (Jun Zhang, Bang, Tang, & Kamat, 2009). Micro and nano structured transition metal oxide/ halide materials with high surface area and controlled size, shape and morphology have found diverse applications in optical, optoelectronic, photovoltaic, supercapacitors, batteries and gas sensing devices (J. Chen, Xu, Li, & Gou, 2005; Clavero, 2014; Gao, Grätzel, & Nazeeruddin, 2014; Lang, Hirata, Fujita, & Chen, 2011). Such materials offer a unique combination of their structural, optical, electrical and photoelectrochemical properties. The photoactive materials have been designed and developed with the aim to fix the main photoelectrochemical problems such as proper conduction/valence band position, narrowing of the band gap to harness visible light, fast electron/hole pair separation/transportation (Baker & Kamat, 2009; Gonçalves, Leite, & Leite, 2012; Le Formal, Grätzel, & Sivula, 2010; Leung et al., 2010; G. Li et al., 2013; Momeni, Ghayeb, & Davarzadeh, 2015; Sivula et al., 2010; J. Su, Feng, Sloppy, Guo, & Grimes, 2010; M. Wang et al., 2013; Yan, Ye, Wang, Yu, & Zhou, 2012), however, these extensive studies could not find an individual material which can overcome all these issues at once. The main criteria for photocatalytic material is low cost, environment friendly and highly efficient.

Ceramic films are commonly nonselective, while some selectivity could be achieved by modifying the optical, electronic, electrochemical characteristics and the use of solid solution and composite materials (Lazar & Daoud, 2013). Diverse electroactive ceramic thin films of NiO, Fe₂O₃, Mn₃O₄, SnO₂ and Co₃O₄ have been broadly reported in literature. Some work has been done on their fabrication methods, structure, controlled surface morphology and electrochemical studies (Nakata & Fujishima, 2012; Park, Park,

Kim, & Choi, 2013; Rehman, Ullah, Butt, & Gohar, 2009). However photo activity can be improved by defect engineering, doping of non-metal, coupling with other semiconductor or metal oxides, deposition of noble metal nanoparticles (Jinlong Zhang, Wu, Xing, Leghari, & Sajjad, 2010). Defect engineering indicates inclusion of inherent defects, such as vacancies, interstitials, and antisites, while doping infers the addition of impurities into the crystal lattice (Djurisic, Leung, & Ching Ng, 2014). The recent work showed that coupling with other semiconductor or metal oxide (Dhanalakshmi, Pandikumar, Sujatha, & Gunasekaran, 2013) and deposition of noble metal nanoparticles (Pandikumar, Murugesan, & Ramaraj, 2010) results in enhances the charge transfer at the electrode electrolyte interface and minimization in the charge recombination. Therefore, the method of catalytic (Rossetti, 2013) and photocatalytic oxidation of organic molecules (Y. J. Kim et al., 2009) and water (Jiao et al., 2013) and application as anode materials for Li-ion batteries (S. Guo et al., 2015) can occur by transfer of an electron to the semiconductor surface (Shinde, Bhosale, & Rajpure, 2013).

The physical and chemical properties of metal oxide and metal halide solid solution thin films are intensely affected by the composition and microstructure of their particles, which depend on the research method used in their synthesis. A number of procedures are introduced for the fabrication of metal oxide and halide ceramic thin films (Babuji, Balasubramanian, Radhakrishnan, & Kasilingam, 1980; Corneille, He, & Goodman, 1995; C.-L. Huang, Wang, Chen, Li, & Lin, 2012; Korotcenkov, Brinzari, Schwank, DiBattista, & Vasiliev, 2001; M. Nirmala, 2010; Mondal, Bhattacharyya, & Mitra, 2013; Ozegowski, Meteva, Metev, & Sepold, 1999; Scott, 2008). Nevertheless, the reported methods have shortcomings of not distributing the precise stoichiometric composition and fail to provide phase purity of the materials (Mansoor, Ismail, et al., 2013; M. Veith, Haas, & Huch, 2004). Therefore, in order to use of chemical vapour deposition it is necessary to modify the physio-chemical properties of the complex to improve process parameters.

To attain this, the molecular structure design method is based on the selection of a proper molecular structure type and competing it with ligands providing the required donor atoms. The growth of materials with complexes composition in micro or nanometers can define the surface morphology and physical properties, which recently focus on single or dual source precursor comprising of molecules containing all required elements in the appropriate ratios and decompose in a controllable way under normal conditions.

The aim and objective of the work is to study the performance of electro ceramic materials and devices depends on the complex interplay between processing, chemistry, structure at many levels and device physics and so requires truly interdisciplinary effort by individuals from many fields. Topical areas cover a wide spectrum with recent active areas including sensors and actuators, electronic packaging, photonics solid state ionics, defect and grain boundary engineering, magnetic recording, non-volatile ferroelectric memories, wide band gap semiconductors, high Tc superconductors, integrated dielectric and nanotechnology. Improvements in the numerous categories of electroceramics have paralleled the development of new technologies.

The present research work focuses on the design and development of single and dual source molecular precursors that contain all the components of target material, for the deposition of metal/mixed metal oxides, composites and solid solution thin films by using the AACVD, EFDAACVD and EPD techniques. The deposited films were characterized by XRD, XPS, FESEM/EDX, Raman spectroscopy and UV-visible spectroscopy for their microstructure, morphology, stoichiometry, thickness, chemical sates of constituent metals and optical band gap. A further scope of these fabricated films electrodes towards electrochemical studies is investigated.

CHAPTER 2: LITERATURE REVIEW

2.1 Ceramic Materials

Ceramics consist of a wide range of synthetic materials based on inorganic non-metallic compounds, primarily oxides, sulphides, nitrides, carbides, silicides and silicates (Da Silva, 2016; Gryshkov et al., 2016; Lahcen et al., 2014; Y.-C. Liang, Wang, & Lo; H.-H. Lu & Chen, 2016; Secu, Secu, & Bartha, 2016; J. Wei et al., 2016; Y. Yang et al., 2015; Yeh et al., 2013). The essentially ionic, covalent, non-metallic compounds that constitute ceramics are compounds formed between metals and non-metals. The crystallinity of ceramic materials ranges from highly oriented to semi-crystalline, and not fully amorphous. The advantageous properties of these ceramics are hardness, rigidity, chemical inertness, toughness and nonconductors of heat and electricity. Ceramics in the form of thin films, powders, single crystals and composites, have showed important role in medical field, electronics, chemical, energy and manufacturing industries (Affatato, Ruggiero, & Merola, 2015; N. Choudhary & Kaur, 2016; Kose et al., 2016; Saji, Venkata Subbaiah, Tian, & Tiwari, 2016; Sommers et al., 2010; S. Zhang et al., 2015).

Ceramics can be classified into two main categories. Structural ceramics and functional ceramics. Structural ceramics have potential to tolerate mechanical and thermal loading exposed to aggressive, severe chemical and thermal environment. They combine the properties and benefits of ceramics like chemical inertness, high temperature capability and rigidity, high strength, toughness, stiffness, hard, corrosion and thermal shock resistance and long term durability (Booth et al., 2016). The lifetime of ceramics in several structural applications is sensitive to unusual measures including brittle failure during mechanical or thermal loading, pitting by corrosion, dielectric breakdown and fatigue crack initiation. Structural ceramics are also used to investigate for employment in many high performances applications including metal cutting and shaping tools.

Because of high temperature and corrosion resistant properties structural ceramics are mainly valuable to resolve a large number of today's material challenges in process industries, power generation, aerospace, transportation and military applications (M. Rahman, Haider, Akter, & Hashmi, 2014).

Functional ceramics have good electrical, magnetic, and optical properties and find vast application in the field of optics, optoelectronics, catalysis, photovoltaics, sensors, biomedical, biotechnological and environmental applications etc (Maglia, Tredici, & Anselmi-Tamburini, 2013; Treccani, Yvonne Klein, Meder, Pardun, & Rezwan, 2013). A variety of deposition techniques such as chemical vapor deposition, RF sputtering, Chemical bath deposition, electrodeposition and molecular beam epitaxial growth have been applied to synthesize functional ceramic thin films with preferred characteristics. Functional ceramics also attract attention of many researchers because they have ability to interact with the surrounding to detect, act upon and generate power. However, by reducing the dimension of the devices, development in terms of sensitivity, proficiency, and portability can be improved. For these reasons micro-electromechanical systems have been widely used in the field of science and technology. Lead zirconate titanate (LZT) a renowned functional ceramic displays a variety of composition and has been applied in a range of ultrasound, supercapacitors, batteries, transducers, actuators and sensor devices (Izyumskaya et al., 2007). Functional metal oxide and halide materials are the hot research topics due to their bonding and structures in the field of electrochemistry and photocatalysis.

As most of the metallic element are reactive towards oxygen, oxides exist in stable single or mixed phases. Oxides is the largest group of ceramic materials that have chemical inertness, good properties at high temperature and resistance to oxidation. As the oxygen is the most electronegative divalent element, most oxides have significant degree of ionic bonding. As a result, they generally have the characteristics of ionic crystals, optical transparency, high electrical resistivity, low thermal conductivity, diamagnetism and chemical stability. There are some exceptions in which oxides of indium and tin are electrically conductive while others such as beryllium oxide have high thermal conductivity.

2.2 Properties of Ceramic Materials

The property of ceramic material is its characteristic features expressed in terms of the measured response to specific imposed stimulus. While ceramics have traditionally been admired for their mechanical and thermal stability, their unique electrical, optical and magnetic properties have become of increasing importance in many key technologies including communications, energy conversion and storage, electronics and automation. Such materials are now classified as electroceramics to distinguish them from other functional ceramics such as advanced functional ceramics.

2.2.1 Electrical Properties

The performance of electroceramic materials and devices depends on the complex interplay between processing, chemistry, structure at many level and device physics and so requires a truly interdisciplinary effort by individuals from many fields. Materials can be categorized in various ways on the basis of their capacity to conduct electricity. Depending upon their capacity to conduct electric current (an ease of flow of electron) ceramic have been classified as conductors, semiconductors and insulators. The borders between the three sets are somewhat adjustable and some overlap happens. There are, however, basic differences between the mechanism of conduction in metals semiconductors and insulators (Hensel, Slocombe, & Edwards, 2015). The electrical features of solid-state materials depend on their band structure. The highest filled electronic state at 0 K is called the Fermi energy E_{f} .


Figure 2.1: Energy level diagrams representing (a) insulators. (b) semiconductors and (c) conductors (Copyright permission from Hensel, et al., 2015)

Figure 2.1 shows that conductor such as copper, tungsten and silver which has a partially filled outermost band. Each copper atom has one 4s electron to make 4s band half filled. Electrons in this band are free to travel when an electric field is applied. However, in the case of magnesium, there is an overlap between the 3s and 3p band. On the other hand in insulators electrons are restricted within the valence band (VB) while conduction band (CB) is totally empty. The band gap, which is of some electron volts, makes it difficult to promote the electron from valence band to conduction band. For semiconductors a small gap splits the wholly filled valence band from an empty CB, because of which electrons can gain enough energy to promote into the empty CB.

Most of the structural ceramics are electric insulators, while some are electroceramics. Semiconducting functional ceramics can be either p-type or n-type depending on the access of number of holes or electrons. They mostly undergo redox reactions, i.e., oxidation-reduction reactions with surroundings and they are highly suitable for gas sensors. Developments in the various subdivisions of electroceramics along the growth of developing technologies. Dielectric materials are electrical insulators, used mainly in capacitors and electrical insulators. For practical uses, they have high electric strength, able to endure high voltages without undergoing depletion and become electrical conductive as well as own low dielectric loss i.e., in an alternating electric field, the electrical energy loss in the form of heat should be lessened. When a potential difference is applied across a dielectric, polarization of charge within the material will take place, while long range movement of ions or electrons cannot occur (Figure 2.2). The polarization disappears as the voltage is removed. If a dielectric is placed between two plates of the capacitor, the total charge already stored in it will change which depends upon the polarizability of the material under an electric field. The change in charge storage is examined by the dielectric constant or permittivity of the ceramic material. High dielectric constants are necessary for high capacity applications.



Figure 2.2: Plolatization of dielectric material by applying electric field

If a material contains polar molecules, they will generally be in random orientations when no electric field is applied. When the electric field is applied, the materials get polarized orienting the dipole moments of polar molecules. This decrease the effective electric field between the plates and will increase the capacitance of parallel plate structure. The dielectric must be a good electric insulator so as to minimize any DC leakage current through a capacitor.

2.2.2 Magnetic Properties

Magnetic materials are classified into five types by their response to externally applied magnetic fields as dimagnetism, paramagnetism, ferromagnetism, antiferromagnetism and ferrimagnetism. This classification based on magnetic properties such as ordering, sign, magnitude and temperature that influence magnetic susceptibility.

Diamagnetic materials have very weak negative susceptibility, typically of the order of -10^{-5} and relative permeability is less than one. These are the materials which do not have native magnetic moment but magnetic field (H) is applied show negative susceptibility and acquire magnetization. The orbital motion of electrons creates tiny atomic current loops, which produce magnetic fields. When an external magnetic field is applied to a material, these current loops will tend to align in such a way as to oppose the applied field (Figure 2.3). This may be observed as an atomic form of Lenz's law: induced magnetic fields tend to oppose the change which produced them.



Figure 2.3: The atomic dipole orientation for a diamagnetic material in presence and absence of magnetic field.

Materials in which this effect is the only magnetic response are called diamagnetic. Diamagnetism is the residual magnetic behavior when materials are neither paramagnetic nor ferromagnetic. Ionic crystals and inert gas atoms are diamagnetic e.g. PbS, FeS₂.

Paramagnetic materials is class of materials, some of the atoms or ions in the material have a net magnetic moment due to unpaired electrons in partially filled orbitals. One of the most important atoms with unpaired electrons is iron. However, the individual magnetic moments do not interact magnetically, and like diamagnetism, the magnetization is zero when the field is removed. In the presence of a field, there is now a partial alignment of the atomic magnetic moments in the direction of the field, resulting in a net positive magnetization and positive susceptibility. The materials show a magnetization which is proportional to the applied magnetic field in which the material is placed. These materials are said to be paramagnetic. These materials show no net magnetic moment in the absence of an applied magnetic field. The presence of a permanent magnetic moment is often the result of unpaired electron spins. In such materials, the magnetic moment is non zero for each atom, but average to zero over many atoms. If a magnetic field is applied across the material and the atoms are free to oscillate, they will associate with the magnetic field, amplifying the strength (Figure 2.4). e.g. O_2 paramagnetic behavior. When a paramagnetic material is placed in a magnetic field, the magnetic moments experience a torque and they tend to orient themselves in the direction of magnetic field. At room temperature, paramagnetic susceptibilities are much less, typically about 10⁻⁵ barely exceeding the diamagnetic susceptibility.

Unlike paramagnetic materials, the atomic moments in these materials exhibit very strong interactions. These interactions are produced by electronic exchange forces and result in a parallel or antiparallel alignment of atomic moments. Exchange forces are very large, equivalent to a field. In addition, the efficiency of the field in aligning the moments is opposed by the randomizing effects of temperature. This results in a temperature dependent susceptibility, known as the Curie Law.



Figure 2.4: The atomic dipole orientation for a paramagnetic materials in the presence and absence of magnetic field.

At normal temperatures and in moderate fields, the paramagnetic susceptibility is small (but larger than the diamagnetic contribution). Unless the temperature is very low (<<100 K) or the field is very high paramagnetic susceptibility is independent of the applied field. Under these conditions, paramagnetic susceptibility is proportional to the total iron content. Many iron bearing minerals are paramagnetic at room temperature. The paramagnetism of the matrix minerals in natural samples can be significant if the concentration of magnetite is very small. In this case, a paramagnetic correction may be needed.

Ferromagnetic materials exhibit parallel alignment of moments resulting in large net magnetization even in the absence of a magnetic field (Figure 2.5). The elements Fe, Ni, and Co and many of their alloys are typical ferromagnetic materials. Two distinct characteristics of ferromagnetic materials are their (a) spontaneous magnetization and (b) magnetic ordering temperature.



Figure 2.5: The atomic dipole orientation for a Ferromagnetic materials.

The *spontaneous magnetization* is the net magnetization that exists inside a uniformly magnetized microscopic volume in the absence of a field. The magnitude of this magnetization, at 0 K, is dependent on the spin magnetic moments of electrons. The saturation magnetization is the maximum induced magnetic moment that can be obtained in a magnetic field (H_{sat}); beyond this field no further increase in magnetization occurs. The difference between spontaneous magnetization and the saturation magnetization has to do with magnetic domains (more about domains later). Saturation magnetization is an intrinsic property, independent of particle size but dependent on temperature. There is a big difference between paramagnetic and ferromagnetic susceptibility. As compared to paramagnetic materials, the magnetization in ferromagnetic materials is saturated in moderate magnetic fields and at high (room-temperature) temperatures:

Even though electronic exchange forces in ferromagnetic materials are very large, thermal energy eventually overcomes the exchange and produces a randomizing effect. This occurs at a particular temperature called the *curie temperature* (T_c). Below the Curie temperature, the ferromagnetic is ordered and above it, disordered. The saturation magnetization goes to zero at the Curie temperature. In addition to the Curie temperature and saturation magnetization, ferromagnets can retain a memory of an applied field once it is removed. This behavior is called hysteresis and a plot of the variation of magnetization with magnetic field is called a hysteresis loop.

Another hysteresis property is the coercivity of remanence (Hr). This is the reverse field which, when applied and then removed, reduces the saturation remanence to zero. It is always larger than the coercive force. The initial susceptibility (χ_0) is the magnetization observed in low fields, on the order of the earth's field (50-100 µT) (Figure 2.6).

The various hysteresis parameters are not solely intrinsic properties but are dependent on grain size, domain state, stresses, and temperature. Because hysteresis parameters are dependent on grain size, they are useful for magnetic grain sizing of natural samples.



Figure 2.6: Hysteresis loop of a ferroelectric (Copyright permission from Shahid, 2009).

Antiferromagnetism involves materials in which atoms, ions, or molecules have permanent ferromagnetic materials. The crystals have domain structure, as in ferromagnetic materials, but alternating ions within a domain have their magnetic moments oriented in opposite directions, so the domain as a whole has zero magnetization, or zero magnetic susceptibility. An example of an antiferromagnetic material is manganese oxide, in which manganese ion has a magnetic moment. Such materials are generally antiferromagnetic at low temperatures. If the sublattice moments are exactly equal but opposite, the net moment is zero. This type of magnetic ordering is called antiferromagnetism (Figure 2.7).



Figure 2.7: The atomic dipole orientation for antiferromagnetic manganese oxide. In ionic compounds, such as oxides, more complex forms of magnetic ordering can occur as a result of the crystal structure (Muralt, 2000). One type of magnetic ordering is call ferrimagnetism (Damjanovic, 1998). A simple representation of the magnetic spins in a ferrimagnetic oxide is shown here. The magnetic structure is composed of two magnetic sublattices (called A and B) separated by oxygens. The exchange interactions are mediated by the oxygen anions. When this happens, the interactions are called indirect or super exchange interactions. The strongest super exchange interactions result in an antiparallel alignment of spins between the two sublattice. In ferrimagnets, the magnetic moments of the sublattices are not equal and result in a net magnetic moment. Ferrimagnetism is therefore similar to ferromagnetism. It exhibits all the hallmarks of ferromagnetic behavior- spontaneous magnetization, Curie temperatures, hysteresis, and remanence. However, ferro- and ferrimagnets have very different magnetic ordering. Like ferromagnetics and antiferromagnetics, there is a domain structure and like antiferromagnetic, alternate magnetic moments are pointing in opposite directions. However, this does not result in complete cancellation of the magnetization of a domain.

This often results if the alternating atoms or ions within domain are different species, with unequal magnetic moments. Magnetite (Fe_3O_4) is a well-known ferrimagnetic material. Indeed, magnetite was considered a ferrimagnet until Neel in the 1940's, provided the theoretical framework for understanding ferrimagnetism (Figure 2.8).



Figure 2.8: The atomic dipole orientation for a Fe (II) and Fe(III) ions in Fe₃O₄

2.2.3 Optical Properties

In a semiconductor, conductor, or insulator the valence electrons occupy the valence band, which is separated from the conductance band, by a forbidden gap of energy (band gap). In a conductor the two bands overlap resulting in the flow of electrons within the conduction band creating an electric current. Insulators have very large band gaps (> 5eV) and do not conduct electricity because electrons cannot be promoted from the VB to CB. However, an insulator can be made to conduct electricity if thermal energy or energy from an externally applied field contributes enough energy for the electrons in the filled valence band to jump to the conduction band. Semiconductors are elements or compounds with a small band gap (\sim 1.4-5.0 eV) that can conduct electricity under some conditions (Figure 2.1). Therefore it is a good medium for the control of electrical current making it very attractive for applications in electronic devices. Additionally, metal oxides display optical

characteristics and their studies have directly showed the ground state electronic structures as well as numerous excitations of charge, spin, orbital, and lattice degrees of freedom. The optical features of metal oxides have broaden their field of technological applications including optical and optoelectronic devices by applying the optical responses, magneto-optical effect, photo-refractive effect and elasto-optic effect. Moreover, the conductivity of a semiconductor depends on the current or voltage applied to a control electrode or on the intensity of irradiation by infrared (IR), visible light, ultraviolet (UV) or X-ray.

2.3 Ceramic Thin Films

Thin film technology is the basis of astonishing development in solid state electronics (Kern, 2012). The utility of the optical properties of ceramic or semiconductor films, and scientific interest about the activity of two-dimensional solids has been responsible for the great interest in the area of science and technology of the thin films. Thin film studies depend on thickness, geometry, and structure of the film (Prellier, Singh, & Murugavel, 2005). The thickness of thin film ranges between tenths of nanometer (nm) and several micrometers (µm). So the properties of thin film particularly can be controlled by the thickness parameter. Thin films are especially suitable for applications in the field of microelectronics, optoelectronic, photonic, magnetic devices, integrated optics, IR detectors, interference filters, solar cells, polarizer's, temperature controller in satellite, superconducting films, anticorrosive and decorative coatings (Muralt, 2000). Amorphous and crystalline thin films have been produced mostly by deposition, either physical or chemical methods. The vast varieties of thin film materials, their deposition techniques and fabrication methods, spectroscopic characterization and optical characterization inquiries that are used to produce the devices (Niesen & De Guire, 2001). It is possible to categorize these techniques in two ways. (a) Physical method and (b) Chemical method.

Physical method includes the fabrication methods which depends on the evaporation or discharge of the material from a source such as evaporation and sputtering. Structureproperty relationships are the important characteristics of such devices and basis of thin film technologies. Primarily the performance and economy of thin film depends on the deposition techniques in a specific chemical reaction. Thus chemical reactions may depend on thermal effects, as in vapour phase deposition and thermal growth. However, in all these cases a definite chemical reaction is required to get the final film. In order to classified deposition of films by chemical methods into two categories. The first of these category is concerned with the chemical formation of the film from medium involved are electroplating, chemical reduction plating and vapour phase deposition. While second one is that of production of thin film from the precursor ingredients like iodization, gaseous iodization (Hass, Francombe, & Hoffman, 2013), thermal growth, sputtering ion beam implantation (Windischmann, 1987), chemical vapour deposition (CVD) (Minegishi et al., 1997) and vacuum evaporation (Hass, et al., 2013). The techniques are summarized in table 2.1 are often capable of forming films. The films thickness of 1 µm or less are defined as thin films while thick films have thickness of 1 µm or more.

Furthermore, there are several techniques which are only able to produce thick films such as screen printing (Ito et al., 2007), glazing, electrophoretic deposition (EPD) (Kawachi et al., 2001), flame spraying and painting (Kawachi, et al., 2001). Controlled morphology and thickness of thin films can be used for optical and photoelectrochemical studies (Kawachi, et al., 2001; Hongkang Wang et al., 2014). Multiple layers of thin films can also enhance the optical efficiency (H. Wang, et al., 2014). Ceramic thin films extensively applied for solar cells (Chopra, Paulson, & Dutta, 2004; Poortmans & Arkhipov, 2006), photovoltaic devices (Izaki et al., 2007), Dye sensitizes solar cell (DSSC) (Chopra, et al., 2004; Mor, Shankar, Paulose, Varghese, & Grimes, 2006), gas sensor (Suchea, Christoulakis, Moschovis, Katsarakis, & Kiriakidis, 2006; Traversa, Gnappi, Montenero, & Gusmano, 1996), fuel cells (Minh, 1993), supercapacitors (Yao et al., 2011) and in rechargeable batteries (Bates et al., 1993; Dudney, 2005). Semiconductor ceramic thin films are in the form of oxides, sulphides and nitrides have attract the attention of researchers in the last few decades (Suresh, 2013). These semiconducting films are highly important for electrochemical applications. Metal oxide and metal halide thin films are also used in making transparent transistors, which are of low cost, stable and environment and economic friendly. On behalf of phase separation, ceramic oxide thin films can be classified as:

- i) Solid solution ceramic thin films
- ii) Composite ceramic thin films.

2.3.1 Solid Solution Ceramic Thin Films

These ceramic thin films are mixture of two crystalline solid materials that exist together as a new crystalline solid, or crystal lattice. It can be done by mixing of two solids in their molten state at temperature higher than their melting point and then cooling that produce a new form of solid or by fabricating vapors of the precursor materials onto the substrates to deposit thin films. As compared to liquids solids have different criteria of mutual solubility, depending on their crystalline structure and chemical properties, which define how their atoms fix together in the combined crystal lattice. The combined lattice can be substitutional, in which the atoms of one crystal substitute those of the other, or interstitial, in which the atoms inhabit vacant position in the lattice other crystal. The solids may be soluble to some extent or entire range of relative concentrations, result a crystal with variable properties as compared to starting precursor (Handoko & Goh, 2013; Mansoor, Ehsan, et al., 2013). This offers a way to modify the properties of the solid solution for different applications. Solid solutions of ceramic semiconductors are of remarkable technological importance, as in the mixture of aluminum arsenide (AlAs), gallium arsenide (GaAs) with gallium phosphide (GaP), or indium arsenide (InAs) (Askeland & Wright, 2015; Fulay & Lee, 2013; Voitsekhovskii, Drobyazko, & Mityurev, 1995). The properties of these solid solutions can be altered to final product by modifying the relative proportions of the starting materials; for example, the band gap for mixtures of InAs and GaAs can be adjusted in any range between the value for pure InAs (0.36 electron volt (eV) and that for pure GaAs (1.4 eV), depending on required electrical and optical properties of materials. This approach makes ceramic semiconducting solid solutions efficient towards optical and electronic devices, including solar cells, transistors, light-emitting diodes (LEDs), infrared detectors, and semiconductor lasers. Similar examples of solid solution ceramic thin films are PbS_xSe_{1-x}, Cd_xZn_{1-x}S, Bi-Sb, Cr-Me-Si, MnCo₂O₄ (K. J. Kim & Heo, 2012; Kud, Ieremenko, Likhoded, Uvarova, & Zyatkevich, 2012; Z. Liu et al., 2013; Noro, Sato, & Kagechika, 1993; Raviprakash, Bangera, & Shivakumar, 2009; Uusi-Esko, Rautama, Laitinen, Sajavaara, & Karppinen, 2010).

2.3.2 Composites Ceramic Thin Films

These are materials prepared from two or more different materials with distinct physical or chemical properties, that when mixed, produce a material with properties changed from the isolated components (Ehsan, Naeem, Khaledi, Sohail, Saeed, et al., 2016; Ehsan, Naeem, McKee, et al., 2016). Each component remains dissimilar within the final product. Using this explanation, large number of engineering materials can be found in this class. For example when glass fibers are embedded in a polymer produces fiber glass sheet which is a composite.

Composite materials possess two phases. First one is the reinforcing phase like fibers, particles or sheets that are embedded in the second phase called the matrix phase. Both of the phases can be ceramic, metal or polymer. Mostly, matrix materials comprises of tough

or ductile materials whereas reinforcing are strong materials having low density. Some common composite thin films are TiO₂–Cu₂O used for superhydrophobic coatings (Aytug et al., 2014), Cu₂O–CoO composites employed for optical band gap. The incorporation of reduced graphene oxide (rGO) on a TiO₂ surface has been used for photoelectrochemical (PEC) studies (Aytug, et al., 2014) and ZnS–SiO₂ composite ceramics utilized thermal shock resistance materials (G.-S. Kim, Shin, Seo, & Do Kim, 2008).

2.4 Thin Film Deposition Techniques

Several fabrication techniques have been established over time as the concern in thin film formation has continued to build up (Hartnagel, Dawar, Jain, & Jagadish, 1995). In broad terms these techniques can be categorized as either physical or chemical deposition techniques (Humphreys et al., 1990; Mahan, 2000; R. Mane & Lokhande, 2000; Nair & Nair, 1991). The benefits and problems pertaining to these methodologies are summarized in Table 2.1.

20

Thin Films Deposition Techniques			
PHYSICAL		CHEMICAL	
Sputtering	Evaporation	Gas Phase	Liquid Phase
1) Glow discharge	1) Vacuum	1) Chemical vapour	1) Electro-deposition
DC Sputtering	evaporation	deposition (CVD)	
2) Triode	2) Resistive heating	2) Atmospheric	2) Chemical bath
Sputtering	evaporation	pressure CVD	deposition (CBD)
		(APCVD)	3) Arrested
			precipitation technique
			(APT)
2) Cotton	2) Elash Exercise		(1) Electrologo
5) Getter	5) Flash Evaporation	CVD (LPCVD)	deposition
Sputtering			deposition
4) Radio Frequency	4) Electron beam	4) Metal-organic	5) Anodisation
sputtering	evaporation	CVD (MO-CVD)	
5) Magnetron	5) Laser evaporation	5) Photo enhanced	6) Sol-gel
sputtering		CVD (PHCVD)	7) Spin Coating
6) Ion beam	6) Reactive	6) Laser induced	8) Spray-pyrolysis
sputtering	Evaporation	CVD (PCVD)	technique (SPT)
7) A.C sputtering	7) Arc Evaporation	7) Electron	9) Ultrasonic SPT
	8) Molecular beam	enhanced CVD	10) Polymer assisted
	epitaxy (MBE)		deposition (PAD)

2.4.1 Electrophoretic Deposition (EPD)

The term 'electrodeposition' is often used to refer to either electroplating or electrophoretic deposition (EPD). It usually refers to the former term which exhibits the difference between the two processes deposition process (Santos et al., 2015). EPD is one of the colloidal method in semiconductor or ceramic formation and has benefits of less deposition time, require simple apparatus, slight limit on the shape of substrate, no need of binder burn out as the green coating do not contain organics. EPD also control the thickness and morphology of a deposited film through simple modification of the deposition time and applied potential. In EPD process, charged powder particles, dispersed or suspended in a liquid medium are attracted and deposited on a conductive substrate of opposite charge in the presence of electric field. There are two types of electrophoretic deposition depending on which electrode the deposition occurs. When the particles are positively charged, the deposition (Zhitomirsky, 1998). The deposition of negatively charged particles happens on an anode is named as *anodic electrophoretic deposition* (Hanaor et al., 2011) (Figure 2.9).

The EPD method has been used effectively for thick film of silica, nano size zeolite membrane (Shan et al., 2004), hydroxyapatite coating on metal substrate for biomedical applications (Pang & Zhitomirsky, 2005), luminescent materials, high-Tc superconducting films, gas diffusion electrodes and sensors (Hossein-Babaei & Taghibakhsh, 2000), multi-layer composites (Chang et al., 2010), glass and ceramic matrix composites by infiltration of ceramic particles onto fiber fabrics (A. R. Boccaccini, Kaya, & Chawla, 2001), oxide nanorods (Cao, 2004), carbon nanotube film (Aldo R. Boccaccini et al., 2006), functionally graded ceramics, layered ceramics, superconductors

and piezoelectric materials (Besra, Compson, & Liu, 2006; Besra, Zha, & Liu, 2006; Besra & Liu, 2007).



Figure 2.9: Schematic representation of the two types of cathodic electrodeposition processes: (a) electroplating and (b) electrophoretic deposition (EPD) (Copyright permission from Santos, et al., 2015).

2.4.1.1 Factors Influencing EPD

The EPD technique involve charged particles in a suspension being deposited on substrate in the presence of an applied electric field. Two groups of parameters define the features of this method related to; (i) the suspension, and (ii) the process including the physical factors such as nature of the electrodes and electrical conditions including voltage/intensity relationship, deposition time, etc.

(i) Effect of deposition time

Deposition rate for a fixed applied field decreases with increased or prolonged deposition time. A typical deposition characteristics of ZnO coating on copper electrode at different applied potentials, with increasing time of deposition (Wong & Searson, 1999). It is clearly evident that the deposition is linear during the initial time of deposition. But as more and more time is allowed, the deposition rate decreases and attains a plateau at very high deposition times. In a constant voltage EPD, this is expected because: while the potential difference between the electrodes is maintained constant, the electric field influencing electrophoresis decreases with deposition time because of the formation of an insulating layer of ceramic particles on the electrode surface. But during the initial period of EPD, there is generally a linear relationship between deposition mass and time.

(ii) Applied voltage

For a higher applied field, which may cause turbulence in the suspension, the coating may be disturbed by flows in the surrounding medium, even during its deposition. In addition, particles can move so fast that they cannot find enough time to sit in their best positions to form a close-packed structure. Finally, in high field situations, lateral motion of the particles once deposited, also are restricted on the surface of the already deposited layer, because higher applied potential exerts more pressure on particle flux and movement, the applied field affects the deposition rate and the structure of the deposit. It is observed that the unstable current density effects the surface morphology of deposited films. It was found that quantity of YSZ deposition from the n-propanol increased with increasing applied voltage (Jia et al., 2006). However, the microstructures, texture and surface morphologies of the EPD deposited film were found to be smooth at low voltages and rough at high voltage.

(iii) Concentration of solid in suspension

The concentration of solid in the suspension play a significant part for multi-component EPD. In some cases, although each of the particle species have same sign of surface charge, they could deposit at different rates depending on the volume fraction of solids in the suspension. If the volume fraction of solids is high, the powders deposit at an equal rate. If however, the volume fraction of solids is low, the particles can deposit at rates proportional to their individual electrophoretic mobility.

(iv) Conductivity of substrate

The uniformity and conductivity of substrate electrode is an important parameter critical to the quality of the deposition of films by EPD. Peng and Liu (Peng & Liu, 2001) noticed that low conductivity of the La_{0.9}Sr_{0.1}MnO₃ (LSM) substrate deposit the non-uniform green films by EPD. Chen and Liu (F. Chen & Liu, 2001) observed that when LSM (LaSrMnO₃) or LSM–YSZ composite pellets have been used as conductive substrate for EPD, the deposition rate of non-uniform YSZ (yittria-stabilized zirconia) film was slow. Therefore, the green YSZ film obtained was of high quality.

2.4.2 Chemical Vapour Deposition (CVD)

2.4.2.1 Basic Principles of CVD

Chemical Vapour Deposition (CVD) is a main process that has found wide application in modern industry for the production of microelectronic devices, optical, decorative coatings, in order to produce a broad range of new materials, such as ceramic based thin films. The CVD process of creating a film has to be reproducible and controllable. As a result, the intrinsic properties such as the purity, composition, thickness, adhesion, microstructure and surface morphology have to be reproducible for the same reactor conditions.

Conventional CVD is an extensively-used method to growth of thin films of material of interest on substrate. The technique involves different steps including transfer of activated precursor by the inert carrier gas (argon/nitrogen/air/oxygen) to the reactor zone where the substrates are placed (Figure 2.10). Once the precursor approaches reactor zone it undergoes systematic reaction either in gaseous phase or onto the substrate surface. Both the possibilities of reactions result in the formation of thin film on the surface of substrate. Thus, CVD reactions can be homogenous or may be heterogeneous. Most CVD reactions are likely to be heterogeneous because they occur at the surface of substrate rather than gaseous or vapour phase. Homogenous process involves nucleation of particles in gaseous

phase resulting in powder coating that neither strongly adheres to substrate nor completely pure (Özgür et al., 2005).



Figure 2.10: A representation of chemical vapour deposition (CVD) involving physical changes: [a] precursor reaction in vapour state; [b] diffusion of precursors on the surface of substrate; [c] precursor adsorptions and reaction on substrate; [d] elimination of volatile by-product; [e] adatoms get diffused on substrate sites; [f] nucleation and formation of thin film on substrate.

CVD technique is now considered as an important process in many industrial fields and solid-state microelectronics. Thin films of conductors (W, Mo, Al etc), semiconductors (Si, GaAs etc.) and insulators, dielectrics (oxides, silicates, and nitrides) are broadly used in the progress of solid state devices (Cahill, Goodson, & Majumdar, 2002). Most of these CVD reactions were used for the coating of the substrates at low pressure, often at high temperatures (Pierson, 1999). Recent developments emphasis on low or moderate temperature for deposition through CVD, such as plasma-CVD, and photo-CVD, MOCVD, and atomic layer deposition (ALD). These assisted techniques of chemical vapour deposition are widely applied in semiconductor industry, microelectronics, hard coatings corrosion and wear resistance applications at reduced fabrication temperatures thus facilitating utilization of substrates in a broader spectrum.

2.4.2.2 Variations of CVD

The improvement of CVD technique has developed in a many directions, leads to variety of variations of the process. The process selected for the deposition of any target material

is depending on the precursors used and type of thin film required. Some of the variations of CVD are plasma enhanced CVD (PECVD) (Hozumi & Takai, 1997), metal– organic CVD (MOCVD) (J. L. Yang, An, Park, Yi, & Choi, 2004), atmospheric pressure CVD (APCVD) (Manning, Parkin, Pemble, Sheel, & Vernardou, 2004), low pressure CVD (LPCVD) (X. Li et al., 2011), liquid injection CVD (Jones et al., 1998), laser Assisted CVD (LACVD) (Herman, 1989) and molecular beam epitaxy (Y. Chen et al., 1997). In this work we will through on two of significant variation of CVD known as Aerosol Assisted Chemical vapour deposition (AACVD) and electric field directed aerosol assisted chemical vapour deposition (EFDAACVD), are the latest modified assistance of CVD.

2.4.2.3 Aerosol-Assisted Chemical Vapour Deposition (AACVD)

Aerosol-assisted chemical vapour deposition (AACVD) is a liquid-phase variation of the conventional CVD process that involves first preparation of a clear soluble solution of precursor in some suitable volatile solvent from which an aerosol particles are formed by using ultrasonic humidifier (nebulizer), generating a mist of precursor solution, which is then transferred to a hot chamber of furnace (reactor), where the substrates are already placed, by a carrier gas. Once the aerosols approaches substrate in hot zone of reactor due to high temperature solvent gets evaporated and leaving behind the vapourized precursor in its gaseous state, followed by the deposition onto the substrate resulting in the formation of target material.

One main development of AACVD over conventional CVD techniques is any precursor that can be easily soluble in any volatile (preferably organic) solvent is required. The parameter for volatile precursor is excluded (Marchand, Hassan, Parkin, & Carmalt, 2013). However, inorganic molecular precursors are very stable and less sensitive towards air; possess less volatility, therefore require elevated temperatures and low pressure for fabrication. Fabrication of gold films possess robust and strongly adhered by AACVD making it suitable to work at industrial scale (Hannon, Kodambaka, Ross, & Tromp, 2006). Hydrogen tetrachloroaurate, [HAuCl₄], was not suitable for conventional CVD due to its low decomposition temperature (175 °C) and poor volatility. However, [HAuCl₄] has revealed to be the best precursor in the growth of gold films via AACVD (Palgrave & Parkin, 2007). Another important advantage of AACVD arises from use of an ultrasonic humidifier to produce aerosol particles of precursor solution rather than focusing on the evaporation of precursors to transport it to the reaction chamber. This makes it simple to transport the precursor, thus becomes economical promising deposition method. Another favorable feature of AACVD is the utilization of carrier gas to deliver the precursor droplets to CVD reactor which requires adequate pressure to deliver the aerosols. For this purpose, the optimum gas flow rate during the process has to be established enabling increased the deposition rate due to the higher mass transfer of precursor on to the substrate. In a nutshell, AACVD is a versatile method to create thin films of a multicomponent material with controlled stoichiometry by chemical reaction of precursor on the substrate surface.

2.4.2.4 Deposition Conditions and their Influence on Morphology

The deposition conditions or parameters employed in a system during deposition are important to produce thin films with the required architecture and morphology. During an AACVD, the structure and morphology of the deposited thin films can be changed depends upon a variation in certain factors/conditions, for example the use of precursor, temperature, solvent and substrate. Field emission scanning electron microscopy (FE-SEM) is an important technique for defining the morphology of thin films by changing these factors. There are some main highlighted variables from which and how we can determine the variation in morphology.

a) Precursor

The selection of a precursor or complex plays a vital part in the deposition of thin film. It has been revealed that when different precursor were used for the fabrication of zinc oxide (ZnO) thin films via AACVD process, different topography, architectures and surface morphologies were obtained as shown in Figure 2.11. Walters et al. used Zn (acac)₂ as basic precursor for the growth of ZnO thin films (Walters & Parkin, 2009). They reported that the surface morphology of pristine ZnO films formed at 450 °C was round shape. However, hexagonal shaped nanoparticles (Figure 2.11a,b) could have been the subsequent growth of ZnO crystallites from the round shaped particles. In spite of using a normal precursor, Hamid et al. effectively fabricated ZnO films by using a zinc complex, $Zn_6(OAc)_8(\mu-OH)_2(dmae)_2(dmaeH)_2$ (OAc = acetate and dmaeH = N,N'-dimethylaminoethanol) at a temperature of 350 °C via AACVD process (Hamid et al., 2008).



Figure 2.11: (a) SEM images of thin ZnO thin films fabricated by using different precursors (a,b) zinc acetate at 450 °C (Copyright permission from Walters & Parkin, 2009), (c) Zn₆(OAc)₈(μ-OH)₂(dmae)₂(dmaeH)₂ at 350 °C (Hamid, et al., 2008) and (d) Zn₆ (OAc)₈(μ-O)₂(dmae)₄ (OAc) at 400 °C (Copyright permission from M. Shahid, et al., 2012) by AACVD on FTO sunbstrate.

b) Deposition Temperature

The temperature can influence the texture of a film fabricated by AACVD. For example, Shahid et al. reported that when ZnO films were fabricated at various temperatures different morphologies had been experienced (M. Shahid, et al., 2012). Films fabricated at 250 °C had small, poorly defined individual grains in the range of $0.1-0.3 \mu m$, while relatively large individual grains size of $0.2-0.7 \mu m$ were observed for the films fabricated at 475 °C. At temperatures of 325 and 400 °C, the films were more dense and flatter, with uniformly discrete grains as shown in Figure 2.12. The sphere-shaped particles had a good orientation and definite grain boundaries. The various morphologies can be observed for the ZnO thin films, as shown in Figure 2.11 c, and it is establish that the zinc oxide thin film had a dense, compact, continuous, and smooth morphology. The spherical shaped particles have good orientation and clear well-defined grain boundaries.



Figure 2.12: Surface morphology of ZnO thin films deposited from Zinc precursor at (a) 250, (b) 325, (c) 400 and (d) 475 °C on glass substrate (Copyright permission from M. Shahid, et al., 2012).

Furthermore, Shahid et al. also used a novel hexanuclear zinc complex, Zn_6 (OAc)₈(μ -O)₂(dmae)₄ (1) (OAc = acetato, dmae = N,N-dimethyl aminoethanolato) for the growth of ZnO films (M. Shahid et al., 2012). They stated that the ZnO film exhibited a more regular look, as compactly packed rectangular-shaped particles that were uniformly distributed, as shown in Figure 2.11d. They also reported that the production of well-developed isolated crystalline particles was due to the homogeneous decomposition pathway in AACVD approach. The formation of a well-defined ZnO nanostructure rather than the aggregation of nanoparticles is also well supported by the deposition of ZnO thin films using single source precursors (SSP) (AzadáMalik, 1994; Ying Wang, Li, Zhou, Zu, & Deng, 2011). These interpretations showed that the morphology of the semiconductor thin film significantly depend upon the choice of the precursors

The effect of solvents on the morphologies of films grown by AACVD can be important and depending on the precursor. Titanium dioxide (TiO₂) thin films deposited by a AACVD using titanium (IV) isopropoxide (TTIP) with various solvents (hexane, ethanol, methanol, isopropanol and dichloromethane) which were used to deposit on glass and steel substrates at 550 °C as shown in Figure 2.13 (Edusi, Sankar, & Parkin, 2012).



Figure 2.13: Different morphologies of TiO₂ thin films fabricated by using (a) 100% ethanol, (b) 100% methanol, (c) 10% methanol and 90% ethanol, and (d) 25% methanol and 75% ethanol from (a) chloroform and (b) chloroform/toluene (1:1) on steel via AACVD Copyright permission from (Edusi, et al., 2012).

Edusi, et al. reported that the solvent effected the phase of the fabricated TiO_2 film, it display either an anatase or rutile phase, or a combination of the two phases. As demonstrated in Figure 2.13, the influence of solvents on the phase of TiO_2 phase has been explained via AACVD. In case of methanol solvents under same conditions titania

films produce the rutile phase, while the other solvents only produced the anatase phase. More surprisingly, a mixture of ethanol and methanol as the solvent produced only the rutile phase at a mixture as low as 90% ethanol and 10% methanol as shown in Figure 2.13. This displays that the methanol has a directing influence on the formation of the rutile phase. They also exhibited that the TiO₂ films grown on steel substrates are photochemical active, and the rutile phase is less active than the anatase phase. Moreover, Panjawi et al. described the AACVD deposited titania thin films on gas-sensor substrates at 450 °C by using solution of titanium isopropoxide in toluene (N. Panjawi, A. Naik, M. E. Warwick, G. Hyett, & R. Binions, 2012).

d) Effect of Electric Field on AACCVD

Previous studies already reported the effect of an electric field during CVD, with crystallographic orientation, microstructure, and functional properties being the most influenced features (Naik et al., 2013; N. Panjawi, A. Naik, M. E. A. Warwick, G. Hyett, & R. Binions, 2012; Shaw, Parkin, Pratt, & Williams, 2005). This effect was also observed for titania thin films (Romero & Binions, 2013). These changes in morphology are thought to be a result of the interaction between a permanent or induced dipole in the CVD precursor species (or partially decomposed gas phase and/or surface species (Romero & Binions, 2013)) and the applied electric field and the application of EFDAACVD reactions (Crane, Warwick, Smith, Furlan, & Binions, 2011). It has previously been observed that there has been an enhancement of growth rate due to the introduction of an electric field in the deposition process. This has been attributed to the increase of kinetic energy of aerosol droplets which, in turn, increases the likelihood of nucleation on the substrate, or through bond activation due to the molecule being stretched along the direction of its dipole (Naik, et al., 2013), however in this instance it is unlikely that there is a strong interaction between the electric field and gas-phase species as the

TTIP precursor does not have a permanent dipole, as such gas-phase effects are not expected to dominate in this work.



Figure 2.14: FE-SEM of TiO₂ films fabricated via EFD-AACVD of Ti(O^{*i*}Pr)₄ solution in toluene at 450 °C by applying an electric field: **A**) no field. **B**) 1.11×10^4 , **C**) 2.22×10^4 , **D**) 1.11×10^5 , **E**) 2.22×10^5 , **F**) 4.44×10^5 and **G**) 6.67×10^5 Vm⁻¹ (Copyright permission from Panjawi, et al., 2012)

It is possible that the aerosol droplet may be charged: As the droplet approaches the heated substrate surface, the solvent evaporates and interaction with the electric field ceases. It is more likely, however, that the film growth is dominated by the interaction of the electric field with species on the substrate, most likely through the formation of surface dipoles, which direct the crystal growth via a strong localized electric field (Panjawi, et al., 2012; Romero et al., 2015). In this work, they examined the effect of the potential difference on

the architecture and surface morphology of the fabricated films. The electric field applied across the electrodes led to some differences in the morphology of the deposited films (Figure. 2.14B–G). Increasing the potential between 1.11×10^4 and 2.22×10^4 Vm⁻¹ (Figure 2.14B and C) shows small 5 µm diameter of the sphere-shaped aggregates. The size of octahedral shaped particles was also uniformly decreased. By increasing the electric field strength (Figure 2.14C–G) larger aggregates are formed, and separate agglomerates were difficult to distinguish in the thick film.

2.5 Precursors for Ceramic Thin Films

The precursors can be widely categorized into three types.

- i) The inorganic precursors, which do not contain carbon.
- The metal-organic precursors which contain organic ligands, but do not have metal-carbon bonds
- iii) The organometallic precursors, which contain both organic ligands and metalcarbon bonds.

These kinds of precursors contain one or more atoms or group of atoms that are components of the target material. Target materials are produced by decomposition of precursor during synthesis process. Metal-organic and organometallic precursors have brought a great attention due to their ability to improve the structure, stoichiometry and the ligand framework, e.g. if a same metal of interest is surrounded by different types of hydrocarbons will finally change the chemical reactivity as well as physical properties of the different precursors for the same target material. Thus controlling these parameters is important for good precursor engineering.



Figure 2.15: Coordination modes of alkoxide ligands



Figure 2.16: Coordination modes of carboxylate ligands.

Coordination modes of metal with alkoxide and carboxylate ligands are described in Figure 2.15 and Figure 2.16. Inorganic molecular precursors include binary hydrides or halides, owe chemical simplicity but they do not give similar degrees of freedom as in case of organo-metallic precursors. These inorganic precursors can also leave some halide contaminations in the target material at normal temperature of deposition.

2.5.1 Precursor Requirements for CVD

The struggle to prepare precursors is considered important that have a combination of exact characteristics which make them suitable for the basic of ceramic thin film deposition. Achievement of a precursor for adsorption and deposition depends on the grade of these characteristics and potential. However, the problem starts when the precursor preferably starts to react in vapour phase rather than on the surface of substrate during thin film fabrication by AACVD. This difficulty can be diminished by lessening the precursor concentration in a reaction chamber. Furthermore, the droplets that are created by reaction in vapour phase can contaminate the thin film. So it is compulsory to use precursor that preferably reacts or decomposes on substrate surface rather than in gaseous state during AACVD technique. For these types of systems precursor must be able to tolerate high temperature for short period of time before reaching the tube furnace for decomposition. So the necessary requirements for precursor design to fabricate the ceramic thin films have to meet the following properties.

Solubility: For film fabrication by CVD the first and primary demand for a precursor is to soluble in some appropriate, less dense and low boiling solvent. Which can allow the solution in making aerosol droplets to travel in the reactor region. The precursors should also have good volatility and easily travelled to the reactor zone.

Stability: A suitable precursor is the one which is stable in air and can be stored under normal conditions. Thus, it minimize the need of any inert or special conditions during film deposition. The precursor must be chemically and thermally stable during thermal decomposition to avoid premature decomposition and inimitable film growth.

Toxicity: Precursors with non-toxic or less toxic nature is always favored, if not then special storage and safety will be required during CVD.

Precursor Purity: One of the important demand is to synthesize pure precursor to improve fabrication of thin film that is free from residual impurities. Then it should be purified through suitable purification methods during the preparation of precursors. The decomposition of precursor should be clean, thus no residual contaminations can be incorporated in the ceramic thin film.

Precursor Reactivity: A suitable precursor for CVD is the one which decomposes on the substrate surface rather than in gaseous form. For good deposition it is necessary to heat the substrate before precursor decomposition in the tube furnace.

Synthesis in bulk: If a precursor is appropriate for CVD of thin film then it must also be easy to synthesize it in large amount without facing main difficulties.

Environment and cost effective: The precursor should be non-toxic, non-pyrophyric, nonflammable and non-explosive It should also be recyclable and its decomposition is either free from carbon dioxide (CO₂) emission or with very less quantity which can be controlled from environmental pollution. At the same time the CVD precursor must be easy to synthesize at low cost with high yield and stability in both air and moisture environment.

2.6 Characterization Techniques

2.6.1 Characterization of Precursors

2.6.1.1 Microanalysis

Microanalysis or elemental analysis is the qualitative and quantitative identification of chemical elements (atoms or ions) in a specimen. Results of elemental analysis face difficulties in determining the exact of stoichiometry heterometallic complexes due to the alteration in ratio of metals and ligands. However, by the help of atomic absorption analysis of metallic elements, the CHN results may become helpful to obtain the composition of the heterometallic compounds. The validation of these results are further confirmed by single crystal X-ray analysis.

2.6.1.2 Infrared Spectroscopy

Infrared (IR) spectroscopy is a useful method for the determination of organic and inorganic moieties present in a sample. The IR spectrum is recorded by passing IR radiation through a sample and measured the absorption frequencies that correspond with the structural properties of molecules. The different functional groups attached to a molecule produce characteristics absorption in IR spectrum. The IR spectroscopy is known technique for the structural determination in the samples. The IR spectrum ranges from 14,000 cm⁻¹ to 10 cm⁻¹. The region of most consideration for chemical interpretation is the mid-infrared regions (4000-400cm⁻¹). Which determines changes in vibrational energies within the molecules. The far-infrared region (400-10cm⁻¹) esteemed for molecules including inorganic compounds but needs somewhat particular laboratory techniques. IR spectra represents valuable data for the compounds with functionalized ligands, which face difficulties in structural determination of heterometallic schemes because of the screening of significant bands. The IR spectra becomes very complex because of crowded ligand climate and definite absorption band could not easily determined. The O-H group nature either bonded with central metal or may be a part of ligand can be known by the absorption frequency. The coordination performance of carboxylate to metal can be planned by identifying the factor $\Delta v = (v(COO)_{asym})$ and $v(\text{COO}^{-})_{\text{sym}}$ by IR spectroscopy, if Δv is less than 200 cm⁻¹ the carboxylate behave as a bridging ligand. This technique also has been used to find out the presence of numerous alkoxy groups as every metal ligand bond produces a characteristic absorption such as $v_{OMe} = 1185$, $v_{OEt} = 1020$, $v_{OPr} = 839,1124$ and 1158 cm^{-1} , respectively in different mixed metal alkoxides. The terminal and bridging alkoxy groups in various heterobimetallic species may be determined on the behalf of IR absorption bands present in the area around 1022-1181 and 939-1072 cm⁻¹, respectively. Heterometallic diketonates shows two absorption bands around 1565-1573 due to C=O and 1510-1514 cm⁻¹ due to C=O stretching vibrations. The presence of the absorption frequency due to bonded "dmae" bridging moiety appeared between 1070-1075 cm⁻¹ varied from those reported for free "DmaeH" at 1040 cm⁻¹. A band identified in the region less than 550 cm⁻¹ may be relate to M-O stretching vibrational band for the samples.

In case of inorganic compounds IR spectroscopy is very useful technique to determining the nature, and added impurities both in powder and thin films. FTIR was also useful for the evaluation of Hydrogen (H) and moisture contents on deposited films. The IR spectroscopy has verified to be a helpful analytical method for industrial and environmental areas.

2.6.1.3 Thermogravimetric Analysis (TGA)

Thermogravimetric analysis (TGA) is an analytical method used to approach the thermal stability of the materials. It also helps to obtain the components by observing the weight changes that occur when a sample is heated. Thermogravimetric measurements are generally carried out in air or an inert atmosphere (He, Ar and N₂) and weight loss is calculated as a function of raising temperature. Furthermore, differential scanning calorimetry (DSC) instrument can also record the temperature differences or heat flow between the sample and reference pans. DSC can be used to calculate the melting point, enthalpy, energy released or absorbed through chemical reaction during heating process. During TG analysis, when materials are heated they can lose weight whether by a sample drying process. In this study TGA analysis is performed to examine the pyrolysis temperature of the complex to give stable metal oxide or halide end product.

2.6.1.4 X-ray Crystallography

X-ray crystallography is a device that can see inside of crystals to determine their atomic and molecular structure. Which allow us to completely identify their structures, geometries and unit cell size. Based on the diffraction pattern obtained from X-ray scattering off the orderly arranged atoms or molecules in the crystal, the electron density map can be refined to generate valuable information about their atomic positions, bond length and angles and disorder and various other information. In single crystal X-ray diffraction the crystalline atoms cause a beam of incident X-rays to diffract into many specific directions, construct a diffraction pattern of spots called reflection. Each reflection relates to one set of planes within the crystal and the density of electrons is obtained from position and brightness of the several reflections collected as the crystal is gradually rotated in X-ray beam. For single crystals with a sufficient purity and uniformity, X-ray diffraction data can evaluate the mean of bond angle and bond length in few thousands of an angstrom and within a few tenth of a degree, respectively. X-ray crystallography is useful in determining identified materials, analyzing novel materials and differentiating materials that appear alike by other experiments. The single X-ray crystallography technique includes three steps to model the crystal structure. First step is to develop an appropriate crystal of the material under investigation. The crystal should be effectively large, stoichiometry pure, regular structure and free of defects like cracks. In second step rising of crystal in an intense beam of monochromatic X-ray, produce the arrangement of reflections. The third step is refinement of the thousands of the reflection intensities composed by the full reflection of the crystal. The reflection data are collected computationally with analogous chemical details to develop and refine a model of the location of atoms with in the crystal structure.

2.6.2 Characterization of Thin Films

2.6.2.1 X-ray Powder Diffractions

X-ray powder diffraction is a rapid technique primarily to identify crystalline phase and degree of crystallinity of thin films and powder. The diffraction pattern allows the detection of phase composition and texture of the film, favored orientation and size of crystallites and existence of film stress. By scanning the sample through a range of 20 angles, all possible diffraction directions of the lattice should be achieved due to the random orientation of the thin films. It is difficult to identify the crystal structure for the high symmetry crystals. A large library of spectra of famous compounds is available at JCPDS (Joint Committie for Powder Diffraction Standards) files. When the powder pattern of the sample are collected and miler indices, d-spacing and lines intensity are displayed, these can be matched with the standard reference pattern of identified compounds in the library.

2.6.2.2 Raman Spectroscopy

Raman spectroscopy is an efficient and non-destructive spectroscopic technique based on the scattering of monochromatic light. Photons of the monochromatic light are absorbed by the samples and then remitted. Frequency of reemitted photons is shifted up and down in comparison with the original monochromatic frequency called a raman shift. This shift provides information about vibrational, rotational and other low frequency modes in the molecules. Raman shift in wavelength of the scattered radiation that provides the chemical and structural information. Raman shifted photons can be of either higher or lower energy, depending upon the vibrational state of the molecule under study.
2.6.2.3 X-ray Photoelectron Spectroscopy

X-ray photoelectron spectroscopy (XPS) is an important and widely used surface and subsurface analysis technique in a many fields of study in physics and chemistry such as microelectronics, heterogeneous catalysis, environmental geochemistry etc. XPS investigates the energy distribution of electrons removed from the solids by irradiation of X-ray and the photoelectric effect: the electrons contain information about chemical oxidation state, electronic structure, binding energy and elemental composition of the compounds being studied. Thus, surface composition as well as the electronic environment can be determined. Since the photoelectrons examined come only from the topmost atomic layer of the solid surface being analyzed, the method is powerful tool for studying the interfacial phenomena at the solid-solid and solid-gas boundaries. XPS is usually accomplished by exciting the surface with mono-energetic Al $k\alpha$ x-rays causing photoelectrons to be escaped from the sample surface. An electron energy analyzer is used to measure the energy of the ejected photoelectrons. From the binding energy and intensity of a photoelectron peak, the elemental identity, chemical state, and quantity of a detected element can be identified. A typical XPS spectrum is a plot of the number of electrons detected versus the binding energy of the electrons identified. Each element produces a characteristic set of XPS peaks at specific binding energy values that directly find each element that exists in or on the surface of the material being studied. The XPS data explains about surface layers or thin film structures is important for many industrial and research applications where surface or thin film composition plays an important part in performance including: nanomaterials, photovoltaics, catalysis, corrosion, adhesion, electronic devices and packaging, magnetic media, display technology, surface treatments and thin film coatings used for several applications.

2.6.2.4 BET Analysis

Brunauer–Emmett–Teller (BET) study provides a detailed specific surface area estimation of materials by nitrogen multilayer adsorption measured as a function of relative pressure using a fully automated analyzer. The technique includes external area and pore area evaluations to investigate the total specific surface area in m²/g yielding important information to study the effects of surface porosity and particle size in many applications. While Barrett-Joyner-Halenda (BJH) analysis can also be used to find out the pore area and specific pore volume using adsorption and desorption method. This method characterizes pore size distribution independent of external area due to particle size of the sample.

2.6.2.5 Field Emission Scanning Electron Microscope (FE-SEM) and Energy Dispersive X-ray Analysis (EDX)

Field emission scanning electron microscope (FE-SEM) uses a focused electron analysis to extract structural chemical data from required area in a thin film. The high resolution spectra of FE-SEM make it a useful tool to characterize a broad range of materials at several nm and µm. FESEM offers high magnification with greater depth then optical microscopes. FESEM images may be distorted by the surface potential which improves an insulator level defects at sharp contours. Nonconductive samples are decorated by conductive layer of Au, Pt or carbon to disperse the surface charge. FE-SEM images at high magnification describe the surface morphology or architecture and film thickness.

The most usual extension to the FE-SEM is the energy dispersive x-ray spectrometer (EDX). The energy level for EDX systems is from 1.0 to 220 KeV, which detects the elemental composition or chemical characterization in the composite thin films. When EDX detectors with thin protective layers functioned in high vaccum systems, allow the

analysis of the lighter elements down to B. The analysis depth depending on the path length of the X-ray not on the primary electron beam. As a results EDX signals may arise from the depth of 0.5 μ m or more. Due to pulse counting mode of EDX system, it has ability to detect the characteristic X-ray of all elements above F in the periodic table. However, EDX takes a lesser time to scan the complete spectrum as compared to wavelength dispersive X-ray analyzer. The simultaneous development of the highbrightness, high beam current thermal field emission gun-SEM has provided an electronoptical platform that ideally matches the performance of the silicon drift detector (SDD-EDS).

2.7 Electrochemical Applications of Ceramic Thin Films

Micro and nanostructured thin films of metal oxides and metal halides for electrochemical applications has been recognized recently, but the number of studies is increasing suddenly. The recent importance of renewable energy sources has sparked research on very fundamental and applied levels. The most prominent applications in Li-ion batteries, fuel cells, gas sensors and photovoltaic devices. The most important drawback is the material, which is either very expensive noble metal or lacking in performance and stability. It is therefore one of the main future task to identify a material which is cost effective, stable and environment friendly. Ceramic thin films deposited by AACVD, EFDAACVD and EPD are therefore the potential candidate to test their activity and stability for application in electrochemical devices, some of these are discussed below.

2.7.1 Batteries and Supercapacitors

Many chemically deposited metal oxide thin films including ruthenium oxide, iridium oxide, manganese oxide, cobalt oxide, nickel oxide, tin oxide, iron oxide, pervoskites, ferrites, etc. have been applied in supercapacitors.(Fujimoto, Kuwata, Matsuda,

Kawamura, & Kang, 2015; C. D. Lokhande, D. P. Dubal, & O.-S. Joo, 2011) The thin film deposition methods involving the growth from solution are called as chemical methods. Depending on applications, one would prefer thin films which have a special texture, low grain boundary density, or smooth surfaces. Amongst the numerous metal oxide materials, only RuO_2 , MnO_2 , NiO and Co_3O_4 thin film based systems have gained more attention due to superior electrochemical capacitor response. Apart from the scientific quest for high capacitance of metal oxide thin films, the long-term cycling stability of these electrodes is a technological issue that must be addressed to evaluate the commercial development of metal oxide thin film based aqueous supercapacitors. Other issues such as self-discharge, corrosion of the current collector, low temperature performance etc should also be studied. Considering that metal oxide thin film based supercapacitor technology is still in its beginning, future research and development should ultimately yield high-performance, low cost, and safe energy storage devices. Synthesis of phase-pure SnO₂ hierarchical structures with different morphologies such as nanorods, nanosheets, and nanospheres, as well as their modifications by doping and compositing with other materials. They studied the design of SnO₂-based nanostructures with improved performance in the field of lithium-ion batteries (LIBs), supercapacitors and energy conversion performance (J. S. Chen & Lou, 2013; Q. Zhao, Ma, Zhang, Wang, & Xu, 2015). SnO₂-based nanostructures, such as anode materials, demonstrate superior cycle performance of lithium storage by doping (J. S. Chen & Lou, 2013). In the supercapacitors, the prepared SnO₂-based nanostructures provide fast ion and electron transfer, which led to a prominent supercapacitor performance. Therefore, SnO₂-based nanostructures with a proper design can possess advanced physical and chemical properties, which are vital for a variety of energy and environment applications.

Nanostructured V_2O_5 has potential application in the fields of lithium-ion batteries, the as-prepared vanadium hollow microspheres can be calcined into crystalline V_2O_5 without

changing their morphologies. These V_2O_5 products exhibit improved electrochemical properties when they are used as cathode material in lithium-ion batteries and show good application potential. The prepared V_2O_5 exhibits desirable electrochemical properties such as high capacity and remarkable reversibility when it is used as cathode material in a lithium-ion battery (A. M. Cao, Hu, Liang, & Wan, 2005). Mesoporous Co₃O₄ nanowire arrays (Y. Li, Tan, & Wu, 2008), Mn₃O₄–graphene hybrid (Hailiang Wang et al., 2010), Fe₃O₄-based Cu nano-architecture (Taberna, Mitra, Poizot, Simon, & Tarascon, 2006), reduced graphene oxide/Fe₃O₄ (Guangmin Zhou et al., 2010; X. Zhu, Zhu, Murali, Stoller, & Ruoff, 2011) electrode nanocomposites were employed as a high-capacity and rate capability anode material for lithium ion batteries applications.

2.7.2 Fuel Cells

Fuel cells, due to their high efficiency and low environmental effect, have been paid more attention in these years. The fuel cell is the most potential tool for automotive, portable, and stationary applications. Although hydrogen is an ideal fuel for polymer electrolyte membrane fuel cells (PEMFC), it is very dangerous to store it under high pressure. The hydrogen production is still challenging. To avoid these drawbacks, the direct methanol fuel cell (DMFC) has been developed with a simplified structural system, using aqueous methanol as the fuel. It is widely established that carbon monoxide (CO) species produced in the process of methanol electro-oxidation are the main poisoning intermediate that slows down the oxidation kinetics and rate of reaction. To resolve this issue, Pt-based binary catalysts (PtRu (Koper, Lukkien, Jansen, & van Santen, 1999) and (Q. Lu, Yang, Zhuang, & Lu, 2005), PtMo (Russell, Ball, Maniguet, & Thompsett, 2007), PtSn (Y. Guo, Zheng, & Huang, 2008), etc.) and ternary catalyst (PtRuNi (Moreno, Chinarro, Pérez, & Jurado, 2007)) have been established to enhance the catalytic activity of Pt through bifunctional mechanism. Besides this, it has been found that Pt with metal oxides

like (Rolison, Hagans, Swider, & Long, 1999) TiO₂ (Song, Qiu, Guo, & Li, 2008), Al₂O₃, ZrO₂ (Ribeiro, Mendes, Perez, Souza, & Schmal, 2008), MoO₂ (Ioroi et al., 2006), etc. can efficiently improve the electro-oxidation of methanol and reduce the CO poisoning. Firstly, metal oxides stabilize Pt particle dispersion, which increase the surface area of the catalyst. Secondly, metal oxide have a good ability for storing and releasing oxygen, which plays a vital role in CO_{ads} (adsorbed CO) methanol oxidation. At the same time, the low cost and the abundance of metal oxides can help to reduce the price of DMFC. Therefore, metal oxides are suitable additives for Pt catalysts. Direct methanol fuel cells (DMFCs) have some benefits such as high energy density, low temperature operation and convenient operation (Y. Huang et al., 2014), thus they have been considered as a potential candidate for power generation in portable electronic devices and hybrid electric vehicles.

After the hydrothermal reaction, (graphene oxide) GO sheets evolved into (reduced graphene oxide) RGO sheets and well-crystallized Mn₃O₄ nanoparticles uniformly distribute on RGO sheets, followed by the spontaneous deposition of Pt on Mn₃O₄/RGO surface via the galvanic replacement process between Mn₃O₄ and PtCl₄²⁻ (Y. Huang, et al., 2014). By combining the advantages from the small-sized and well-dispersed Pt nanoparticles, the possible synergetic effect from the ternary components, and the strong metal-support interaction, the Pt/Mn₃O₄/RGO catalyst exhibited higher electrochemical surface area (ECSA), better tolerance toward CO and outstanding electrocatalytic activity than the Pt/RGO catalyst, and long-time stability than the conventional Pt/C catalyst. Thus, this work supplied an important and efficient way to build up various two-dimensional sandwich-like nanomaterials that provide an important platform for many advanced industrial fields, such as electrocatalysis, photocatalysis and sensors. Moreover, metal oxides (CeO₂, TiO₂ and SnO₂) and Pt nanoparticles were successively decorated on carbon nanotubes (CNT). The effect of metal oxides on the catalytic behaviour of Pt for

electro-oxidation of methanol has been studied by cyclic voltammetry (CV), chronoamperometry (CA) and electrochemical impedance spectroscopy (EIS) methods, purpose to establish the most suitable catalyst for fuel cells. Different Pt/MO₂/CNT catalysts (M = Ce, Ti, Sn) were synthesized and the electrocatalytic activity in respect to the electro-oxidation of methanol in H₂SO₄ solution were examined. The CV revealed that the current density of the oxidation peak increases for Pt/CeO₂/CNT as compared to Pt/CNT catalysts, showed the highest catalytic activity. The kinetics of methanol oxidation, rate of reaction, maximum frequency, charge recombination life time were studied by using electrochemical impedance spectroscopy. It was establish that metal oxides can promote the electro-oxidation of CO_{ads}, which was verified by a decrease of the charge-transfer resistance at a low potential region. The accumulation process of CO_{ads} was not observed as it was on the Pt/CNT electrode. In addition, the decreased rate of charge-transfer resistance was determined by the metal oxides added, which indicated different reaction activity of CO_{ads} oxidation with hydroxyl groups on various metal oxides (Yuan, Guo, Qiu, Zhu, & Chen, 2009). In the present investigation, the potential of formation of solid electrolyte thin film on ceramic substrates has been demonstrated using spray pyrolysis technique (SPT). Analysis of (gadolinia-doped ceria/ galdoliniumdoped ceria) GDC/GDC structure revealed that electrolyte-grade substrates could be coated with ultra-thin protective layer using SPT to avoid the interfacial reactions. Besides, the studies on GDC films deposited on NiO-GDC substrate depicted that the electrolyte-grade GDC films could also be deposited using SPT. However, some modification, as mentioned, should be employed in the process. Further, the choice of material for solid electrolyte film i.e. GDC and NiO-GDC as substrate (precursor composite ceramic anode) would enable to utilize the prepared structure (GDC/NiO-GDC) for fabrication half-cell in low temperature solid oxide fuel cells (SOFCs). Electrical characterization of GDC/NiO-GDC structure showed that there is only a nominal decrease in overall ionic conduction of the structure over the bare substrate, indicating good quality film/substrate interface. Such synthesized structures along with a layer of suitable cathode material, could find promising application in low temperature SOFCs (Myung, Ko, Lee, Lee, & Hyun, 2012). In practical application of direct methanol fuel cells (DMFC), methanol concentration plays a vital role. In this regard effect of methanol concentration was studied by varying the concentration of methanol in the presence of CuO–1.5ZrO₂ composite oxide film modified Pt electrode deposited by AACVD at a scan rate of 50 mV s⁻¹ in the presence of 0.1 M KOH can be noticed that anodic peak current increases and the anodic peak potential have a slightly shifted to positive potential while increase in the methanol content due to the saturation of active catalytic sites at the CuO–1.5ZrO₂ composite oxide film modified Pt electrode surface.

2.7.3 Electrochemical Sensor

Electrocatalysts are occasionally employed in the development of electrochemical sensors. It has recently been shown that composite electrodes of transition-metal oxides are electrocatalytically active for range of different analytes. Lead (IV) oxide is a noted electrocatalyst and is characterized with good electrical conductivity, mechanical stability and chemical inertness, and high oxygen evolution overpotential. Lead dioxide electrodes are particularly attractive since they do not require voltage pretreatment to attain their electrocatalytic activity (Biljana Šljukić, Craig E. Banks, Alison Crossley, & Richard G. Compton, 2007). These properties suggest applications in a variety of fields, particularly the generation of oxygen (Ho, Filho, Simpraga, & Conway, 1994) and ozone (Feng, Johnson, Lowery, & Carey, 1994) and electro-oxidation of organic compounds, both for their synthesis (Amadelli, De Battisti, Girenko, Kovalyov, & Velichenko, 2000; Treimer, Feng, Scholten, Johnson, & Davenport, 2001) and degradation of organic contaminants

in water (Grimm, Bessarabov, Maier, Storck, & Sanderson, 1998; Hyde, Jacobs, & Compton, 2004; Saterlay et al., 2001).

Transition metals have attracted the attention of researchers due to their multiple oxidation which make them suitable candidates for electron-transfer processes (El Khatib & Abdel Hameed, 2011; Rafiee & Fakhari, 2013). Because transition metallic nanoparticles (NPs) increase their surface area, enhance mass transport and hold good biocompatibility, the metallic nanoparticles can be used as modification for sensors and biosensors (Lin, Lin, & Chen, 2013). Especially, transition metal oxides combine physical with chemical properties, which make them become the promising electrode materials (Azaceta et al., 2012). Nanomaterials are gaining increasing interest in the development of several research fields. Among various nanomaterials, nickel oxide (NiO) and copper oxide (CuO) are attractive electro-catalysts in electrochemical different catalytic application (Arredondo Valdez, García Jiménez, Gutiérrez Granados, & Ponce de León, 2012; Ripolles-Sanchis, Guerrero, Azaceta, Tena-Zaera, & Garcia-Belmonte, 2013). Due to relatively low cost and high catalytic activity, NiO and CuO can be ideal modifying agent. Some effort have been made on determination of glucose (Lin, et al., 2013) and (X. Wang, Liu, & Zhang, 2014), H₂O₂ (Gao & Liu, 2015) and other biomolecules (S. Zhou et al., 2013) by using nanostructured NiO and CuO materials (B. Liu et al., 2016). CuO-2TiO₂ electrode in electrochemical sensor was investigated towards the detection of NO_2^- ions and the electrode showed the limit of detection (LoD) of 0.0166 μ M with linear range of 10 to 200 µM. Beyond this, present sensor electrode is more selective towards NO₂⁻ ions in the presence of other common interfering species. This CuO-2TiO₂ electrode is more ideal candidate for the selective and sensitive detection of toxic NO₂⁻ ions from environmental remediation aspect (Ehsan, Naeem, McKee, et al., 2016).

Furthermore, Pt-based GO modified nano-catalysts not only maximize the availability of nano-sized electro-active surface area for electron transfer but also provide better mass transport of reactants to the electro-catalyst and sensors for dopamine (DA), ascorbic acid (AA), uric acid (UA), catecholamines and acetaminophen (AP) (Alothman, Bukhari, Wabaidur, & Haider, 2010; Atta, El-Kady, & Galal, 2010; S. A. Kumar, Tang, & Chen, 2008; B. Liu, et al., 2016). The NiO-CuO/Graphene/Glassy carbon electrode enhanced the oxidation peak currents towards DA, acetaminophen (AP) and tryptophan (Trp) and the negative shift of the oxidation peak potentials, which were attributed to the incorporation of transition metal oxides providing larger specific surface and electrocatalytic activity (B. Liu, et al., 2016). This modified electrode exhibited that the linear response ranges for detecting DA, AC and Trp were 0.5-20 µM, 4-400 µM and 0.3-40 µM, respectively, and the detection limits were 0.17 µM, 1.33 µM and 0.1 µM (S/N=3). The proposed method for GO-La/CPE electrode provides an effective linear calibration ranges of 0.01–0.1 µM and 0.1–400.0 µM, low detection limit of 0.32 nM, good repeatability and stability. Thus, the developed GO-La/CPE sensor presents good potential application in the selective detection of DA (F. Ye et al., 2015). CoTiO₃-TiO₂ electrode in electrochemical sensors has been investigated towards the detection of DA. The results indicate that the CoTiO₃-TiO₂ electrode showed good electrocatalytic activity for DA with the limit of detection (LoD) of 0.083 μ M and a linear range of 20 to 300 μ M (Ehsan, Naeem, Khaledi, Sohail, Hakeem Saeed, et al., 2016). The improvement of various nanostructured metal-oxide such as ZnO, CuO, CuO₂, MnO₂, Mn₂O₃, TiO₂, CeO₂, SiO₂, ZrO₂ have been used as glucose biosensors (M. M. Rahman, Ahammad, Jin, Ahn, & Lee, 2010). The study on H₂O₂ detection is of practical significance for both academic and industrial purposes. Electrochemistry can offer simple, rapid, sensitive, and cost effective means since H₂O₂ is an electroactive molecule (W. Chen, Cai, Ren, Wen, & Zhao, 2012).

2.7.4 Photoelectrochemical (PEC) performance of ceramic thin films

Now a days the progress of clean energy has become a main attention among the scientists. Water using sunlight has attracted attention as a new renewable energy source to generate hydrogen gas with negligible pollution. Because the other energy sources such as fossil fuel, coal, oil and natural gas is quickly being reduced. Hydrogen gas has developed as a new alternate energy supply that offers several benefits as compared to other fuels, including a decrease in global warming carbon dioxide (CO₂) emissions, developments in air quality and the capability to reduce the energy crises. On one hand, the wide use of fossil fuel leads to a decline in natural resources. While on the other hand, the energy requirements have enormous effect on society include financial troubles and environmental pollution. Since climate alertness has raised in society, the hydrogen generation has suffered difficulties in the form of greenhouse effect and global warming issues. Hydrogen is secondary and alternate energy carrier that allows the normal energies such as coal, oil, gas and nuclear fission to join the clean sustainable energies. Furthermore, hydrogen has distinct properties that make it a potential candidate for future clean energy, which are described below:

- i. It is recyclable and can be efficiently converted into electricity
- ii. Abundantly available water is a raw material for hydrogen generation.
- iii. It can be kept as a liquid, gas, or solid in the form of metal hydrides.
- iv. It can be easily carried through large distances by using pipelines or by other ways.
- v. It can be transformed into other energy forms than any other fuel.
- vi. As an energy carrier, hydrogen is environment friendly and economical.

The quest to split water into oxygen and hydrogen has explored a huge variety of nano/micro photcatalyst materials and solar energy techniques that can actively perform this ambitious goal (Shi et al., 2015; Hisatomi, Kubota, & Domen, 2014). However,

highly efficient hydrogen production by photocatalytic water splitting is limited by many factors such as non-ideal photocatalyst materials, complex thermodynamics of the reactions and ambiguous mechanisms and therefore is still far from industrialization levels (Ma et al., 2014; Martin et al., 2015). Continuous efforts are being made to resolve these problems and to make solar photocatalytic hydrogen production feasible. A variety of photoactive materials have been designed and developed with the aim to fix the main PEC obstacles such as proper conduction/valence band position, narrowing of the band gap to harness visible light, fast electron/hole pair separation/transportation (Baker & Kamat, 2009; Gonçalves, et al., 2012; Le Formal, et al., 2010; Leung, et al., 2010; G. Li, et al., 2013; Momeni, et al., 2015; Sivula, et al., 2010; J. Su, et al., 2010; M. Wang, et al., 2013; Yan, et al., 2012), however, these extensive studies could not find an individual material which can overcome all these issues at once. The main criteria for photocatalyst material is low cost, environmentally friendly, high efficiency and stability under visible light irradiation (Serpone & Emeline, 2012; Walter et al., 2010). TiO₂ is a strong candidate due to its high stability in aqueous solutions and high photovoltaic and photocatalytic activity (Nowotny, Bak, Nowotny, & Sheppard, 2007; Fujishima, Zhang, & Tryk, 2008) but it is restricted to work under UV light due to its large a band gap (3-3.2 eV) limitations.

Photoelectrochemical water splitting cells require semiconductor materials with following characteristics:

- i. An ideal optical band gap.
- ii. Holes diffusion length should be small
- iii. Able to support rapid charge transfer at a semiconductor/electrolyte interface
- iv. Show stability to photocorrosion
- v. Space-charge layer should be relatively large.

In the photoelectrochemical mechanism, when light is absorbed by the semiconductors metal oxide electron hole pairs are generated as a result photolysis of water take place and oxidation reduction reaction occurs at anode and cathode for the production of hydrogen and oxygen.

$$H_2 O \xrightarrow{h\nu} H_2 + 1/2O_2 \tag{2.1}$$

$$2hv \rightarrow 2e^{-} + 2h^{+}$$
 (2.2)
 $2h^{+} + H_{2}O \rightarrow 1/2O_{2(g)} + 2H^{+}$ (2.3)

The electron and holes get separated due to potential produced at interface of the semiconductor-electrolyte due to band bending. The holes migrate to the interface and reacts with the water to produce oxygen.

$$2e^- + 2H^+ \to H_{2(g)} \tag{2.4}$$



Figure 2.17: Illustration of a photoelectrochemical cell that consists of a semiconducting photoanode.

The electron move to an external circuit and arrive at interface between counter electrode and electrolyte, where hydrogen ion is reduced to hydrogen as gas. These overall photoinduced charge separation obtained for the semiconductor in the photoelectrochemical cells are schematically shown in Figure 2.17.



Figure 2.18: Schematic representation for the photo induced charge-separation process at metal oxide thin film in a photoelectrochemical cell (Copyright permission from Naeem et al., 2015).

Overall photoelectrochemical decomposition of water is shown in Figure 2.18. Numerous PEC cells using thin film electrodes have been established especially for the cleavage of water. But suitable electrodes with ideal band gap and stable towards photocorrosion are still under research.

An optical band gap is the energy gap, usually apply to the energy difference (in electron volts) between the top of the valence band (VB) and the bottom of the conduction band (CB) in semiconductors and insulators. The optical band gap describes that which part of the solar spectrum a photovoltaic cell absorbs. In case of semiconductors, there band gap is always one of two types, a *direct band gap* or an *indirect band gap*. The band gap is called "direct" if the momentum of electrons and holes is the same in both the CB and the VB; an electron can directly emit a photon (Figure 2.19). In case of "indirect" gap, a photon cannot be emitted because the electron must travel through an intermediate state and transfer momentum to the crystal lattice (phonon).



Figure 2.19: Optical transitions in semiconductors with a direct and an indirect bandgap. The indirect transition requires assistance of a phonon with energy hv (Copyright permission from Seo & Hoffmann, 1999).

The optical band gap of thin films can be examined by the Tauc equation, if the top of the VB and bottom of the CB are expected to have a parabolic shape. The Tauc's equation is

$$\alpha = \mathbf{A}(hv - \mathbf{E}_{g})^{\gamma}/hv$$

where, α is the linear absorption coefficient of the material, hv is the energy of photon, A is a proportionality constant and γ is a constant depending on the band-gap nature; $\gamma = 1/2$ for direct band gap and $\gamma = 2$ for indirect band gap (Seo & Hoffmann, 1999).

The water splitting potential is 1.23 V (G = +237.7 KJ/mol). Which relates to photon below about 1000 nm and covers a large part of spectrum. For water splitting reaction to be thermodynamically favorable, the band gap of the semiconductor phorocatalyst should have these reduction potentials. The conduction band should have higher energy (more negative potential) than the hydrogen evolution potential (H₂/H⁺) and the valence band should be lower in energy (more positive potential than the oxygen evolution potential (H₂O/O₂). So electrons can lower their energy being transferred to hydrogen ions in solution and holes lower their energy being transferred to water molecules through a short circuited reaction and balancing the charges transferred to the solution. The final results are H_2 and O_2 molecules. If the position of valance and conduction band energy state is not achieved an external bias has to be applied in order to promote the photo-oxidation process. Figure 2.20 shows band levels of various semiconductor materials to fulfil the requirement for the PEC cell. This means the photocatalytic materials have a very strong water splitting ability to enhance the photoelestrochemical performance.



Figure 2.20: Relationship between band structure of semiconductor and redox potentials of water splitting (Copyright permission from S. Choudhary et al., 2012).
Furthermore, photocatalytic behavior under visible light could be attained by defect engineering, doping of non-metal, combining with other semiconductor (Dhanalakshmi, et al., 2013) and decoration of noble metal nanoparticles (Pandikumar, et al., 2010; Jinlong Zhang, et al., 2010) results in better interfacial charge transfer, thus reducing the charge recombination and decrease in band gap. Defect engineering indicates controlled introduction of innate defects, such as vacancies, interstitials, and antisites, while doping implies controlled introduction of impurities into the crystal lattice (Djurisic, et al., 2014).
Therefore, the photocatalysis process takes place by moving of an electron from noble metal to semiconductor due to surface plasmon resonance effect (SPR) (Figure: 2.21).



Figure 2.21: Charge transfer mechanism between Au nanoparticles and TiO₂ in visble and UV light (Copyright permission from F. Su et al., 2013).

The performance of electro ceramic materials and devices depends on the complex interplay between processing, chemistry, structure at many levels and device physics and so requires truly interdisciplinary effort by individuals from many fields.

CHAPTER 3: MATERIALS AND METHODS

3.1 General Consideration

All the manipulations were carried out under an inert atmosphere of dry argon, using Schlenk tubes and vacuum line attached to a RZ 6 ROTARY VANE PUMP (Model: 698132). All flasks are evacuated and then purged with argon at least three times prior to use, with external heat applied where considered necessary. Liquid air sensitive reagents were transferred to Schlenk tube by using cannula filter. Most of the chemicals and reagents used such as SnCl₂(anhydrous), Y(OAc)₃. xH₂O, Mn(OAc)₂, Co(OAc)₂.4H₂O, Zn(OAc)₂.2H₂O, Cd(OAc)₂.2H₂O, Pb(OAc)₄, Ti(OPro)₄, Mg(OAc)₂.4H₂O, Ag(OAc), Cu(OAc)_{2.2}H₂O, Ni(OAc)_{2.2}H₂O, Fe(OAc)₂, CuI, Pb(NO₃)₂, KI, Triethylamine, N,N-Dimethylaminoethanol (dmaeH), Trifluoroacetic acid (TFAH) and sodium were purchased from Sigma Aldrich. The solvents like tetrahydrofuran (THF) and toluene were rigorously dried on sodium benzophenoate and distilled immediately before use. N,N-Dimethylaminoethanol (dmaeH) was purified by refluxing over K₂CO₃ for 10 hrs and distilled immediately before use. The melting point was determined in a capillary tube using an electrothermal melting point apparatus; model MP.D Mitamura Riken Kogyo (Japan). The elemental analysis were performed using Leco CHNS 932. FT-IR spectra were recorded on an attenuated total reflectance (ATR) instrument (4000-400 cm⁻¹, resolution 4 cm⁻¹). The controlled thermal analysis was investigated using a METTLER TOLEDO TGA/ SDTA 851e Thermogravimetric Analyzer with a computer interface. The ¹H -NMR were recorded by JEOL DELTA2 NMR Spectrometer at field strength of 400 MHz using deuterated chloroform (CDCl₃) and dimethyl sulfoxide (DMSO-d6) as solvent. The thermal measurements were carried out in an alumina crucible under an atmosphere of flowing nitrogen gas (25 cm³ min⁻¹) with a heating rate of 10 °C min⁻¹.

The surface morphology and cross-sectional view of thin films were determined by using a field-emission gun scanning electron microscope (FESEM, FEI Quanta 400) coupled with Energy Dispersive X-ray spectrometer EDX INCA Energy 200 (Oxford Inst.) at an accelerating voltage of 10-20 kV and a working distance of 3-9 mm. The phase purity and crystallanity were characterized using X-ray diffraction (XRD) on a D8 Advance X-Ray Diffractometer- Bruker AXS using Cu-K α radiation ($\lambda = 1.542$ Å) at a voltage of 40 kV and current of 40 mA at ambient temperature). Raman spectra of the thin films were acquired using a Renishaw inVia Raman microscope with green laser excitation (532 nm). The UV-visible spectrum of the thin film was measured on a Lambda 35 Perkin-Elmer UV-visible spectrophotometer in the wavelength range of 300-900 nm and the film thickness was also obtained by using profilometer KLA Tencore P-6 surface profiler. The PEC studies of thin film electrodes were recorded by using a electrochemical workstation with a conventional three-electrode system. The thin films were used as a working electrode, platinum as a counter and Ag/AgCl as a reference electrode. For photocurrent measurement, the metal oxide thin films were dipped into the supporting electrolyte (0.1 M Na₂SO₄ and 1M NaOH) and irradiated with a 150-W xenon arc lamp (Newport, Model 69907) containing a simulated AM 1.5G filter. The effective area of the film was adjusted to 1×1 cm. Frequency response analysis (FRA) software was used in the EIS experimental and simulation experiments while general purpose electrochemical software (GPES) was used in the linear scan voltammetry (LSV) by Autolab PGSTAT-302N. The scan rate for LSV was 50 mV s⁻¹ between -0.2 V to 1V while the EIS measurements were carried out at a frequency range of 100 kHz-10 mHz.

3.2 Syntheses

3.2.1 Synthesis of [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1)

Complex (1) was prepared by mixing stoichiometric amounts of 0.50g (2.50 mmol) of Cu(CH₃COO)₂·H₂O and 1.49mL (5.03mmol) of Ti(OCH(CH₃)₂)₄ followed by the addition of 1.14mL (10.05mmol) of CF₃COOH in 25mL of THF in a 50mL Schlenk tube. The reaction mixture was stirred for 4h and solvent was evacuated under vacuum to obtain a green powder which was dissolved in THF. The resulting transparent clear green solution was cannula-filtered and placed at room temperature for overnight to obtain green block shaped crystals of precursor (1) in 70% yield. Mp: 225 °C (decomposition). Elemental analysis, (Found: C, 27.96; H, 2.87. C₄₄H₅₈F₂₄O₂₉Cu₂Ti₄ requires C, 28.89; H, 3.17 %). IR: ν_{max}/cm^{-1} 3290br, 1715s, 1671s, 1544m, 1471s, 1442w, 1197s, 1146s, 1054w, 1025s, 891s, 797s, 722s, 682w, 623w, 581w, 522s. TGA: 51-134 °C (11.1% wt. loss); 139-240 °C (25.8% wt. loss); 241-277 °C (14.0% wt. loss), 280-500 °C (22.3% wt. loss) (Residual mass of 26.80%); (Cal. for CuO-2TiO₂ 26.18%).

3.2.2 Synthesis of [Co₂Ti₄(µ-O)₆(TFA)₈(THF)₆]·THF (2)

Complex (2) was prepared by mixing stoichiometric amounts of 0.50 g (2.0 mmol) of $Co(CH_3COO)_2$ ·4(H₂O) and 1.19 mL (4.0 mmol) of Ti(OCH(CH₃)₂)₄ followed by the addition of 1.21 mL (16.0 mmol) of CF₃COOH in 25 mL of THF in a 50mL Schlenk tube. The reaction mixture was stirred for 4h and solvent was evacuated under vacuum to obtain a red powder which was again dissolved in THF. The resulting transparent clear red solution was cannula-filtered and placed at room temperature for 2 days to obtain the red block shaped crystals of complex (2) in 75% yield. Mp: 195 °C (decomposition). Elemental analysis, (Found: C, 26.98; H, 2.17. C₄₄H₅₄F₂₄O₂₉Co₂Ti₄ requires C, 28.89; H, 2.97 %). IR: v_{max}/cm^{-1} 2989w,

2904w, 1717s, 1681s, 1469s, 1388w, 1329w, 1198s, 1148s, 1025w, 1038w, 899w, 792s, 722s, 681w, 654w, 618s, 585w, 493s, 474s. TGA: 50-95 °C (1.53% wt. loss); 100-180 °C (7.2% wt. loss); 181-225 °C (23.6% wt. loss), 250-500 °C (40.17% wt. loss) (Residual mass of 27.50%); (Cal. for CoTiO₃-TiO₂ 25.80%).

3.2.3 Synthesis of [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (3)

Complex (3) was isolated by mixing stoichiometric amounts of 0.50g (2.33 mmol) of Mg(OAc)₂·4H₂O and 1.38mL (4.66mmol) of Ti(^{*i*}Pro)₄ followed by the addition of 0.70mL (9.36 mmol) of TFAH in 25mL of THF in a 50mL Schlenk tube. The reaction mixture was stirred for 4 hours and solvent was evacuated under vacuum to obtain a white powder which was re-dissolved in THF. The resulting transparent solution was cannula-filtered and placed at room temperature overnight to obtain colourless block shape crystals of complex (3) in 75% yield. Mp: 220 °C analysis, (decomposition). Elemental (Found: C. 27.06: H. 2.77. C44H58F24O29Mg2Ti4 requires C, 28.89; H, 3.17 %. IR: vmax/cm⁻¹ 3318br, 2988w, 1721w, 1636s, 1453s, 1192s, 1143s, 1034s, 845s, 797s, 722s, 619s, 509w, 480w. TGA: 73-130 °C (3.6 % wt. loss); 135-235 °C (19.0 % wt. loss); 238-575 °C (56.5 % wt. loss), (Residual mass of 20.9 %); (Cal. for MgTi₂O₅ 20.6%).

3.2.4 Synthesis of [Mn(dmae)₂(TFA)₄] (4)

0.40 g (2.31 mmol) of Mn(CH₃COO)₂ and 0.5ml (6.2mmol) of trifluoroacetic acid were added to 50ml Schlenk tube containing 20ml of THF under argon atmosphere. The mixture was stirred for 6 h to obtain a clear solution. The solvent was then evaporated under vacuum to obtain a powder which was re-dissolved in 5 ml of THF followed by the addition of 0.228mL (2.28 mmol) N, N-dimethyl-2-aminoethanol in a 50mL Schlenk tube. The resulting transparent solution was cannula-filtered and placed at -10 °C for one week to obtain the transparent crystals of complex (**4**) in 70% yield. Crystals suitable for single crystal X-ray analysis were grown from THF solution. m.p: 83 °C (decomposition). Elemental analysis: % calculated (found) for [Mn(dmae)₂(TFA)₄] C, 21.11 (20.83), H, 1.77 (1.69), N, 2.05 (1.95). IR (cm⁻¹): 1728(s), 1635(s), 1444(m), 1420(s), 1391(w), 1177(s), 1130(s), 1074(s), 1048(m), 986(s), 852(m), 727(s), 600(m), 502(m). TGA: 179-260°C (72.77% wt. loss) and 260-550 °C (7.06% wt. loss); (Residual mass of 20.40%); (Cal. for Mn₂O₃ 23.10%).

3.2.5 Synthesis of [Sn(dmae)(OAc)]₂ (5)

A solution of 0.97g (0.40 mmol) of bis(dimethylaminoethanolato)tin(II), Sn(dmae)₂, (Wakeshima & Kijima, 1972) prepared as reported earlier,(Wakeshima & Kijima, 1972) in 10 mL of toluene was transferred to a suspension of 0.10 g Y(OAc)₃. xH₂O in 10 mL of toluene. The reaction mixture was then stirred at room temperature for 6 h for the completion of the reaction. Filtration through a cannula gave a clear white solution which was evaporated to dryness under vacuum, and the solid residue was re-dissolved in 5 mL of toluene to give a 65% yield of white crystals after 5 days at -10°C. mp: 147°C. Micro analysis for [Sn((dmae) OAc)]2: Calculated (found) % C, 27.10 (27.28); H, 4.90 (5.04); N, 5.28(5.12). Selected FT-IR absorption (cm⁻¹): 2810w, (NCH₃); 1615s, (C= 0); 593s, (Sn- O); H1NMR: (SI Figure 3) 1.9 (3H, s, Me), 2.3 (6H, s, NMe), 2.6 (2H,b, CH₂N), 3.4 (2H, b, CH₂O). TGA: 177-258 ^oC (51.46 wt % loss) (Residue = 48.53 %).

3.2.6 Synthesis of CuPbI₃

0.50 g (2.62 mmol) copper(I) iodide was suspended in 20 mL distilled water in a 100 mL beaker. 0.87 g (2.64 mmol) lead(II) nitrate solution in 10 mL of distilled water was added drop by drop to the suspension of copper(I) iodide with constant stirring for 1 h. 0.87 g (5.28 mmol) potassium iodide dissolved in 10 mL of distilled water was added very

slowly to the vigorously stirred mixture for 2 h. The obtained yellow-brown precipitates were filtered and washed several times with distilled water until free from lead, nitrate and iodide ions. Finally, the precipitates were washed with ethyl alcohol and dried in air. The obtained yellow-brown powder was charged in a 5 mL Pyrex glass ampule and evacuated for several hours. The ampule was sealed under vacuum and heated at 620 °C for 72 h in a tube furnace (Titilayo A. Kuku & Salau, 1987). The furnace was allowed to cool to room temperature before the ampule was taken out. The ampule was opened carefully and mustard colour solid was carefully scratched from the ampule and ground to fine powder in an agate pestle mortar. The finely ground powder of copper lead iodide was washed with several 5 mL portions of DMF to remove excess of unreacted lead(II) iodide to give crystals of CuPbI₃ (m.p. 307 °C).

3.3 Crystallography and Structure Refinement

The data of complex (1) were collected at 150(2)K on a Bruker-Nonius Apex II CCD diffractometer using Mo K_{α} radiation ($\alpha = 0.71073$ Å) and were corrected for Lorentz-polarisation effects and absorption (SADABS) (Krause, Herbst-Irmer, Sheldrick, & Stalke, 2015). The structure was solved by dual space methods (SHELXT) (Sheldrick, 2015) and refined on F² using all the reflections (SHELXL-2014) (Sheldrick, 2015). The central section, comprising most of the molecule is disordered and was modelled with 50% occupancy of two positions related by a center of symmetry (reduction of the space group symmetry did not reduce the disorder). The data for complex (2) collected on a Agilent Supernova diffractometer equipped with a MoK α Microfocus X-ray source ($\lambda = 0.71073$ Å). The Agilent CrysAlisPro software was used for data collection, cell refinement, data reduction and absorption collections. Molecular graphics were drawn by using the XSEED and Mercury software were collected at 150(2)K on a Bruker Apex II CCD diffractometer using Mo K_{α} radiation ($\lambda = 0.71073$ Å). The structure was solved

by direct methods (SIR-2004) and refined on F^2 using all the reflections (SHELX) (Sheldrick, 2015). All the non-hydrogen atoms were refined using anisotropic atomic displacement parameters and hydrogen atoms were inserted at calculated positions using a riding model.

Diffraction data for the crystal (3) were collected on an Agilent SuperNova Dual diffractometer with an Atlas detector (graphite-monochromatized Mo-K α radiation, $\lambda =$ 0.71073 Å) at 100(2) K. The data were processed using CrysAlisPro, Agilent Technologies, Version 1.171.37.34 (release 22-05-2014 CrysAlis171.NET) and empirical absorption correction using spherical harmonics implemented in SCALE3 ABSPACK scaling algorithm. The structure was solved using the program SHELXT and was refined by the full matrix least-squares method on F^2 with SHELXL-2014/7 (Sheldrick, 2008). All the non-hydrogen atoms were refined anisotropically. All the hydrogen atoms were placed at calculated positions and were treated as riding on their parent atoms. The structure exhibits a whole molecule disorder with the two components being related by a pseudo-inversion center. The occupancy of the main component refined to 0.640(2). The structure was also refined as a racemic twin with the twin parameter of 0.46(4). Drawing of the molecule was produced with Mercury (Macrae et al., 2006). Crystal data: C₄₄H₅₆Co₂F₂₄O₂₉Ti₄, $M_r = 1814.34$, pink block, $0.49 \times 0.28 \times 0.26$ mm³, orthorhombic, $Pca2_1, a = 19.2672(4), b = 20.5759(5), c = 17.2453(4) \text{ Å}, V = 6836.7(3) \text{ Å}^3, Z = 4, D_c = 10.2672(4), c = 10.2672(4)$ 1.763 Mg/m³, 135126 measured reflections, 19480 unique reflections ($R_{int} = 0.0517$), 14499 observed reflections [(I > 2σ (I)], final R indices [(I > 2σ (I)]: $R_1 = 0.0858$, $wR_2 =$ 0.2091. CCDC No. 1453304.

Diffraction data for the crystal (4) were collected on an Agilent SuperNova Dual diffractometer with an Atlas detector (graphite-monochromatized Mo- $K\alpha$ radiation, $\lambda = 0.71073$ Å) at 100(2) K. The data were processed using CrysAlisPro, Agilent

Technologies, Version 1.171.37.34 (release 22-05-2014 CrysAlis171.NET) and empirical absorption correction using spherical harmonics implemented in SCALE3 ABSPACK scaling algorithm. The structure was solved using the program SHELXT and was refined by the full matrix least-squares method on F^2 with SHELXL-2014/7.The data of crystal (5) were collected at 150(2)K on a Bruker-Nonius Apex II CCD diffractometer using Mo K_{α} radiation ($\lambda = 0.71073$ Å) and were corrected for Lorentz-polarisation effects and absorption (SADABS) (Krause, Herbst-Irmer, Sheldrick, & Stalke, 2015). The structure was solved by dual space methods (SHELXT) (Sheldrick, 2015) and refined on F² using all the reflections (SHELXL-2014) (Sheldrick, 2015).

3.4 Thin Film Deposition Techniques

The semiconducting solid solution and composite thin films were developed by using the precursor (1-5). The thin films of precursor (1-4) were tailored on commercially available FTO-coated glass substrates using a self-designed AACVD assembly. Precursor (5) and metal acetates of (Mn, Fe, Cu, Ni, Zn, Cd and Pb) were fabricated on FTO substrate by an in house built EFDAACVD method. CuPbI₃ films were deposited by EDP technique. The general procedure of all these methods are described below:

3.4.1 Aerosol Assisted Chemical Vapor Deposition

The FTO-coated glass substrates purchased from Sigma Aldrich were cut to the dimension of 25.4 x 12.7 x 2.2 mm (L x W x D) and then prepared by ultrasonically washing with distilled water, acetone and then ethyl alcohol. Finally, they were washed with distilled water, kept in ethanol and dried in air before use. Substrate slides of the dimension of 25.2 mm \times 12.7 mm were placed inside a tube furnace chamber and then heated up to the deposition temperature for 10 min before carrying out the deposition. The aerosol of the precursor solution was formed by keeping the round-bottom flask in a

water bath above the piezoelectric modulator of an ultrasonic humidifier. The aerosol particles generated by the complexes were transferred into the hot wall region of the reactor by the carrier gas, whose flow rate was measured by a LIX linear flow meter and adjusted at 120 mL/min (Figure 3.1). In the last step of deposition, the aerosol assembly was turned off and a carrier gas was streamed over the substrates till the chamber cools down to normal temperature before they were removed for analysis.



Figure 3.1: Schematic diagram of Aerosol-Assisted Chemical Vapour Deposition.

3.4.2 Electric Field Directed Aerosol Assisted Chemical Vapor Deposition

The deposition of thin films on the commercially available fluorine-doped tin oxide (FTO) substrate dimension of 25.2 mm \times 12.7 mm were carried out using an in-house built EFDAACVD technique as shown in Figure 3.2. Prior to the deposition, the FTO substrates were cleaned ultrasonically by washing with distilled water, acetone and ethyl alcohol. Finally, they were washed with distilled water, stored in ethanol and dried in air before use. The aerosol of the metal precursor was generated by keeping the reaction mixture in a two necked round bottom flask in a water bath above the piezoelectric modulator of an ultrasonic humidifier. The generated aerosol droplets of the precursor were transferred through an injection needle anode that was connected to a power supply. The distance between the edge of the needle (anode) and the substrate was kept at 6 inches

and the substrate connected to the cathode was placed on the heater. Argon gas was passed through the aerosol mist at a flow rate of 200 mL/min to carry the aerosol droplets.



Figure 3.2: An in-house built experimental set up the orientation of the spray-needle was directed horizontally orthogonal to the plane of the substrate for Electric Field-Directed Aerosol-Assisted Chemical Vapour Deposition.

A potential of 9.5 kV was applied across the terminals while the aerosol was flowing through the needle and the deposition were conducted at 400 °C for 45 min. The power supply and the ultrasonic humidifier were switched off and the aerosol line was closed. The substrate was then coolled down to room temperature before it was removed from the heating plate to obtain thin films. As the coated area and the deposition rate are strongly dependent on the angle of the needle tip to the substrate, the aerosol spray-needle must be mounted in a horizontal position and perpendicular to the substrate surface at a suitable distance. It was observed that a relatively shorter distance between needle and substrate reduces the spinning time of the aerosol to yield a higher deposition rate and small coated areas having irregular particle shape. The increase in voltage and adjustment of distance between the needle tip and the substrate resulted in an evenly distributed thin film of precursor particles.

3.4.3 Electrophoretic Deposition

CuPbI₃ modified FTO electrodes were prepared by adopting EPD technique as reported in the literature (Tajabadi et al., 2015) (Figure 3.3). In a typical experiment a two milligrams of the as-synthesized CuPbI₃ powder was dispersed in 40 mL of 0.025 M $Mg(NO_3)_2$ in isopropanol.



Figure 3.3: Schematic diagram of electrophoretic deposition of charged particles on the anode of an EPD cell with planar electrodes.

The mixture was sonicated for 30 min to obtain a homogeneous suspension containing 0.05 mgL^{-1} of CuPbI₃. The pH of the suspension was adjusted at 3 by utilizing 1 M HCl solution before carrying out EPD experiment. The FTO glass substrates with an area of 10 mm × 20 mm were immersed in a 5% HF solution for a few minutes to remove the native oxide layer followed by washing in acetone and distilled water prior to being vertically immersed into the suspension. The linear distance between the electrodes was maintained at 10 mm and the DC potential and deposition time were adjusted to 80 V and 5 min, respectively. The coated film was dried at 50 °C in a vacuum oven to remove the excess solvent from the EPD process.

3.5 Photoelectrochemical Behavior

Photoelectrochemical activities of semiconducting metal oxides and metal halide films were examined by the use of three electrode system fitted with quartz window. Three electrode electrochemical cell consist of metal oxide/halide thin film as working, Ag/AgCl/3M KCl used as reference and Pt wire as counter electrode respectively. 0.1M Na₂SO₄ and 1M NaOH were used as electrolyte solution to evaluate the PEC behavior of particular photoelectrodes. The surface of FTO substrate of working electrode was employed as a mean for electrical contact, connected to crocodile clip coated with gold and kept beyond the electrolyte surface. A potentiostat (Eco Chemie micro-Autolab type III) was used to set the potential to photoelectrode in range of -0.2 to 1.2 V, while the cells were illuminated by an AM 1.5 Class A solar simulator (Solar Light 16S-300 solar simulator), at 100 mW cm⁻² light intensity from 150 W xenon arc lamp, adjusted by a silicon pyrometer (Solar Light Co., PMA2144 Class II). The active area of the film was arranged to 1×1 cm. The light enters the electrochemical cell through quartz window. Generally working electrode is irradiated for two minutes before the cell is turned ON so that electrons can travel to the conduction band.

3.6 Electrochemical Sensor Studies

Sensor studies of semiconducting bimetallic oxide thin films were performed in a single compartment three–electrode cell at room temperature using a PAR-VersaSTAT-3 Electrochemical workstation. The CoTiO₃-TiO₂ composite thin film and a platinum wire were used as working and counter electrodes, respectively. Silver/silver chloride (Ag/AgCl) electrode was used as a reference electrode. All studies for DA were carried out at pH 7.0 using a phosphate buffer solution. All solutions for electrochemical experiments were prepared with Millipore water having a resistivity of 18.2 M (Purelab Classic Corp., USA).

Precursors	Solvent	Deposition Temperature	Method	Carrier Gas	Deposition Time	Composition of Fabricated Thin Films
		°C		mL/min	min	
[Cu ₂ Ti ₄ (O) ₂ (OH) ₄ (TFA) ₈ (THF) ₆]·THF (1)	Methanol, Ethanol	550	AACVD	Air/150	40	CuO-2TiO ₂
[Co ₂ Ti ₄ (μ-O) ₆ (TFA) ₈ (THF) ₆]. THF (2)	Methanol, Ethanol	500, 550, 600	AACVD	Air/150	40	CoTiO ₃ -TiO ₂
$[Mg_2Ti_4(O)_2(OH)_4(TFA)_8(TH F)_6] \cdot THF \textbf{(3)}$	Methanol, Ethanol	500, 550, 600	AACVD	Air/150	40	MgTi ₂ O ₅
[Mn(dmae) ₂ (TFA) ₄] (4) +	Methanol	450	AACVD	Ar/120	45	Mn_2O_3 ,
Ag(OAc)						Ag-Mn ₂ O ₃
$[Sn(dmae)(OAc)]_2$ (5)	Toluene	400	EFDAACVD	Ar/200	30	SnO ₂
Mn(OAc) ₂	THF	400	EFDAACVD	Ar/200	45	Mn_2O_3
Fe(OAc) ₂ .2H ₂ O	THF	400	EFDAACVD	Ar/200	45	Fe ₂ O ₃
Cu(OAc) ₂ .2H ₂ O	THF	400	EFDAACVD	Ar/200	45	CuO
Ni(OAc) ₂ .H ₂ O	THF	400	EFDAACVD	Ar/200	45	NiO
Zn(OAc) _{2.} 2H ₂ O	THF	400	EFDAACVD	Ar/200	45	ZnO
Cd(OAc) _{2.} 2H ₂ O	THF	400	EFDAACVD	Ar/200	45	CdO
Pb(OAc) _{2.} 4H ₂ O	THF	400	EFDAACVD	Ar/200	45	PbO
CuPbI ₃	Isopropyl alcohol	50	EPD	Air	5	CuPbI ₃

Table 3.1: Parameters for the fabrication of thin films from their respective precursors.

3.7 Attempted Reactions

Some chemical reactions that might not produce the desired products were tried. The common method utilized in the attempted reactions is as follows: In a stirred mixture of Tin dimethhylamino ethanol Sn(dmae)₂ and metal alkoxide/carboxylate in dry Toluene was added few drops of triflouroacetic acid to result a clear solution after several hours, which was evaporated under vaccum to a dry solid. The solid was dissolved in 2-3 mL Tolune to give a clear solution which was filtered by cannula and kept for crystallization at -10 °C as well as room temperature.

The quantities of reactants used are given below

- *i)* Reaction between Sn(dmae)₂ and Titanium isopropoxide
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II) ; 0.093 mL (0.34 mmol) Titanium isopropoxide; 20 mL Toluene.
- *ii)* Reaction between Sn(dmae)₂ and Iron (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.06g (0.34 mmol) Iron (II) acetate (anhydrous); 20 mL Toluene.
- *iii)* Reaction between Sn(dmae)₂ and Manganese (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.058g (0.34 mmol) Manganese (II) acetate (anhydrous); 20 mL Toluene.
- *iv)* Reaction between Sn(dmae)₂ and Zinc (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.07g (0.34 mmol) Zinc (II) acetate dihydrtate; 20 mL Toluene.
- v) Reaction between Sn(dmae)₂ and Nickle (II) acetate

- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.08g (0.34 mmol) Nickle(II) acetate tetrahydrate; 20 mL Toluene.
- vi) Reaction between Sn(dmae)₂ and Silver (I) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.056g (0.34 mmol) Silver

(I) acetate (anhydrous); 15 mL Toluene.

- vii) Reaction between Sn(dmae)2 and Copper (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.07g (0.34 mmol) Copper

(II) acetate monohydrate; 20 mL Toluene.

- viii) Reaction between Sn(dmae)₂ and Lead (IV) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.15g (0.34 mmol) Lead

(IV) acetate; 25 mL Toluene.

- ix) Reaction between Sn(dmae)₂ and Iron (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.06g (0.34 mmol) Iron (II) acetate (anhydrous); 20 mL Toluene.
- *x)* Reaction between Sn(dmae)₂ and Cadmium (II) acetate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.07g (0.34 mmol) Cadmium (II) acetate dihydrate; 20 mL Toluene.
- *xi) Reaction between Sn*(*dmae*)₂ *and Cobalt* (*II*) *acetate*
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.08g (0.34 mmol) Cobalt
 - (II) acetate tetrahydrate; 15 mL Toluene.
- *xii)* Reaction between Sn(dmae)₂ and Cerium (III) acetylacetonate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.06g (0.34 mmol) Cerium (III) acetylacetonate; 25 mL Toluene.
- xiii) Reaction between Sn(dmae)₂ and Chromium (III) acetylacetonate
- 4.4 g (0.34 mmol) bis (dimethylaminoethanolato)tin (II); 0.12g (0.34 mmol) chromium (III) acetylacetonate Iron (II) acetate (anhydrous); 20 mL Toluene.

CHAPTER 4: RESULTS AND DISCUSSION

Metal carboxylates with their unique properties of high volatility, suitable decomposition temperature and stability during transport in the gas phase make them versatile CVD precursors for the fabrication of thin layers of metal oxides for various technological applications (Joshi & Cole, 2000; Niederberger & Pinna, 2009). The different coordination modes (monodentate or terminal, chelating, bridging and bridging chelating) of the carboxylate ligand force the metal into strict molecular regimes that enhance their potential to perform as CVD precursor (Chandler, Roger, & Hampden-Smith, 1993; Hubert- Pfalzgraf, 1992; Norman, Perez, Schulz, & Waechtler, 2008). Metal oxide core covered by organic surrounding making the precursor soluble in suitable organic solvents (Chandler, et al., 1993; Hasenkox, Hoffmann, & Waser, 1998). Semiconducting nanostructured metal oxide/halide thin films have been fabricated by different chemical and physical techniques and studied widely for their material based applications (Jagadish & Pearton, 2011; C. Lokhande, D. Dubal, & O.-S. Joo, 2011; Ohring, 2001). These materials have been offer a significant role in field of telecommunication, microelectronics, optoelectronics, sensors, actuators, computer memories, optical wavelength guide, infrared detectors and fuel cell (Beckel et al., 2007; Hotovy, Huran, Spiess, Hascik, & Rehacek, 1999; Kessler, 2003). A variety of newly synthetic routes are now capable to yield desired products under mild conditions are known as the Soft chemistry approach (Graf et al., 2011; Kessler, 2003; Lepage, Michot, Liang, Gauthier, & Schougaard, 2011; Niederberger, Pinna, Polleux, & Antonietti, 2004). These techniques including non-hydrolytic Sol-Gel processing, Metal Organic Deposition (MOD) or Chemical Vapour Deposition (CVD) and others involve the utilization of metal-organic compounds or metal complexes. These metal complexes can be easily hydrolytically or thermally decomposed and are usually described as molecular precursors. Single source precursors (SSP) are molecules containing all necessary elements required by the final material in proper ratio have proven extremely versatile as they often decompose cleanly under mild conditions and in a controllable manner.

Here, we report a deposition method of solid solution and composite metal oxide/halide thin films using the AACVD, EFDAACVD and EPD technique. Different metal oxide complexes such as $[Cu_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ ·THF (1), $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$.THF (2), $[Mg_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ ·THF (3), $[Mn(dmae)_2(TFA)_4]$ (4) and $[Sn(dmae)(OAc)]_2$ (5) were prepared using Lewis-acid base adduct methodology (Michael Veith et al., 2000), which is unique procedure for the design of mono and bimetallic oxides.

The syntheses of these precursors involves the reaction of matal alkoxides, carboxylates and β -diketonates in presence of more volatile and strongly bonding trifluoroacetic acid (TFAH) or dimethylaminoethanol (dmaeH) (Nicholas & Tuley, 2012). The replacement of alkoxides, carboxylates and β -diketonates by trifluoroacetato (TFA) and dimethylaminoethanolato (dmae) provides a stable mono and bimetal complex of that is soluble in various organic solvents and able to deliver a target material either as a single or dual source of respective metals in the form of a thin film on the FTO substrate without carbonaceous contamination.

The semiconducting photoactive thin films of CuO-2TiO₂, CoTiO₃-TiO₂ and MgTi₂O₅ were fabricated from single source precursors (**1**), (**2**) and (**3**) respectively, whereas thin film of Ag-Mn₂O₃ were grown from dual source using (**4**) via AACVD. SnO₂, Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO films were deposited from the precursor (**5**) and respective metal acetates (Mn, Fe, Cu, Ni, Zn, Cd and Pb) precursors by EFDAACVD technique. While metal halide CuPbI₃ deposited by EPD method. After possible characterizations, photoelectrochemical response of these thin films (except for CuO-

 2TiO_2 , CoTiO₃-TiO₂ and SnO₂) was investigated in order to evaluate their photocurrent and solar energy harvesting properties. CuO-2TiO₂ and CoTiO₃-TiO₂ thin films were tested for electrochemical sensing of NO₂⁻¹ ion and dopamine (DA), whereas SnO₂ for lithium ion batteries.

4.1. Synthesis and Characterization of [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1)

The chemical interaction diacetatocopper(II) between and tetrakisisopropoxytitanium(IV) in the presence of trifluoroacetic acid yields a heterobimetallic complex [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1). The isopropoxo and acetato groups attached to titanium and copper centres are completely exchanged by the stronger trifluoroacetato ligands as the reaction progresses in forward direction. The complex (1) prepared in a good yield, has copper to titanium ratio of 1:2, is stable in air and finds high solubility in common organic solvents such as methanol, ethanol, acetonitrile and tetrahydrofuran. The overall reaction for the formation of (1) is shown below in equation 1.

Chemical equation 1

$$\begin{split} & 2Cu(CH_3COOH)_2.H_2O + 4Ti(OCH(CH_3)_2)_4 + 8CF_3COOH \xrightarrow{THF} \\ & [Cu_2Ti_4(O)_2(OH)_4(CF_3COO)_8(C_4H_8O)_6].C_4H_8O + 4CHCOOH + 16(CH_3)_2CHOH \end{split}$$

The heterometallic architecture of the complex (1) has been framed on the basis of elemental analysis, FT-IR, and single crystal X-ray analyses as described in experimental section. The FT-IR spectrum of complex (1) shows the presence of characteristic vibrations of functional groups attached to the copper and titanium atoms. The typical symmetric and asymmetric v(C=O) absorptions of trifluoroacetato ligand arose at 1671 and 1471 cm⁻¹ respectively. The difference in value of 208 cm⁻¹ between symmetric and asymmetric v(C=O) absorption bands reveals the bidentate behaviour of the carboxylato

group of trifluoroacetato ligand that is bonded to different metal centres (Ehsan, Khaledi, Pandikumar, Rameshkumar, et al., 2015; Ehsan et al., 2011). Similarly, the peak at 1195 cm⁻¹ confirms the presence of C–F bonds in complex (**1**) (Ehsan, Khaledi, Pandikumar, Rameshkumar, et al., 2015; Ehsan, et al., 2011).

4.1.1 Molecular Structure of Complex [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (1)

The structure of (1) was solved in space group *Pbca*, and is disordered about the centre of symmetry. The core of the molecule consists of a tetrahedron of Ti(IV) ions (Figure 4.1). Each edge of the tetrahedron is bridged by an oxygen atom (O^{2-} or OH^{-}), generating a Ti₄O₆ adamantane-type cage. Four of the bridging species are hydroxo ions; the remaining two are oxo ions which are also coordinated to Cu(II) ions. The disorder arises from titanium ions occupying alternative sites, generating a second, overlapping adamantine with the oxygen atoms in the same positions. All the non-hydrogen atoms were refined using anisotropic atomic displacement parameters and hydrogen atoms were inserted at calculated positions using a riding model. Parameters for data collection and refinement are summarised in Table 4.1.

$C_{40}H_{52}Cu_2F_{24}O_{28}Ti_4 \cdot C_4H_8O$	$V = 6863.3 (7) Å^3$
$M_r = 1827.60$	Z = 4
Orthorhombic, Pbca	Mo <i>K</i> α radiation, $\lambda = 0.71073$ Å
a = 18.8071 (11) Å	$\mu = 1.20 \text{ mm}^{-1}$
b = 17.3656 (10) Å	<i>T</i> = 150 K
c = 21.0146 (12) Å	$0.43 \times 0.32 \times 0.24 \text{ mm}$
$R[F^2 > 2\sigma(F^2)] = 0.067$	59386 measured reflections
$wR(F^2) = 0.217$	7057 independent reflections
<i>S</i> = 1.01	4097 reflections with $I > 2 \Box(I)$
$\Delta >_{max} = 0.65 \text{ e } \text{Å}^{-3}$	1810 restraints
$\Delta \ge_{\min} = -0.67 \text{ e Å}^{-3}$	910 parameters

Table 4.1: Crystal data and refinement parameters for complex $[Cu_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ ·THF (1)


Figure 4.1: Perspective view of the core of (1). CF_3COO^- ions are represented by OCO links; terminal O atoms represent THF molecules, bold bonds highlight the $Ti_4O_2(OH)_4$ adamantane core. Atoms with suffix "A" generated by symmetry operation 1-x, 1-y, 1-



Figure 4.2: Perspective view of the [Cu₂Ti₄(O)₂(OH)₄(CF₃COO)₈(THF)₆] (1) molecule. Bold bonds highlight the metal coordination spheres. Disorder and H atoms are omitted for clarity.

Four trifluoroacetate (CF_3COO^-) ions are bonded to each copper ion; each trifluoroacetate also bridges to a titanium ion. All of the metal ions are six-coordinate, the last binding

site being filled by one coordinated THF molecule for each metal ion (Figure 4.2). There is also a (disordered) non-coordinated THF solvate molecule in the lattice.

4.1.2 Thermal (TG/DTG) Analysis of Complex [Cu₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]· THF (1)

The thermal decomposition behaviour of the complex (1) was studied by simultaneous thermogravimetric (TG) and derivative thermogravimetric (DTG) analysis under an inert dinitrogen atmosphere with a flowing rate of 25 cm³ min⁻¹ and a heating rate of 10 °C min⁻¹ and the results are presented in Figure 4.3.



Figure 4.3: TG (black) and DTG (red) profiles representing thermal decomposition of complex (1) as a function of temperature.

The TG/DTG curves impart that thermal degradation of (1) completes in four continuous weight loss steps and maximum heat intakes sequentially occur at 81, 225, 250 and 306 °C giving weight loss of 11.1 %, 25.8%, 14.0%, and 22.3% respectively. The thermal decay process in (1) ends at 500 °C leaving an invariable residue that amounts to 26.80 % of its original mass. The weight of the residue (26.18%) reasonably accords with the formation of the expected 1:2 CuO: TiO₂

composite oxide material from (1). Further sintering of the observed residue to the higher temperature of 900 °C did not experience any change in weight, suggesting that (1) decomposes quantitatively to endow CuO-2TiO₂ as a stable final product. Based on TGA information, quantitative pyrolysis of (1) has been indicated in equation below:

Chemical equation 2:

 $[Cu_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ THF $\xrightarrow{500^\circ C} 2CuO - 2TiO_2 + Volatiles$

4.1.3 Structural Analysis of CuO-2TiO₂

Thin films were developed via AACVD method on FTO glass substrate at temperature of 550 °C from 0.1M solution of precursor (1) in ethanol and methanol solvents respectively, using air as a carrier gas. The phase formation and degree of crystallinity of the deposited films were examined by XRD technique and X-ray diffractograms are comparatively overlapped in Figure 4.4. The XRD peak patterns seem identical in terms of their peak positions and 20 values and both the diffractograms are dominated by the diffraction peak located at $2\theta = 25.27^{\circ}$ and 37.81°. XRD qualitative phase analysis was performed on each XRD pattern shown in Figure 4.4, which reveals the growth of tenorite CuO (ICSD 98-001-6025) (Åsbrink & Norrby, 1970) and a mixture of anatase (98-000-9853) (E.P. Meagher, 2002) and rutile (98-003-1321) (Mumme, Cranswick, & Chakoumakos, 2002) TiO₂ phases as crystalline end product in both the cases. The prepared CuO exists in a monoclinic crystal system with space group C12/c1 and produced characteristic peaks indicated by (Z) at $2\theta = 32.58$, 35.60, 48.84, 58.36, and 75.16° as observed by their Miller indices (110), (11-1), (20-2), (202) and (004) respectively. The emergence of peaks at $2\theta = 25.27 (011)$, 37.80 (112), 48.0 (020)

70.39 (220) and 73.59° (017) denoted by (**X**) are well indexed to tetragonal anatase TiO_2 .



Figure 4.4: XRD patterns of the CuO-2TiO₂ composite thin films prepared from solutions of (1) in ethanol (green line), methanol (blue line), on FTO glass at 550 °C in air ambient; Inset shows the proportion of crystalline phases present in CuO-2TiO₂ composite films from (i) ethanol: 48% anatase TiO₂ (X), 17% rutile TiO₂ (Y), 35% tenorite TiO₂ (Z); (ii) methanol: 67% anatase TiO₂ (X), 17% rutile TiO₂, (Y) 16% tenorite CuO (Z).

Furthermore, the peaks marked by (**Y**) at $2\theta = 27.46^{\circ}$ (110), 36.0° (011) and 41.27° (111) are attributed to tetragonal rutile TiO₂. The X-ray diffractograms also demonstrate the overlapped peaks between CuO and anatase TiO₂ phases at 2 θ values of 53.95°, 68.89° and 80.62°. A few common reflections originating from both anatase and rutile TiO₂ phases appear at 2 θ values of 36.45 and 62.75°. No possible crystalline impurities such as metallic copper or Cu₂O were detected from these XRD patterns.

The XRD qualitative phase analysis has established that both the copper oxidetitania composite films deposited from two different solvents are comprised of similar crystalline phases including tenorite CuO and a mixture of anatase and rutile TiO₂. The proportion of crystallinity of each phase in the composite product was determined by XRD semi-quantification analysis. The crystalline composition of CuO-2TiO₂ deposit obtained from ethanol is poised at 48% anatase TiO₂ (**X**), 17% rutile TiO₂ (**Y**) and 35% tenorite CuO (**Z**), respectively (inset Figure 4.4(**i**)). The film deposited from methanol contains the crystalline contents of 67% anatase TiO₂ (**X**), 16% rutile TiO₂ (**Y**) and 17% tenorite CuO (**Z**), respectively (inset Figure 4.4(**i**)).

The crystalline contents of the CuO-2TiO₂ films deposited from different solvents varies from each other which suggest that solvents play a vital role in decorating the crystalline phases of the films on substrate surface by AACVD and not just act as a transport medium. In aerosol deposition, solvents play an important role in the determination of the extent of a reaction. The precursor can react differently in various solvents in the gas phase which may lead to the formation of different intermediates and thus to different phases of the deposit. There have been similar reports whereby a variety of solvents have been used to alter the phase composition of titania using sol-gel approach, spray pyrolysis and AACVD (Edusi, et al., 2012).⁽Xiaoxin, Zhengguo, Shaojing, & Tao, 2005).

4.1.4 Raman Spectroscopy of CuO-2TiO₂

Further the structural analysis of CuO-2TiO₂ composites thin films deposited from two different solutions was carried out by Raman spectroscopy and results are displayed in Figure 4.5. The Raman scattering vibration modes detected at 151, 400, 519 and 630 cm⁻¹, corresponds to anatase TiO₂ phase (Nolan, Seery, & Pillai, 2011) and peaks located at 280 and 630 cm⁻¹ signify the presence of CuO phase (Nguyen, Nguyen, Ung, & Nguyen, 2013). The characteristic peaks for rutile TiO₂ which are expected to appear at 246, 446 and 601 cm⁻¹ are merged in the broad bands at 280, 400 and 630 cm⁻¹ (Hardcastle, 2011). Hence the CuO and mixture of anatase and rutile TiO₂ phases determined from our XRD analysis are further validated from Raman spectroscopy.



Figure 4.5: Raman spectra of the CuO-2TiO₂ composite thin films prepared from solutions of (1) in ethanol (green line), methanol (blue line), on FTO glass substrate at $550 \,^{\circ}$ C in air ambient.

4.1.5 Micro-structural Properties of CuO-2TiO₂

The micro-structural properties of the films deposited from 0.1 M (20 mL) solution of precursor (1) in ethanol and methanol at 550 $^{\circ}$ C in air atmosphere were analysed by SEM.

Figure 4.6 depicts the surface and cross sectional SEM images of $CuO-2TiO_2$ composite films. Figure 4.6(a) shows the surface topography of the film, prepared from ethanol solution, is composed of interconnected spherical objects of heterogeneous design, shape and size which are developed in the vertical direction of substrate plane. One type of microspherical object attains donuts shape structure while

the other exists as round ball shaped entity of size range $0.5-1.3\mu m$ (Appendix 1(a2)). The low resolution surface SEM images (Appendix 1(a1)) reveal that these microspherical objects are homogenously distributed though out the film matrix.

The cross sectional view of CuO-2TiO₂ composite film of average thickness 4.0 μ m, deposited from ethanol solution, displayed in Figure 4.6(b) and (Appendix 1. (b1)), show growth of small grains on the boundary layer of the FTO substrate. Figure 4.6 (b) shows that the surface architecture of the film obtained from methanol solution is made up of small and big sized spherical objects which are discretely grown in upward direction. The high resolution image (Appendix 1(c2)) demonstrates that the surface of these spherical bodies is fully covered with buds. The low resolution surface SEM image (Appendix 1. Figure 1(c1)) depicts that these objects are uniformly furnished on substrate surface however the surface of the substrate is not fully covered as observed in the film deposited from ethanol solution.

The shape of the thin-film cross sections is shown in Figure 4.6(d) and (Appendix 1 (d1)) and a layer of spheroid objects of thickness range 1.77-4.40 μ m can be clearly seen on the surface of the FTO substrate.



Figure 4.6: (a) and (c) show surface and (b) and (d) indicate the cross sectional SEM images of CuO-2TiO₂ composite thin films deposited on FTO glass substrate at 550 °C from solution of precursor (1) in (a, b) ethanol (c, d) methanol, respectively.

The elemental composition of CuO–2TiO₂ composite oxide thin films were analyzed by energy dispersive X-ray (EDX) analysis and spectra are presented in (Appendix 2(i & ii)). The EDX analysis performed on several randomly selected large regions revealed that the metallic ratio of Cu:Ti in the films is close to 1: 2 confirming the retention of the same metallic ratio in the films as found in complex (1).

Further EDX map analysis was performed to establish the composite nature of the CuO– 2TiO_2 films. The distribution of the constituent Cu, Ti and O atoms has been highlighted by using different color schemes as shown in Figure 4.7 (a & b) which reveals the even distribution of these atoms throughout the films matrix.



Figure 4.7a: : EDX Elemental map showing the distribution of Cu, Ti and O atoms in $CuO-2TiO_2$ composite thin film deposited from ethanol solution of precursor (1).



Figure 4.7b: EDX Elemental map showing distribution of Cu, Ti and O atoms in CuO– 2TiO₂ composite thin film deposited from methanol solution of precursor (1).

4.1.6 XPS Analysis of CuO-2TiO₂

The XPS analysis was employed to determine the surface composition and chemical states of the Cu, Ti, and O elements in CuO-2TiO₂ composite oxide thin film prepared from ethanol solution of precursor (1) at 550 °C.



Figure 4.8: (a) Survey scan XPS spectrum of CuO-2TiO₂ composite thin films prepared from ethanol solution; High resolution spectra of CuO-2TiO₂ for (b) Ti 2p (c) O 1s (d) Cu 2p

The survey scan spectrum in Figure 4.8(a) shows the binding energy peaks at 458.4, 529.5 and 933.4 eV which are attributed to Ti 2p, O 1s and Cu 2p respectively. In the high resolution Ti 2p spectrum Figure 8(b), binding energies of 458.6 and 464.3 eV are indicative of Ti 2p3/2 and Ti 2p1/2 respectively which correspond to Ti⁴⁺ and matches well with the published data for TiO₂ (S. S. Lee, Bai, Liu, & Sun, 2013). Meanwhile, the peaks at 529.7 and 530.1 eV are evidence of O1s in CuO and TiO₂ Figure 4.8(c). The Cu 2p peak of the CuO-2TiO₂ is shown in Figure 4.8(d). The Cu 2p3/2 is allocated at 934 eV with a shakeup satellite peak at about 943.5eV and Cu 2p1/2 lies at 954 eV with a satellite peak at about 962.5eV, which is consistent with earlier reports (Dar, Nam, Kim, & Kim, 2010; D. Tahir & Tougaard, 2012). The presence of shakeup satellite features for Cu 2p rules out the possibility of presence of Cu₂O phase. The gap between Cu 2p1/2 and Cu 2p3/2 is 20eV, which is in agreement with the standard CuO spectrum (L. Zhu, Hong, & Ho, 2015).

4.1.7 Electrochemical Detection of Nitrite Ions by CuO-2TiO₂ Film Electrodes

The CuO–2TiO₂ composite film deposited from ethanol solution of (1) was used for the electrocatalysis and sensing of NO_2^- ions in 0.1 M phosphate buffer solution (PBS) (pH 7.2).



Figure 4.9: Cyclic voltammograms obtained for the CuO–2TiO₂ composite thin film in the (a) absence and (b) presence of 5 mM NO_2^- ions in 0.1 M PBS (pH 7.2) at a scan rate of 50 mV s⁻¹

The CuO–2TiO₂ composite electrode displayed an intense anodic peak current in the cyclic voltammogram for 5 mM NO₂⁻ at +1.0 V due to the electrocatalytic oxidation of NO₂⁻, Figure 4.9(b), and did not show any voltammetric response in the absence of NO₂⁻, Figure 4.9(a). During the electrocatalytic oxidation of NO₂⁻, two electrons were transferred and thus to form NO₃⁻ as a product.(Guidelli, Pergola, & Raspi, 1972) (Pandikumar, Yusoff, Huang, & Lim, 2014) Further, influence of the scan rate on the electrocatalytic oxidation peak potential (E_{pa}) and peak current for NO₂⁻ at the CuO–2TiO₂ film electrode in 0.1 M PBS (pH 7.2) were studied using CV, as shown in Figure 4.10(a).



Figure 4.10: (a) Cyclic voltammograms recorded for the CuO–2TiO₂ electrode in the presence of 1 mM NO₂⁻ ions in 0.1 M PBS (pH 7.2) at various scan rates of ((a)–(m)) 10–300 mV s⁻¹. (b) Plot of anodic peak current vs square root of the scan rate obtained for the CuO–2TiO₂ electrode.

The current values were found to be increased with an increase in the scan rate from 10 to 300 mV s⁻¹, Figure 4.10(a). The linear relationship between the anodic peak currents and the square root of the scan rate is shown in Figure 10(b). As can be seen, the anodic peak current (I_{pa}) for the 1 mM NO₂⁻ varied linearly with the square root of the scan rate $(v^{1/2})$, with a linear regression equation of (I_{pa} (μ A) = 0.205 $v^{1/2}$ + 20.48) and a correlation coefficient R² = 0.971. This result indicates that the electron transfer of the CuO–2TiO₂ composite film is mainly controlled by a diffusion-controlled electrochemical process (Ikhsan et al., 2015).

The sensitivity of the sensor under the optimized detection for NO₂⁻ conditions were tried, and a series of linear sweep voltammetry (LSV) curves were recorded in 0.1 M PBS (pH 7.2) with different NO₂⁻ concentrations at the CuO–2TiO₂ electrode as shown in Figure 4.11(a). It could be observed that the anodic peak current increased linearly with an increase in the concentration of NO₂⁻ in the range of 10 to 200 μ M, with a linear regression equation of I_{pa} = 0.0415 M + 1.4336 μ (R² = 0.9994), Figure 4.11(b). The sensitivity is determined from the slope of the calibration plot. The Figure 4.11(b) shows the standard addition line, limit of detection (LoD) for NO₂⁻ was calculated as 16.6 nM (S/N = 3). It can be seen that this present detection limit is comparable as well as lower than detection limits obtained for other oxides by different electrochemical methods.

The sensing performance of the CuO– 2TiO_2 composite film was compared with other previously reported sensor materials for the detection of NO_2^- and the results are summarized in Table 4.2 which indicates that the detection limit of the present sensor is better than the other oxide materials.



Figure 4. 11:(a) Linear sweep voltammograms (LSV) obtained for the CuO–2TiO₂ composite thin film for various concentration of NO_2^- ions in 0.1 M PBS (pH 7.2) at a scan rate of 50 mV s⁻¹. (b) Correlation between the concentration of NO_2^- and peak current for the CuO–2TiO₂ electrode.

Sensor material	Analytical technique	Limit of detection	Ref.
		(LOD)	
MnO ₂ -CP-E	Linear sweep voltammetry	1.2µM	(Langley, ŠLJUKIC, Banks, & Compton, 2007)
Cobalt oxide	Cyclic voltammetry	20 mM	(Salimi, Hallaj, Mamkhezri, & Hosaini, 2008)
CuO–graphite	Cyclic voltammetry	0.6 µM	(Biljana Šljukić, Craig E Banks, Alison Crossley, & Richard G Compton, 2007)
PbO ₂ –graphite	Cyclic voltammetry	0.9 μM	(Biljana Šljukić, Craig E Banks, Alison Crossley, & Richard G Compton, 2007)
f-ZnO@rFGO	Linear sweep voltammetry	33 µM	(Pandikumar, et al., 2014)
ZnTiO ₃ –TiO ₂	Amperometry	3.98 µM	(Ehsan, Khaledi, Pandikumar, Rameshkumar, et al., 2015)
CuO–2TiO ₂	Linear sweep voltammetry	16.6 nM	Present work

Table 4.2: Comparison of analytical performance of various electrochemical sensors for nitrite (NO₂⁻) detection.

The selectivity of the CuO–2TiO₂ electrode for the determination of NO_2^- investigated by adding various possible interferents and observing the change in current (Figure 4.12). The LSV was continuously recorded for the addition of common interferents such as NaF, NH₄Cl, KCl, NaNO₃ and MgSO₄ in a homogeneously stirred of 0.1 M PBS (pH 7.2) and

there is no significant current response found due the interferents. Upon addition 100 μ M NO₂⁻, the electrode showed the response signal (Figure 4.12). This observation clearly demonstrates that the selective detection of NO₂⁻ even in the presence of common interferents is possible and the CuO–2TiO₂ composite possesses high selectivity toward NO₂⁻ over other common interferents.



Figure 4.12: LSV response obtained for CuO–2TiO₂ composite thin film for the addition of and each 1000 μ M addition of other interferences such as KCl, MgSO₄, NaF, NH₄Cl, NaNO₃ and 100 μ M NO₂⁻ ions in 0.1 M PBS (pH 7.2) at scan rate of 50 mV s⁻¹.

4.2 Synthesis of Complex $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ ·THF (2)

The synthetic protocol of heterobimetallic precursor [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF (2)involves the reaction of diacetatomagnesium(II) tetrahydrate with tetraisopropoxytitanium(IV) in presence of trifluoroacetic acid in THF. As the reaction progresses, the more labile isopropoxy ligands are exchanged by stronger chelating TFA groups which bind Mg and Ti atoms through its carboxylate oxygen atoms. The exchange of ligands and progress of the reaction can be observed by dissolution of salts to result in a clear solution. The transparent solution was then evaporated in vacuum to obtain a white powder which was re-dissolved in 3 mL THF and kept at room temperature to grow the first 70% yield of translucent white crystals of the precursor (2). The overall reaction for the formation of (2) is shown below in equation .

Chemical equation 3

$$2Co(CH_{3}COOH)_{2}.4H_{2}O + 4Ti(OCH(CH_{3})_{2})_{4} + 8CF_{3}COOH \xrightarrow{THF} \rightarrow [Co_{2}Ti_{4}(\mu - O)_{6}(CF_{3}COO)_{8}(C_{4}H_{8}O)_{6}].C_{4}H_{8}O + 4CH_{3}COOH + 16(CH_{3})_{2}CHOH$$

The substitution of carboxy with TFA groups not only aids binding of Mg and Ti atoms in one framework but also co-ordinatively saturates each metal centre, making the precursor more volatile as well as soluble in organic solvents such as chloroform, THF, methanol and ethanol, rendering it a suitable precursor to produce single phased MgTi₂O₅ thin films by the AACVD method. The stoichiometric composition of complex (**2**) was recognized by single crystal X-ray diffraction and further confirmed by FTIR and TG/DTG analysis. The FT-IR spectrum of Mg-Ti precursor showed strong absorption bands at 1654 and 1453 cm⁻¹ due to the asymmetric and symmetric v(C=O) vibrations of the 95carboxylate group of the TFA ligands respectively. The difference of value Δv_{asy} - $\Delta v_{sy} = 200$ cm⁻¹ is consistent with the bidentate bridging behavior of TFA ligand. Similarly, a sharp peak at 1192 cm⁻¹ confirms the existence of C–F bonds in complex (**2**). The IR spectrum is closely related to those reported previously for similar heterobimetallic compounds.

4.2.1 Molecular Structure of Complex [Co₂Ti₄(µ-O)₆(TFA)₈(THF)₆]·THF (2)

The molecular structure of the Co-Ti complex is depicted in Figure 4.13 and a schematic drawing for the molecule is given in Figure 4.14. The structure of the Co-Ti complex resembles those of the analogous Fe-Ti (Ehsan, et al., 2011), Cd-Ti (Ehsan, Khaledi,

Pandikumar, Huang, et al., 2015) and Zn-Ti (Ehsan, Khaledi, Pandikumar, Rameshkumar, et al., 2015) complexes, being isostructural with the latter two complexes.



Figure 4.13: Crystal structure of complex $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ ·THF (2). The minor component of disorder, hydrogen atoms, and the solvate THF molecule are not shown.



Figure 4.14: Schematic diagram of complex $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ ·THF (2).

The molecule has a non-crystallographic D_2 point symmetry and consists of a Ti₄O₆ core arranged in an adamantane-like structure. Two of the core O atoms (O1, O6) are of the μ_3 -type that bridge pairs of the tetrahedrally located Ti's to the two Co^{II} centers. The other four O atoms (O2, O3, O4, O5) link only pairs of the Ti atoms. Each metal center in the structure is in an octahedral coordination environment made of six O atoms from the Ti₄O₆ cage, TFA's and THF ligands. Table 4.3 lists the coordination bond lengths for the structure. The Ti-Ti separations are between 3.328-3.352 Å which are comparable to those in the analogous structures.

Co(1)-O(1)	2.175(6)	Ti(2)-O(13)	2.080(12)
Co(1)-O(7)	2.111(7)	Ti(2)-O(15)	2.108(10)
Co(1)-O(8)	2.039(8)	Ti(2)-O(17)	2.168(9)
Co(1)-O(10)	2.064(7)	Ti(3)-O(2)	1.860(8)
Co(1)-O(12)	2.083(8)	Ti(3)-O(4)	1.744(8)
Co(1)-O(14)	2.079(8)	Ti(3)-O(6)	1.881(7)
Co(2)-O(6)	2.154(7)	Ti(3)-O(20)	2.079(13)
Co(2)-O(18)	2.108(6)	Ti(3)-O(22)	2.101(12)
Co(2)-O(19)	2.030(11)	Ti(3)-O(27)	2.179(8)
Co(2)-O(21)	2.035(8)	Ti(4)-O(3)	1.851(8)
Co(2)-O(25)	2.041(8)	Ti(4)-O(5)	1.782(8)
Co(2)-O(23)	2.046(8)	Ti(4)-O(6)	1.925(7)
Ti(1)-O(1)	1.853(7)	Ti(4)-O(24)	2.067(9)
Ti(1)-O(2)	1.809(8)	Ti(4)-O(26)	2.116(11)
Ti(1)-O(3)	1.792(8)	Ti(4)-O(28)	2.161(9)
Ti(1)-O(9)	2.092(13)	Ti(1)-Ti(2)	3.347(4)
Ti(1)-O(11)	2.085(10)	Ti(1)-Ti(3)	3.328(4)
Ti(1)-O(16)	2.155(10)	Ti(1)-Ti(4)	3.345(4)
Ti(2)-O(1)	1.938(7)	Ti(2)-Ti(3)	3.347(4)
Ti(2)-O(5)	1.813(8)	Ti(2)-Ti(4)	3.338(4)
Ti(2)-O(4)	1.870(8)	Ti(3)-Ti(4)	3.352(4)

Table 4.3: Coordination bond lengths for $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ · THF (2)

4.2.2 Thermal (TG/DTG) of complex [Co₂Ti₄(µ-O)₆(TFA)₈(THF)₆]·THF (2)

The thermal pyrolysis of complex (**2**) was investigated by thermogravimetric (TG) and derivative thermogravimetric (DTG) analysis in a flowing N₂ atmosphere at the rate of $25 \text{ cm}^3 \text{ min}^{-1}$ and a heating rate of $10 \text{ }^{\circ}\text{C} \text{ min}^{-1}$ and results are displayed in Figure 4.15.



Figure 4.15: TG (red) and DTG (dotted black) traces of thermal decomposition of complex (2) as a function of temperature

The TG (red) DTG (black) Figure 4.15 and curves in indicate that complete thermal degradation of complex (2) occurs in five consecutive weight loss stages of 1.53, 7.2, 16.8, 6.8 and 40.17% which appear at maximum heat intake steps at 72, 160, 195, 218, and 292 °C respectively. The weight loss phases are completed at 500 °C yielding steady residues of 27.5 % of its original mass which is equitable with the formation of the expected 1:1 of $CoTiO_3$: TiO₂ (25.80%) composite oxide material from (2). Further sintering of the observed residue to the higher temperature of 900 °C did not produce any change in weight, suggesting that complex (2) decomposes quantitatively to endow $CoTiO_3$ -TiO₂ as a stable final product. Based on TGA information, quantitative pyrolysis of (2) has been indicated in equation below:

Chemical equation 4:

$$[Co_{2}Ti_{4}(\mu - O)_{6}(TFA)_{8}(THF)_{6}]THF \xrightarrow{500^{\circ}C} 2CoTiO_{3} - TiO_{2} + Volatiles$$

4.2.3 XRD Analysis of CoTiO₃-TiO₂ Thin Films

The ability of complex (2) to act as a single source precursor (SSP) for the formation of advanced composite oxides thin film was investigated by AACVD and film deposition experiments were carried out on FTO glass substrate at three different temperatures of 500, 550 and 600 $^{\circ}$ C using ethanolic solution of complex (2) in air ambient.

The structural characterization of crystalline deposit was made by XRD analysis and resultant patterns as function of substrate temperature are overlaid in Figure. 4.16. Each XRD pattern in Figure 4.16 was analyzed by qualitative phase analysis which indicates the presence of similar cobalt titanium oxide CoTiO₃ (ICSD 98-001-6548) (Newnham, Fang, & Santoro, 1964) and rutile TiO₂ (ICSD 98-001-6636) (Tomaszewski, 2002) phases in all the cases. In all films, the prepared CoTiO₃ exists in a hexagonal crystal system with space group R-3 and produced characteristic peaks indicated by (**X**) at $2\theta = 23.9$, 32.8, 35.4, 40.5, 49.0, 53.5, 61.9 and 63.6 ° as observed by their Miller indices (012), (104), (2-10), (2-13), (024), (116), (214) and (030), respectively. The emergence of peaks at $2\theta = 27.4$ (110), 36.0 (011), 41.3 (111), 44.0 (120) and 54.3° (121) denoted by (**Y**) are well indexed to tetragonal rutile TiO₂.

The X-ray diffractograms also demonstrate overlapped peaks between $CoTiO_3$ and rutile TiO_2 phases at 20 values of 56.7, and 68.9°. Peaks indicated by (*) are originated from

crystalline SnO_2 of the FTO substrate. Interestingly, all the XRD patterns show similar phases of ilmenite $CoTiO_3$ and rutile TiO_2 as end product prepared at different temperatures and no sign of phase transformation or growth of impurity phases such as CoO, Co_3O_4 and other titania varieties is perceived from these XRD results.

In comparison with recent literature, the cobalt titanate material is usually prepared at higher temperature of 600 °C and prolong heating is often required to improve the crystallinity of the product (Kapoor, Uma, Rodriguez, & Klabunde, 2005; G Zhou, Lee, Kim, Kim, & Kang, 2006; Chuang et al., 2010). This post sintering process deteriorates the phase purity of the product by generating various unwanted phases and undermines the worth of the material for technological applications.



Figure 4.16: XRD patterns of CoTiO₃-TiO₂ composite films deposited on FTO glass substrate at different temperatures of 500 °C (black line), 550 °C (green line) and 600 °C (red line) from ethanolic solution of precursor (1). (X) indicates peaks originating from ilmenite-CoTiO₃ ((ICSD 98-001-6548)), (Y) specifies peaks related to rutile TiO₂ (ICSD 98-001-6636).

In comparison well crystallized CoTiO₃-TiO₂ composite oxide is formed at lower temperature of 500 °C and product remain pure and stable until 600 °C which is unique aspect of AACVD based SSP method.

4.2.4 Raman Spectroscopy of CoTiO₃-TiO₂ thin films

The chemical structure and identity of cobalt titanate and titanium dioxide phases in the composite films were further characterized from FT-Raman spectroscopy and the spectra of as-deposited films at different temperatures are comparatively shown in Figure 4.17.



Figure 4.17: FT-Raman spectra of CoTiO₃-TiO₂ composite films deposited at different temperatures of 500 °C (black line), 550 °C (green line) and 600 °C (red line).

According to the literature, the Raman scattering modes appeared at 207, 235, 267, 335, 382, 604 and 696 cm⁻¹ witness the presence of ilmenite CoTiO₃ phase in all cases (G Zhou, et al., 2006; Shilpy, Ehsan, Ali, Hamid, & Ali, 2015). The most typical feature of CoTiO₃ is the strong Raman mode observed near 700 cm⁻¹. This mode arises from the highest frequency vibrational mode of CoO6 octahedra that is the symmetric stretching mode (A_{1g} symmetry for regular Oh octahedral) (G Zhou, et al., 2006). The characteristic Raman active band for ruitle TiO₂ (Hardcastle, 2011; Nolan, et al., 2011) phase is observed at 447 cm⁻¹, while the other expected absorptions bands of 246 and 601 seem to

merge with the broad peaks of 235 and 604 of $CoTiO_3$. These results indicate formation of phase pure $CoTiO_3$ and rutile TiO_2 in all cobalt titanate-titania composite films prepared at different temperatures of 500, 550 and 600 °C.

4.2.5 Microstructural properties of CoTiO₃-TiO₂ thin films

The surface morphology, architectures and cross sectional views of CoTiO₃-TiO₂ composite films developed at 500, 550 and 600 °C from ethanol solutions of the precursor (**2**) are shown in Figure 4.18. Figure 4.18a shows that the surface topography of the CoTiO₃-TiO₂ film deposited at 500 °C is composed of spherical objects of two different types of microspheres which are grown in horizontal and vertical directions of the substrate surface and are in the size range of 0.3-0.9 μ m. The surface of one type of microsphere contains buds while others are relatively bare. The cross sectional view of CoTiO₃-TiO₂ composite film prepared at 500 °C is displayed in Figure 4.18(**b**) where small grains developed on the boundary layer of the FTO substrate can be clearly seen and film average thickness was measured to be 4.5 µm.

When the deposition temperature increases to 550 °C, the substrate surface is decorated with a new designs of CoTiO₃-TiO₂ spherical entities and Figure. 4.18 (c) displays that the surface of one kind of spherical object of size $1.12 \,\mu\text{m}$ contains tiny particles on its surface while the other type of microsphere of size 0.55 μm exhibits a smooth and plain texture. Figure 4.18(d) designates the cross sectional view of the CoTiO₃-TiO₂ composite film and it is observed that film thickness increases to 7.8 μm with the rise in temperature from 500 to 550 °C. Further increasing the deposition temperature to 600 °C results in formation of mixture of donuts and round shaped crystallites of CoTiO₃-TiO₂ as displayed in Figure 4.18 (f) where

a layer of spheroid particles of thickness $18 \ \mu m$ is visibly displayed on the surface of the FTO substrate.



Figure 4.18: (a), (c) and I show surface and (b), (d) and (f) indicate the cross sectional SEM images of CoTiO₃-TiO₂ composite thin films deposited on FTO glass substrate from ethanolic solution of precursor (**2**) at temperatures (a, b) 500 °C (c, d) 550 °C and (e, f) 600 °C, respectively.

The surface compositions of all films were analysed by energy dispersive analysis (EDX) analysis. EDX spectra shown in (Appendix 3(i, ii and iii) were recorded at various arbitrary large areas of the films which revealed that the percent atomic ratio of Co: Ti in the films is almost 1: 2 which is in accordance with the expected 1: 2 elemental ratio present in precursor (**2**). These results confirm that the films

grown at different temperatures 500, 550 and 600 °C retain the same metallic ratio as found in complex (2).

Further the heterogeneity and distribution of cobalt, titanium and oxygen atoms in CoTiO₃-TiO₂ composite films was examined by EDX mapping and results are shown in Figure 4.19 (a- c) which reveal that these atoms are evenly distributed throughout the films matrix confirming the composite nature of all films prepared at different temperatures.



Figure 4.19a: Elemental Map showing the distribution of Co, Ti and O elements in CoTiO₃-TiO₂ composite film deposited at 500 °C



Figure 4.19b: Elemental Map showing the distribution of Co, Ti and O elements in

CoTiO₃-TiO₂ composite film deposited at 550 $^{\circ}$ C



Figure 4.19c: Elemental Map showing the distribution of Co, Ti and O elements in CoTiO₃-TiO₂ composite film deposited at 550 °C

All CoTiO₃-TiO₂ films were translucent and light green in colour. The films deposited at lower temperature of 500 and 550 °C were robust and adhered strongly on the FTO substrate as verified by the "Scotch tape test" while the film prepared at 600 °C showed poor adhesive properties and was failed to qualify the adherence test.

4.2.6 XPS Analysis of CoTiO₃-TiO₂ thin films

The CoTiO₃-TiO₂ composite film prepared at 550 °C was further examined by X-ray photoelectron spectroscopy (XPS) and results are presented in Figure 4.20. The XPS survey scan spectrum in Figure 4.20 (a) indicates that cobalt, titanium, and oxygen are the major components at the surface of the film. After elements identification, their chemical and valence states were analyzed by narrow scans and results are shown in Figure 4.20 (b-d).

In the high resolution Ti 2p spectrum, Figure 4.20 (b), the binding energies of 458.7 and 464.4 eV are indicative of Ti 2p3/2 and Ti 2p1/2 respectively which correspond to Ti⁴⁺ and matches well with the published data for TiO₂ (G Zhou, et al., 2006; Chuang, et al., 2010). Figure 7(c), represents O1s spectra where a primary peak at 530 eV can be further divided into sub peaks centered at 529.7 and 530.2 eV attributing to Ti–O, Co–O in CoTiO₃, respectively (G Zhou, et al., 2006; Chuang, et al., 2010). Two peaks at 531.4 and 532.6 eV are assigned to the adsorbed oxygen and hydroxyl oxygen, respectively.

The high resolution Co 2p spectrum is shown in Figure 4.20(d). Two main peaks at binding energies of 781.5 and 797.3 eV correspond to Co $2p_{3/2}$ and Co $2p_{1/2}$. The difference (Δ) between Co 2p1/2 and Co 2p3/2 orbital is nearly 16 eV, which implies the fundamental oxidation state of high-spin Co²⁺, and is very similar to those reported earlier for CoTiO₃ (Y. Liang et al., 2013; Shilpy, et al., 2015). Moreover, the splitting of the Co

2p1/2-Co 2p3/2 orbital components Δ is usually 15 eV for the low-spin Co³⁺. Toward the left of each main peak is a satellite peak known as a shake-up line which occurs when Co (II) resides in a high spin state. Thus, the XPS results strongly suggest the formation of phase pure CoTiO₃-TiO₂ composite oxide films.



Figure 4.20: (a) XPS spectra of CoTiO₃-TiO₂ composite thin films prepared at 550 °C from ethanol solution of precursor (1) ; High resolution spectra CoTiO₃-TiO₂ for (b) Ti 2p (c) O 1s (d) Co 2p.

4.2.7 Electrochemical detection of dopamine (DA) by CoTiO₃-TiO₂ film electrode4.2.7.1 CV behavior of DA

The CoTiO₃-TiO₂ composite film deposited at 550 °C was used for the electrocatalysis and sensing of dopamine (DA) in 0.1 M phosphate buffer solution (PBS) (pH 7.0). Figure 4.21 represents cyclic voltammograms (CVs) both in absence and presence of DA in a phosphate buffer solution, also containing 10 mM of Ascrobic acid (AA), a common interfering specie for DA.



Figure 4.21: Cyclic voltammograms (**a**) absence, (**b**) presence of 15 μ M DA obtained with the CoTiO₃-TiO₂ composite electrode; (**c**) absence and (**d**) presence of 50 μ M DA recorded with the bare FTO electrode in the in 0.1 M PBS (pH 7.0) at a scan rate of 50 mV s⁻¹.

The potential was scanned between -0.2 to +0.6 V. It is evident from Figure 4.21(a) that no redox peaks were observed in the absence of DA, which also infers that AA was not electrochemically active in this potential window. Figure 4.21(b) represents that the CoTiO₃-TiO₂ composite electrode displayed an intense and sharp anodic peak current at +0.215 V due to the electrocatalytic oxidation of dopamine when 15 µM of DA was present in the buffer solution. The corresponding reduction peak appeared at +0.075 V but with much less current density representing the quasi-reversible redox behavior of DA. The sharp peak for DA oxidation at +0.215 V was also indicative of fast electrode kinetics for the DA oxidation (Ping, Wu, Wang, & Ying, 2012; L. Wu, Feng, Ren, & Qu, 2012). To observe contribution from FTO towards DA oxidation, CVs in presence and absence of DA were recorded with bare FTO electrode as shown in Figure 4.21(c,d). The voltamograms indicate that in the absence of DA no redox peaks were observed and background current was higher than the CoTiO₃-TiO₂ composite electrode. In the presence of 50 μ M of DA and AA, only a slight increase in current was observed with a broad oxidation peak starting from approximately 0.22 V and extending up to 0.6 V. These results clearly indicate that the CoTiO₃-TiO₂ composite electrode is capable to catalytically oxidize DA with a sharp oxidation peak within the tested potential window.

4.2.7.2 Effect of scan rate on CV studies

Further, influence of the potential scan rate on the electrocatalytic activity of DA at the CoTiO₃-TiO₂ film electrode surface was studied in the PBS (pH = 7.0) using CV, as shown in Figure 4.22. Increase in scan rate from 25 to 200mV/s led to the increase in both DA oxidation and reduction peaks with a slight shift in the peak potential. The shift in peak potential was due to the quasi-reversible redox process (D. Wu et al., 2013). The linear relationship between the peak currents (I_p) and the square root of the scan rate was observed for both oxidation and reduction processes as shown in the inset of Figure 4.22. It is evident that, the anodic peak currents (I_{pa}) for the 10 μ M DA varied linearly with the square root of the scan rate (v^{1/2}), with a linear regression equation, for anodic peak current I_{pa} (μ A) = 0.0563v^{1/2} + 11.40 and a correlation coefficient R² = 0.985. This behavior suggests that the electrode kinetics is mainly diffusion controlled electrochemical reaction.



Figure 4.22: Cyclic voltammograms recorded for the CoTiO₃-TiO₂ electrode in the presence of 10 μ M DA in 0.1 M PBS (pH 7.0) at various scan rates 25–200 mV s⁻¹. (Inset) Plot of anodic peak current vs. square root of the scan rate obtained with the CoTiO₃-TiO₂ electrode.

4.2.7.3 Effect of pH

pH plays a crucial role in the redox behavior of DA at the $CoTiO_3$ -TiO₂ film electrode surface. In fact, in CV experiments, redox couple of DA shifted towards the negative direction upon increasing the pH from 5-9, Figure 4.23. This infers that electrocatlaytic behavior of DA is pH dependent. For practicality purposes, pH 7 was chosen for further analysis of DA with the CoTiO₃-TiO₂ composite electrode.



Figure 4.23: (a-c) Cyclic voltammograms recorded at CoTiO₃-TiO₂ electrode for 2 μ M of DA in 0.1 M PBS with different pH values at scan rate of 50 mVs⁻¹.

4.2.7.4 Analytical utilization

A series of linear scan voltammetry (LSV) curves were recorded in 0.1 M PBS (pH = 7.0) with different DA concentrations at the CoTiO₃-TiO₂ composite as shown in Figure 4.24 (a). It could be observed that the anodic peak current increased linearly with an increase in the concentration of DA in the range of 20 to 300 μ M, with R² = 0.993 (Figure 4.24b).

The sensitivity is determined from the slope of the calibration plot. The Figure 4.24 (b) shows the standard addition line with linear regression equation. The detection limit found was 0.083 μ M (S/N = 6) by LSV. The sensitivity found from the slope was 0.325 μ A. μ M⁻¹.cm².



Figure 4.24: (a) LSV curves obtained with the CoTiO₃-TiO₂ composite electrode for various concentration of DA 0.1 M PBS (pH 7) at a scan rate of 50 mV s⁻¹. (b)
Correlation between the concentration of DA and peak current for the CoTiO₃-TiO₂ electrode.

4.2.7.5 Selectivity and stability studies

The selectivity of the CoTiO₃-TiO₂ electrode towards DA oxidation was also investigated by LSV. Common interfering species AA, uric acid (UA), glucose, sulphate, nitrate and chloride were chosen and their effect on DA oxidation signal was evaluated as represented in Figure 4.25. It is evident that even when 100-fold higher concentration of an interference source is used in a homogeneously stirred of 0.1 M PBS (pH 7), there is no significant current response in the potential window used for DA analysis. This clearly suggested that DA oxidation at the fabricated CoTiO₃-TiO₂ composite was more selective and not affected in the presence of common interferences.



Figure 4.25: LSV response obtained with the CoTiO₃-TiO₂ composite electrode for 100 μ M of each interferent and 10 μ M Dopamine in 0.1 M PBS (pH 7) at scan rate of 50 mV s⁻¹.

The stability of $CoTiO_3$ -TiO₂ composite electrode was also monitored over the period of study. There was no significant loss observed in response for DA over 4 weeks with the standard deviation (RSD) of 3.4 %. Such a high stability of the CoTiO₃-TiO₂ composite

electrode can be accredited to inherent properties of metal oxides compared to electrodes modified with pure metallic gold or platinium nanoparticles (J. Li et al., 2012).

Sensor Material	Analytical techniques	Limit of detection (LoD) (µM)	Ref.
Au-Pt/GO-ERGO	Cyclic voltammetry	0.02	(Y. Liu et al., 2015)
NiO-CuO/GR/GCE	Square Wave voltammetry	0.10	(B. Liu, et al., 2016)
GO-La/CPE	Differential pulse voltammetry	0.00032	(F. Ye, et al., 2015)
EPPGE-SWCNT– Fe ₂ O ₃	Square Wave voltammetry	0.36	(Adekunle, Agboola, Pillay, & Ozoemena, 2010)
GO/SiO ₂ -MIPs/GCE	Amperometry	0.03	(Zeng, Zhou, Kong, Zhou, & Shi, 2013)
ZnO- GCE	Amperometry	0.06	(Xia, Wang, Wang, & Guo, 2010)
Graphene-AuNPs	Differential pulse voltammetry	1.86	(J. Li, et al., 2012)
CoTiO ₃ -TiO ₂	Linear scanning voltammetry	0.083	Present work

 Table 4.4: Comparison of analytical performance of various electrochemical sensors for DA detection

ERGO = Electrochemically reduced graphene oxide, GCE = glassy carbon electrode, CPE = Carbon paste electrode

GO = graphene oxide , MIP = molecularly imprinted polymers, EPPGE = edge-plane pyrolytic graphite electrode

The sensing performance of the $CoTiO_3$ -TiO₂ film electrode was compared with other previously reported sensor materials for the detection of DA and the results are
summarized in Table 4.4 which reveals that the present electrocatalyst performs equally good to the other bimetallic or metal oxide composite with carbon nanotubes (CNTs) and graphene oxide (GO) for the oxidation of DA.

It is very well known that the use of CNTs and GO provides large network for collecting electrons from oxidation process thereby assisting efficient current generation to improve the detection performance of electro catalyst. However, considering the prolong synthetic methods of these catalysts and high cost of Pt and Au metals, present catalyst prepared from AACVD technique is suitable alternative to Pt and Au free electrocatalyst for the DA oxidation with low cost and ease of fabrication.

4.3 Synthesis and Characterization of Complex [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]· THF (3)

The of synthetic protocol heterobimetallic precursor [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆]·THF involves the of (3) reaction diacetatomagnesium(II) tetrahydrate with tetraisopropoxytitanium(IV) in presence of trifluoroacetic acid in THF. As the reaction progresses, the more labile isopropoxy ligands are exchanged by stronger chelating TFA groups which bind Mg and Ti atoms through its carboxylate oxygen atoms. The exchange of ligands and progress of the reaction can be observed by dissolution of salts to result in a clear solution. The transparent solution was then evaporated in vacuum to obtain a white powder which was re-dissolved in 3 mL THF and kept at room temperature to grow the first 70% yield of translucent white crystals of the precursor (3). The overall reaction for the formation of (3) is shown below in equation.

Chemical equation 5

 $2Mg(CH_{3}COOH)_{2}.4H_{2}O + 4Ti(OCH(CH_{3})_{2})_{4} + 8CF_{3}COOH \xrightarrow{THF} \\ [Mg_{2}Ti_{4}(O)_{2}(OH)_{4}(CF_{3}COO)(C_{4}H_{8}O)_{6}].C_{4}H_{8}O + 4CH_{3}COOH + 16(CH_{3})_{2}CHOH \\ \end{cases}$

The substitution of acetate with TFA groups not only aids binding of Mg and Ti atoms in one framework but also co-ordinatively saturates each metal center, making the precursor more volatile as well as soluble in organic solvents such as chloroform, THF, methanol and ethanol, rendering it a suitable precursor to produce single phased MgTi₂O₅ thin films by the AACVD method. The stoichiometric composition of (**3**) was recognized by single crystal X-ray diffraction and further confirmed by FTIR and TG/DTG analysis. The FT-IR spectrum of Mg-Ti precursor showed strong absorption bands at 1654 and 1453 cm⁻¹ due to the asymmetric and symmetric v(C=O) vibrations of the carboxylate group of the TFA ligands respectively. The difference of value $\Delta v_{asy^-} \Delta v_{sy} = 200 \text{ cm}^{-1}$ is consistent with the bidentate bridging behavior of TFA ligand. Similarly, a sharp peak at 1192 cm⁻¹ confirms the existence of C–F bonds in (**3**). The IR spectrum is closely related to those reported previously for similar heterobimetallic compounds.

4.3.1 Molecular Structure of Complex [Mg2Ti4(O)2(OH)4(TF)8(THF)6]·THF (3)

The structure of (3) is isomorphous with that of the copper analog $[Cu_2Ti_4(O)_2(OH)_4(CF_3COO)_8(THF)_6]$ ·THF and shows the same severe disorder. The structure was solved in space group *Pbca*, and is disordered about the centre of symmetry. The core of the molecule consists of a tetrahedron of Ti(II) ions (Figure 4.26). Each edge of the tetrahedron is bridged by an oxygen atom (O^{2–} or OH[–]), generating a Ti₄O₆ adamantane-type cage. Four of the bridging species are hydroxo ions; the remaining two are oxo ions which are also coordinated to Mg (II) ions. The disorder arises from titanium ions occupying alternative sites, generating a second, overlapping adamantine with the oxygen atoms in the same positions. Four trifluoroacetate ions are bonded to each magnesium ion; each trifluoroacetate also bridges to a titanium ion. All of the metal ions

are six-coordinate, the last binding site being filled by one coordinated THF molecule in each case (Figure 4.27). There is also a non-coordinated THF solvate molecule in the lattice.



Figure 4.26: Perspective view of the core of (**3**). CF₃COO⁻ ions are represented by OCO links; terminal O atoms represent THF molecules, bold bonds highlight the Ti₄O₂(OH)₄ adamantane core. Atoms with suffix "A" generated by symmetry operation 1-x, 1-y, 1-z.



Figure 4.27: Perspective view of the $[Mg_2Ti_4(O)_2(OH)_4(CF_3COO)_8(THF)_6]$ (3) molecule. One component of the disorder and H atoms are omitted for clarity.

$C_{40}H_{52}F_{24}Mg_2O_{28}Ti_4{\cdot}C_4H_8O$	$V = 6956.1 (4) \text{ Å}^3$			
$M_r = 1749.14$	Z = 4			
Orthorhombic, Pbca	Mo <i>K</i> α radiation, $\lambda = 0.71073$ Å			
<i>a</i> = 19.2879 (7) Å	$\mu = 0.60 \text{ mm}^{-1}$			
<i>b</i> = 17.3364 (6) Å	T = 150 K			
c = 20.8027 (7) Å	$0.28 \times 0.26 \times 0.23 \text{ mm}$			
Data collection	0			
Bruker APEX 2 CCD diffractometer	8627 independent reflections			
Absorption correction: multi-scan SADABS v2012/1, (Krause et al., 2015)	6572 reflections with $I > 2 \Box(I)$			
$T_{\min} = 0.677, T_{\max} = 0.746$	$R_{\rm int} = 0.050$			
69548 measured reflections				
Refinement	K I			
$R[F^2 > 2 \sigma(F^2)] = 0.088$	2012 restraints			
$wR(F^2) = 0.230$	H-atom parameters constrained			
<i>S</i> = 1.09	$\Delta > _{\rm max} = 0.58 \ {\rm e} \ {\rm \AA}^{-3}$			
8627 reflections	$\Delta \ge _{\rm min} = -0.68 \ {\rm e} \ {\rm \AA}^{-3}$			
955 parameters				

Table 4.5: Crystal data and refinement parameters for $[Mg_2Ti_4(O)_2(OH)_4(TF)_8(THF)_6]$ ·THF (3)

4.3.2 Thermogravimetric Analysis of Precursor [Mg₂Ti₄(O)₂(OH)₄(TFA)₈(THF)₆] •THF (3)

Prior to thin film growth from precursor (**3**), thermogravimetric (TG) and derivative thermogravimetric (DTG) analysis were performed to study the step-by-step decomposition of the precursor compound and the evolution of the target material that may experience subtle phase changes during analysis. The optimal temperature suitable for the complete pyrolysis of the precursor was also probed and applied for the deposition of thin films.



Figure 4.28: TG (black) and DTG (red) curves showing pyrolysis of precursor (3) as a function of temperature under an inert nitrogen ambient and heating rate of 10 °C min-¹ TGA/DTG profiles (Figure 4.28) of precursor (**3**) displayed an unceasing threestep degradation process with a rapid weight loss of 3.6%, 19.0% and 56.5% at 112 °C, 215 °C and 282 °C, respectively. The weight of the remaining residue at 575 °C is 20.9%, which corresponds to MgTi₂O₅ (calculated percentage 20.6 %). Further sintering of the observed residue to the higher temperature of 800 °C did not bring any appreciable change in weight, suggesting that precursor (**3**) decomposes quantitatively to endow MgTi₂O₅ as a stable final product. Based on TGA information, quantitative pyrolysis of (**3**) has been indicated in equation below:

Chemical equation 6:

$$[Mg_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6] \cdot THF \xrightarrow{500 \text{ °C}} 2MgTi_2O_5 + Volatiles$$

4.3.3 XRD Analysis of MgTi₂O₅ thin film

Magnesium dititanate films via AACVD were grown at three different temperatures of 500, 550 and 600 °C from ethanolic solution of precursor (3) using air as a carrier gas. XRD analysis was carried out to obtain information on chemical formula and purity of the deposited phase and diffraction patterns as function of substrate temperature are depicted in Figure 4.29. Apparently, all the XRD patterns look similar in terms of their peak positions and 20 values however the diffraction peak intensities displayed a notable increase with the rise in deposition temperature. Each XRD pattern, in Figure 4.29 was carefully matched with the standard Inorganic Crystal Structure Database which reveals the formation of "Armalcolite (Fe-free) MgTi₂O₅" ICSD = [98-003-7232] as a crystalline product in each case. The as-synthesized MgTi₂O₅ crystallizes in the orthorhombic crystal system with a = 3.7450, b = 9.7280, c = 9.9900 Å and $\alpha = \beta = \gamma = 90^{\circ}$. As shown in Fig. 4, each peak related to MgTi₂O₅ have been indexed by its standard reflection plane and peaks labelled by (*) correspond to the SnO₂ layer of the FTO substrate. No obvious impurity peaks of TiO₂, MgTiO₃ or Mg₂TiO₄ phases appeared in these XRD patterns. This clearly indicates that the precursor (3) decomposes cleanly at all temperatures of 500, 550, 600 °C to yield the pure crystalline orthorhombic phase of MgTi₂O₅. This formation temperature is considerably lower than the temperature reported (1000-1200 °C) in recent works for MgTi₂O₅ powder synthesis through solid state techniques. Although the synthesis of MgTi₂O₅ nano powders had been achieved even at the lower temperature of 600 °C by various wet processes. The formation of phase pure MgTi₂O₅ thin films via SMP based AACVD route coincides well with previous investigations (N. Zhang et al., 2015; N. Zhang, Qu, Pan, Wang, & Li, 2015).



Figure 4.29: XRD patterns of $MgTi_2O_5 ICSD = [98-003-7232]$ films deposited on FTO glass substrate at different temperatures of 500 (black line), 550 (blue line) and 600 °C (green line) from ethanolic solution of precursor (**3**).

4.3.4 Surface Morphologies and Compositions of MgTi₂O₅ Thin Film

Figure 4.30 shows FESEM micrographs of the surface microstructure of MgTi₂O₅ thin films developed at different temperatures of 500, 550 and 600 °C from ethanol solution of the precursor (**3**) on FTO glass substrates. At 500 °C, an obvious growth of spherical objects can be observed by low resolution SEM image (Figure. 4.30a), although the substrate surface is not fully covered by these objects. An increase in the deposition temperature to 550 °C, intensified the thin film growth rates and the substrate surface is completely decorated with these spherical objects. The nucleation and growth of spherical objects further increases with increase in deposition temperature to 600 °C which results in formation of compact and uniform spherical features of MgTi₂O₅. High resolution images, Figure 4.30 (b, d and f) indicate that the shape and design of these microspheres remain unaffected by rise in deposition temperature and porous MgTi₂O₅ microspheres in size range of 0.3- 1.8µm have been observed at all temperatures.



Figure 4.30: (a,c, e) low resolution (2KX) and (b, d, f) high resolution(20KX) FESEM images of MgTi₂O₅ thin films deposited on FTO glass substrate from ethanolic solution of precursor (3) at temperatures (a, b) 500 °C (c, d) 550 °C and (e, f) 600 °C, respectively.

The FESEM images display the regularly interconnected porous spherical microstructure of the film prepared at 600 °C; this is highly suitable for PEC applications where liquid electrolytes can penetrate in the interior of the film to provide the required large area of solid/electrolyte interfaces for charge transfer reactions (Malengreaux et al., 2014).

The elemental stoichiometry of all the films were probed by energy dispersive X-ray (EDX) analysis and spectra are shown in Appendix 4 (i, ii and iii) which indicates that the metallic ratios of Mg and Ti is about 1:2, that matches well with the expected elemental ratio present in the precursor complex (**3**) and MgTi₂O₅ formula identified from XRD results. The various peaks originating from substrate elements (Sn, Si, Ca, Na, F) were not omitted from EDX spectra.

4.3.5 XPS Analysis of MgTi₂O₅ Thin Film

MgTi₂O₅ film obtained at 600 °C was employed to XPS analysis for the investigation of chemical and valence states of the constituent elements and results are depicted in Figure 4.31. The survey scan spectrum in Figure 4.31a confirms that Mg, Ti and O are major components at the surface of the film. The high resolution spectrum (Figure 4.31b) indicates that strong peak at 49.6 eV is indicative of Mg²⁺ ion and is in good agreement with the reported data for Mg 2p3/2 (N. Zhang, Y. Qu, et al., 2015; N. Zhang, K. Zhang, et al., 2015). The binding energies of 458.66 and 464.37 eV are indicative of Ti 2p3/2 and Ti 2p1/2 respectively which correspond to Ti⁴⁺ and matches well with the published data for TiO₂. (Figure 4.31c) Meanwhile, the peak at 529.94 eV, in Figure 4.31(d) is accredited to Ti–O and Mg–O in MgTi₂O₅. Two small peaks at 531.13 and 532.15 eV are assigned to the atmospheric oxygen and hydroxyl oxygen, respectively.

Taken together, the XRD, EDX and XPS data confirm that pure orthorhombic phase MgTi₂O₅ films have been successfully prepared from precursor (**3**).



Figure 4.31: (a) XPS spectra of MgTi₂O₅ film prepared at 600 °C from precursor (3) ; High resolution spectra of MgTi₂O₅ for (b) Mg 2p, (c) Ti 2p (d) O 1s.

4.3.6 Optical Band Gap of MgTi₂O₅ Thin Film

The optical properties of MgTi₂O₅ film deposited at 600 °C were investigated using UV– vis spectrophotometry; the absorption spectrum shown in Figure 4.32 reveals that no significant absorbance occurs in visible region and MgTi₂O₅ film exhibits steep photoabsorption features in wavelength range from 350-390 with absorption tail at 450nm. The Tauc's formula, $\alpha hv = A(hv-E_g)^{\gamma}$, for the optical band gap determination was employed, where, α is the linear absorption coefficient of the material, hv is the photon energy, A is a proportionality constant. Among these, γ determines the characteristics of the transition in a semiconductor, a value $\gamma = \frac{1}{2}$ signifies allowed direct band gap and $\gamma =$ 2 stands for indirect band gap. The inset Tauc plot in Figure 4.32 demonstrates a direct band gap of 3.4 eV for MgTi₂O₅ film which is in good agreement with the literature reported value for phase pure magnesium dititanate (Suzuki & Shinoda, 2016). This observation suggests that the impurity free MgTi₂O₅ film developed in this work acts as a photocatalyst under UV light irradiation.



Figure 4.32: (a) UV-visible spectrum of MgTi₂O₅ film deposited from precursor (**3**) at 600 °C on the FTO substrate. The inset shows the Tauc's plot of $(\alpha hv)^2$ vs photon energy (eV) obtained for the MgTi₂O₅ film.

4.3.7 Photoelectrochemical Performance of MgTi₂O₅ thin film

The MgTi₂O₅ (MT) film electrodes developed at three different temperatures were further investigated for photoelectrochemical water splitting for H₂ production. The PEC performance of the microspherical electrodes, MT-500, MT-550 and MT-600 designed at 500, 550 and 600 °C respectively, were investigated in presence of 1 M NaOH under dark (D) and simulated solar irradiation (L) of AM 1.5G (100mW/cm²) (Saremi-Yarahmadi, Tahir, Vaidhyanathan, & Wijayantha, 2009) and their corresponding Linear Scanning Voltammograms (LSVs) are shown in Figure 4.33a. The dark current from -0.6 V to +0.7 V(vs. Ag/AgCl) of all MgTi₂O₅ electrodes was almost zero due to inactivation of electron-holes phenomenon. Interestingly, when MgTi₂O₅ electrodes are exposed to light, they exhibit significantly enhanced photocurrent response due to the triggering of photo-induced electro-hole pair separation. It has been observed that MT-600 electrode produces maximum photocurrent density of 400 µA cm⁻² at 0.7 V as compared to the film electrodes MT-500 and MT-550 that produce photocurrent density of 148 and 226 µA cm⁻² respectively. This difference in the PEC performances of these electrodes can be explained on the basis of different thin film deposition temperatures that significantly affect the thickness, crystallinity and porosity of MgTi₂O₅ electrodes (Figure 4.30). The more thick and compact microspherical architecture of MgTi₂O₅ electrode developed at 600 °C (Figure 4.30c to c2) is found more attractive for unidirectional charge transport while its regularly connected porous structure allows the electrolyte to penetrate via the pinholes thereby enhancing the PEC efficiency as compared to the films fabricated at 500 and 550 °C. Although the MT-500 and MT-550 electrodes are also comprised of crystalline porous microspherical entities but they are loosely bonded and their lower film thicknesses are responsible for the decrease in their photocurrent densities. The maximum photocurrent density of 400 µA cm⁻² measured for MT-600 electrode is significantly improved than the previously reported photocurrent densities for MgTi₂O₅ (102 μ A cm⁻²) and Mg_{1.2}Ti_{1.8}O₅ (61 μ A cm⁻²) nanocrystals electrodes (N. Zhang, K. Zhang, et al., 2015; N. Zhang, Y. Qu, et al., 2015).

To authenticate the PEC performances of MgTi₂O₅ photoanodes, amperometric I–t studies were performed at 0.7 V vs. Ag/AgCl under on–off illumination conditions. Figure 4.33 (b) shows that all MgTi₂O₅ photoanodes exhibit steady and reproducible photocurrent responses and no significant decrease in the photocurrents was observed during various on-off illumination cycles for 1 hour which indicate the higher efficiency and good stabilities of all photoelectrodes prepared at different temperature. Moreover, the transient photocurrents recoded for MT-500 (148 μ A cm⁻²), MT 550 (226 μ A cm⁻²) and MT-600 (400 μ A cm⁻²) agree well with their LSV results and strengthened the PEC

performance of the MgTi₂O₅ electrodes. Again, the amperometric photocurrent response is found to be better and durable than those observed previously for MgTi₂O₅ and Mg_{1.2}Ti_{1.8}O₅ nanocrystal electrodes (N. Zhang, Qu, Pan, Wang, & Li, 2016; N. Zhang et al., 2015).



Figure 4.33: (a) Linear Sweep Voltammograms and (b) transient photocurrent response recorded for MgTi₂O₅ film electrode in 1M NaOH under simulated AM 1.5 illumination of 100 mWcm⁻²

The charge separation and transportation are key factors in establishing the photocatalytic performances of a semiconductor material; therefore, electrochemical impedance measurements (EIS) were conducted to demonstrate the charge separation and transfer dynamics in MgTi₂O₅ photoelectrodes. The Nyquist plots obtained from the EIS

measurements under light and dark conditions for the MgTi₂O₅ films deposited at 500, 550 and 600 °C in the presence of 1 M NaOH in the frequency range of 0.1 Hz-10 kHz are displayed in Figure 4.33 (a) and (b), respectively.

Under dark condition each MT-500, MT-550 and MT-600 electrodes exhibited a semicircle like Nyquist plot (Figure 4.34a) with higher the electron transfer resistance (R_{ct}) values (Table 4.6) which suggests hindrance to the electron-transfer kinetics at the electrode surface (Figure 4.34a). While under illumination, the electron transfer resistance (R_{ct}) values in all the film electrodes is decreased as compared to the dark indicating better charge electron transfer with low charge resistance (Figure 4.34b, and Table 4.6). Moreover, under illumination, MT-600 electrode produced lowest R_{ct} value as compared to MT-550 and MT-500 electrodes, indicating the efficient charge separation and transfer across the electrode-electrolyte interface as well as reducing the possibility of charge recombination at the surface of the film fabricated 600 °C than those prepared at 500 and 550 °C. These results indicate that the formation of tightly packed mesoporous microspherical design of MT-600 plays a vital role in charge transfer mechanism under light which are in good agreement with LSV results.



Figure 4.34: EIS Nyquist plots obtained for the MgTi₂O₅ films fabricated at 500, 550 and 600 °C at frequency range of 0.1 Hz-10 kHz in (a) dark and (b) light conditions

Film electrode	R _{ct} (ohm)	f _{max} (Hz)	τ _n (msec)
MT 500 (L)	1301	0.85	187
MT 550 (D)	3128	23.2	6.89
MT 550 (L)	730	0.44	363
MT 600 (D)	2775	11.06	14.4
MT 600 (L)	600	0.19	842

Table 4.6: Charge transfer resistance, maximum frequency and recombination lifetime calculated for $MgTi_2O_5$ film electrodes fabricated at 500, 550 and 600 °C via AACVD.

 R_{ct} – Charge transfer resistance; f_{max} – Maximum frequency; τ_n – recombination lifetime. The frequency dependence phase angle plots (Bode plot) were recorded for detailed understanding of the charge-transfer resistance phenomenon in MgTi₂O₅ electrodes. The Bode phase plots obtained for the MgTi₂O₅ electrodes under dark and light conditions are shown in Figure 4.35 (a) and (b) respectively. It has been observed that the characteristic frequency peaks are shifted under dark and light conditions for the MgTi₂O₅ electrodes fabricated at different temperatures. Figure 4.35 (a) shows that MT-500, MT-550 and MT 600 electrodes showed the frequency peak maximum (f_{max}) at 48.8, 23.2 and 11.06 respectively in dark condition. However, the shifting of peaks toward the low frequency region below 0.1 Hz in presence of light indicates (Figure 4.35b) the rapid electrontransfer behavior of all MT electrodes. The conducting nature of MT-600 under light facilitates the peak shift in the Bode plot. The phase angle of the plot under illumination is less than 90° at higher frequency and there is lesser log z value in low frequency range of 1-100 Hz which suggests that electrode does not behave like ideal capacitor (M. M. Shahid et al., 2015). These characteristic frequencies can be used to calculate the electron recombination lifetime (τ_n) of the material with following relationship (Lim et al., 2014):

$$\tau_n = \frac{1}{2\pi f_{max}}$$

Where f_{max} is the frequency peak maximum. The calculated recombination life time (τ_n) for MT-500, MT-550 and MT-600 in absence and presence of light are listed in Table 4.6 which indicates that the lifetime of charge carriers in MgTi₂O₅ electrodes is prolonged effectively under light compared to dark conditions. The highest τ_n is calculated for MT-600 (L) confirming the production of highest current density in MgTi₂O₅ film fabricated at 600 °C.



Figure 4.35: Bode phase plots obtained for the MgTi₂O₅ films fabricated at 500, 550 and 600 °C at frequency range of 0.1 Hz-10 kHz in (a) dark and (b) light conditions. The Mott–Schottky (MS) approach is a usual way to obtain information about flat band potential and the charge density values and type of semiconductor material. Figure 4.36 shows the MS plot of MgTi₂O₅ film measured as a function of applied potential at a frequency of 1 kHz using 1M NaOH in dark condition which indicates that MgTi₂O₅ is a n-type semiconductor due to the positive slope in MS plot, as expected for n-type materials. The flat band potential values measured from the slope and intercept of the MS curve were found to be -1.35V. It is well-known that the materials with a more negative flat band potential have a better ability to facilitate charge transport in PEC applications.



Figure 4.36: Mott –Schottky plot of MgTi₂O₅ film obtained at frequency of 1kHz in 1M NaOH.

Thus, the porous spherical designed MgTi₂O₅ photoelectrode developed from precursor (**3**) displays higher photocurrent density, smaller interface impedance and higher charge density. These results indicate that the PEC response is very auspicious and competitive as compare to the outcomes of other well established magnesium titanate nanocrystal materials (N. Zhang, Qu, Pan, Wang, & Li, 2016; N. Zhang et al., 2015).

We tentatively attribute this enhancement to the higher purity achieved in the MgTi₂O₅ phase through SSP (**3**) which, because of its exact metallic ratio (Mg/Ti 1:2), eliminates the growth of impurity phases of TiO₂, MgTiO₃ and Mg₂TiO₄. Another key factor is the formation of porous and well-connected microspherical architecture in MgTi₂O₅ which gives the film a large effective surface area, amplified photo absorption ability and an increased electrode electrolyte interfacial area, leading to a reduction in electron-hole recombination as the photogenerated hole travels through fewer material before being collected at the electrode/electrolyte interface and hence increasing cell efficiency (T. W. Kim & Choi, 2014).

4.4 Synthesis and Characterization of Complex [Mn(dmae)₂(TFA)₄] (4)

A mononuclear Mn-complex [Mn(dmae)₂(TFA)₄] (**4**) (TFA = triforoacetato, dmae = N, N-dimethylaminoethanolato) was prepared by the replacement of the acetate ligands by the more strongly chelating TFA and dmae moieties in stoichiometric quantities of manganese(II) acetate dehydrate and trifuoroacetic acid in THF solution as shown in the following chemical equation.

Chemical equation 7:

 $Mn(CH_3COO)_2 4H_2O + 4CF_3COOH + 2(CH_3)_2NCH_2CH_2OH$

THF

 $[Mn((CF_3COO)_4(O(CH_2)_2N(CH_3)_2] + 2 CH_3COOH + 4H_2O$

The above reaction produced complex (**4**) in 75 % yield in form of transparent white crystals that are stable in air and moisture and soluble in common organic solvents such as methanol, ethanol and THF. The stoichiometric composition of the complex was first ascertained by single crystal X-ray diffraction analysis and was supported by elemental analysis, FT-IR and thermogravimetry. Elemental analysis: % calculated (found) for $[Mn(dmae)_2(TFA)_4]$ C, 21.11 (20.83), H, 1.77 (1.69), N, 2.05 (1.95). The FT-IR spectrum of complex (**4**) clearly indicates the presence of the asymmetric and symmetric v(C=O) vibrations of trifluoroacetato ligand have been located at 1635 and 1444 cm⁻¹ respectively. The difference of 191 cm⁻¹ between asymmetric and symmetric v(C=O) vibrations designates the bidentate nature of the carboxylate groups of trifluoroacetato ligands that are bonded to different Mn centre (Mansoor, Mazhar, McKee, & Arifin, 2014; Mansoor et al., 2016). Similarly, the peak at 1177 cm⁻¹ confirms the presence of C–F bonds in

complex (4). The absorption at low frequency of 502 cm⁻¹ is due to stretching vibration mode of (M-O).

4.4.1 Single Crystal Analysis of Complex [Mn(dmae)₂(TFA)₄] (4)

The molecular structure of complex (**4**) is presented in Figure 4.37 while geometric parameters and structure refinement details are provided in Table 4.7 and 4.8, respectively. [Mn(dmae)₂(TFA)₄] is a monomeric coordination complex in which "Mn (IV)" cation lies at the center of symmetry. Mn (IV) is coordinated to four oxygen donor atoms from four independent TFA anions and two oxygen atoms from two different dmae molecules which occupy the equatorial position, thus, completing the approximate coordination sphere around the metal center. The co-ordination behavior of each TFA anion is monodentate and four oxygen atoms are coordinated with both syn and antigeometry. Similarly, each dameH molecules also act as a monodentate ligand. No distortion from linearity is observed at the Mn(IV) center and there are not any notable interactions found in the crystal structure.



Figure 4.37: ORTEP diagram of complex (4) at the 50 % probability level.

Identification code			
Empirical formula	C16 H24 F12 Mn N2 O10		
Formula weight	687.31		
Temperature	114(2) K		
Wavelength	0.71073 Å		
Crystal system	Orthorhombic		
Space group	P b c a		
Unit cell dimensions	a = 9.0076(6) Å		
<i>α</i> = 90°.			
	b = 16.6072(12) Å		
$\beta = 90^{\circ}.$			
	c = 18.0267(11) Å		
$\gamma = 90^{\circ}.$			
Volume	2696.6(3) Å ³		
Ζ	4		
Density (calculated)	1.693 Mg/m ³		
Absorption coefficient	0.623 mm ⁻¹		
F(000)	1388		
Crystal size	0.500 x 0.300 x 0.300 mm ³		
Theta range for data collection	3.197 to 28.694°.		
Index ranges	-8<=h<=11, -22<=k<=21, -		
	20<=l<=24		
Reflections collected	13593		
Independent reflections	3427 [R(int) = 0.0350]		
Completeness to theta = 25.242°	99.8 %		
Absorption correction	"multi-scan"		
Max. and min. transmission	0.4329 and 0.3934		
Refinement method	Full-matrix least-squares on		
	F ²		
Data / restraints / parameters	3427 / 51 / 207		
Goodness-of-fit on F^2	1.108		
Final R indices [I>2sigma(I)]	R1 = 0.0458, wR2 = 0.1153		
R indices (all data)	R1 = 0.0538, wR2 = 0.1211		
Extinction coefficient	n/a		
Largest diff. peak and hole	0.805 and -0.549 e.Å ⁻³		

 Table 4.7: Crystal data and structure refinement.

Mn(1)-O(3)#1	2.1065(15)	Mn(1)-O(3)	2.1065(15)
Mn(1)-O(5)	2.2005(14)	Mn(1)-O(5)#1	2.2005(14)
Mn(1)-O(1)#1	2.2175(14)	Mn(1)-O(1)	2.2175(14)

Table 4.8: Selected Bond lengths [Å]

4.4.2 Thermogravimetric Analysis of Complex [Mn(dmae)₂(TFA)₄] (4)

The thermal degradation of (**4**) has been examined by thermogravimetric (TGA) and differential thermogravimetric (DTG) analyses performed under flowing nitrogen ambient at a flow rate of 25 cm³/min with a heating rate of 10 °C/min (Figure 4.38).



Figure 4.38: TGA (black line) and DTG (red line) plot of complex (4) under nitrogen flow rate of 25 cm³ min⁻¹ and heating rate of 10 °Cmin⁻¹

The thermogram shows that the decay process in complex (**4**) occurs in two successive stages and the first major and rapid decomposition occurs in the temperature range of 179 to 260 °C with weight loss of 72.77 %. The second pyrolysis step is relatively slower and befalls in a wide temperature range of 260 to 550 °C giving a weight loss of 7.06%. The residual mass of 20.17 % observe at 550 °C indicates the formation of expected Mn_2O_3 oxide material from complex (**4**) as shown in following equation.

Chemical equation 8:

$$2[Mn((CF_{3}COO)_{4}(O(CH_{2})_{2}N(CH_{3})_{2}] \xrightarrow{550 \circ C} Mn_{2}O_{3} + Volatile$$

4.4.3 XRD Analysis of Pristine Mn₂O₃ and Ag-Mn₂O₃

Methanol solution of precursor (4) and its mixture with Ag(CH₃COO) were employed in AACVD for the formation of pristine Mn₂O₃ and Ag-Mn₂O₃ composite films, respectively, on FTO glass substrate at a temperature of 450 °C. The resultant films were examined by XRD analysis to identify the crystalline and chemical nature of the deposit and both the diffractograms are overlaid in Figure 4.39. In both the cases, the common Mn₂O₃ phase is in good agreement with standard ICDD card No [98-000-9091] (Appendix 5(i)) and belongs to cubic crystal system. The characteristics peaks of Mn₂O₃ indicated by (\blacklozenge) at $2\theta = 23.0^{\circ}$, 33.1° , 38.3° , 45.0° and 55.2° are originated from their Miller indices (012), (112), (222), (004) and (044) respectively. In Ag-Mn₂O₃ composite XRD pattern (Figure 4.39b), the metallic Ag is identified from its peaks at $2\theta = 38.1$ (111), 44.2 (002), 64.5 (022), 77.6 (113) and 81.9° (222) denoted by symbol (\bullet) and corresponds well to standard ICDD pattern number [01-071-6549] (Appendix 5(ii)). Peaks indicated by (*) are obtained from crystalline F:SnO₂ of the FTO substrate. These XRD patterns do not show any probable crystalline impurities such as MnO, MnO₂ and Mn₃O₄, Ag₂O or AgO. Therefore, we can infer that methanol solution of precursor (4) and its mixture with silver acetate are capable of generating phase pure Mn₂O₃ and Ag-Mn₂O₃ composite films, respectively, at 450 °C through AACVD method.



Figure 4.39: XRD patterns of pristine (**a**) Mn₂O₃ and (**b**) Ag- Mn₂O₃ composite thin films grown on FTO at 450 °C via AACVD

4.4.4 Raman Spectroscopy of Pristine Mn₂O₃ and Ag-Mn₂O₃

Pristine Mn₂O₃ and Ag-Mn₂O₃ composite films were further examined are comparatively shown in Figure 4.40. Figure 4.40 showed four Raman active modes at 195, 309, 644 and 691 cm⁻¹ in pristine Mn₂O₃ as reported in the literature (Han et al., 2007; Javed et al., 2012). These vibrational modes appeared to be out of plane band, asymmetric and symmetric bridging oxygen species Mn-O-Mn. On Ag-Mn₂O₃ composite formation scattering mode at 196 cm⁻¹ disappears and band at 309 cm⁻¹ remains at its place. The other two modes at 644 and 691 cm⁻¹ are shifted to lower wave numbers of 601 and 641cm⁻¹. This is perhaps the Mn-O band is effected by the presence of Ag metal. No characteristic peak for metallic Ag has been observed due to as pure metals do not exhibit raman scattering (Lewis & Edwards, 2001).



Figure 4.40: FT-Raman spectra of (**a**) pristine Mn₂O₃ and (**b**) Ag- Mn₂O₃ composite thin film deposited on FTO substrate by AACVD at 450 °C.

4.4.5 Surface Morphology of Pristine Mn₂O₃ and Ag-Mn₂O₃

The surface morphologies and microarchitectures of pristine Mn₂O₃ and Ag-Mn₂O₃ composite films developed at 450 °C via AACVD were examined by FESEM analysis and images are presented in Figure 4.41. The surface morphology of pristine Mn₂O₃ is consist of cubical shaped particles with sharp edges which are regularly grown on FTO substrate and making the film compact in nature. However Ag-Mn₂O₃ composite film grown at 450 °C exhibits a different kind of surface topography and various multi-shaped particles including triangular, octahedral, rod like objects in size range 200-400nm with clear grains boundary can be observed on FTO substrate Figure 4.41b. The composite nature of Ag-Mn₂O₃ was established by EDX map analysis (Figure 4.42) and results show that Ag, Mn and O atoms are uniformly dispersed throughout the film matrix.



Figure 4.41: FESEM images (a) pristine Mn₂O₃ (b) Ag-Mn₂O₃ composite thin films grown at 450 °C on FTO substrate.



Figure 4.42: Elemental map showing the distribution of Ag, Mn and O elements in Ag-Mn₂O₃ composite thin film.

The surface compositions of both types of films were analyzed by energy dispersive analysis (EDX) analysis. EDX spectra recorded at various arbitrary large areas (Appendix 6(i and ii)) revealed that the pristine manganese oxide films contains only Mn atoms throughout the film matrix. While the metallic ratio of Ag: Mn in composite films is found to be 1:2 which exactly matches with the formula of target Ag-Mn₂O₃ material.

4.4.6 XPS Analysis of Pristine Mn₂O₃ and Ag-Mn₂O₃

The pristine Mn_2O_3 and $Ag-Mn_2O_3$ composite films were employed to X-ray photoelectron spectroscopy (XPS) to investigate the composition, oxidation states and electronic structure of the involved atoms and results are presented in Figure 4.43. The survey scan spectra (Figure 4.43a) reveals that, except for the O 1s (530 eV) and Mn 2p (640 eV) peaks, the Ag 3d peaks emerged with strong relative intensities, showing that the Mn₂O₃ was mainly coated with Ag nanoparticles. In high resolution Mn 2p spectrum, Figure 4.42c, two main peaks at binding energies of 641.10 eV and 653.12 eV correspond to Mn 2p_{3/2} and Mn 2p_{1/2}. The difference (Δ) between Mn 2p_{3/2} and Mn 2p_{1/2} is 12 eV which implies a typical value for Mn³⁺ and is very similar to those reported earlier for Mn₂O₃ (Chigane & Ishikawa, 2000). The higher resolution XPS spectrum of the Ag 3d was fitted to two peaks at 368.43 and 374.43 eV for Ag3d_{3/2} and Ag3d_{5/2}, respectively (Sun et al., 2009; D. Wang et al., 2012) (Figure 4.42b). The difference (Δ) between Ag3d_{3/2} and Ag3d_{5/2} peaks is about the ~6eV indicating that Ag mainly exists in the Ag⁰ state on the Mn₂O₃ surface.

Meanwhile, the high resolution XPS spectrum of O1s, Figure 4.42d, exhibits asymmetric contours at about 530 eV, attributed with Mn–O in Mn₂O₃. The small peaks at 531 and 532 eV are assigned to the adsorbed oxygen and hydroxyl oxygen, respectively (Sekhar, Babu, & Kalaiselvi, 2015; Smith Stegen, 2015). The identical electronic structure (Mn 2p, O1s) confirms the formation of analogues Mn₂O₃ phases in both pristine Mn₂O₃ and Ag-Mn₂O₃ composite films. On the basis of XRD, EDX and XPS results, we infer that pristine Mn₂O₃ and Ag-Mn₂O₃ composite were successfully fabricated by AACVD in this work.



Figure 4.43: (a) Survey scan XPS spectra of pristine Mn₂O₃ (blue line) and Ag-Mn₂O₃ (red line). High resolution spectra for (b) Ag 3d, (c) Mn 2p (d) O 1s.

4.4.7 Optical Band gap of pristine Mn₂O₃ and Ag-Mn₂O₃

The optical band gap of as-synthesized pristine Mn_2O_3 and $Ag-Mn_2O_3$ composite thin films were recorded in UV-visible region of 350-800 nm and is shown in Figure 4.44 (a and b) respectively. It is obvious from the spectra that both the films continuously absorb in visible region from 400-750nm. The UV-vis data were applied to Tauc's formula and direct bandgaps E_g of 2.0 and 1.8 eV were measured for pristine Mn_2O_3 and $Ag-Mn_2O_3$ composite films, and from their respective Tauc's plots (Insets Figure). The bandgap of 2.0 eV is in good agreement with previous reported values for pure Mn_2O_3 prepared by different method (Naeem et al., 2015).



Figure 4.44: UV-Vis spectra of absorbance as function of wavelength and inset Tauc plot $((\alpha hv)^2$ Vs E/eV) of (a) Mn₂O₃ and (b) Ag-Mn₂O₃ thin films deposited at 450 °C on FTO substrate by AACVD.

The lowering of bandgap in case of Ag-Mn₂O₃ composite film is attributed with the plasmonic effect of metallic Ag on Mn₂O₃ oxide. The plasmonic effect of Ag on Mn₂O₃ is also evident from Raman scattering where two bands at 644 and 691 cm⁻¹ are shifted to lower frequency region. Similar plasmonic effect imparted by silver in attaining low band gap with better absorbance in the visible region of light have been reported in metal integrated metal oxide composites (Kharade et al., 2013; Lim, Pandikumar, Huang, & Lim, 2014).

4.4.8 Photoelectrochemical Studies of Pristine Mn₂O₃ and Ag-Mn₂O₃

The PEC properties of pristine Mn₂O₃ and Ag-Mn₂O₃ composite electrodes were evaluated using a three electrode system having Pt wire and standard Ag/AgCl as counter and reference electrodes, respectively. The Mn₂O₃ and Ag-Mn₂O₃ thin films were used as the working electrode. 0.1M Na₂SO₄ aqueous solution was used as an electrolyte. The separation of the photo generated electron-hole pairs was evaluated by measuring photocurrents and Figure 4.45a shows a comparative study of Linear Scanning voltammograms (LSVs) of both pristine Mn₂O₃ and Ag-Mn₂O₃ composite films at scan rate of 50mV/s. The dark current from -0.2 V to 1.0 V (*vs.* Ag/AgCl) of each sample was very low. Upon illumination, the Ag-Mn₂O₃ electrode showed a significant enhancement in photocurrent density (3.0 mA cm⁻²) as compare to pure Mn₂O₃ (1.8 mAcm⁻²) at a potential of 0.7 V *versus* Ag/AgCl. This pronounced photocurrent could be ascribed to the decoration of Ag on Mn₂O₃, resulting in a higher separation efficiency of the generated electron-hole pairs and enhanced visible light absorption due to the surface plasmon resonance (SPR) effect (Linic, Christopher, & Ingram, 2011; Warren & Thimsen, 2012).

The Mn_2O_3 and $Ag-Mn_2O_3$ photoelectrodes were further tested under on-off cycle illumination conditions to determine whether the measured photocurrents were associated with the absorption of light (Figure 4.45b).



Figure 4.45: (a) Linear sweep Voltammetry (LSV) of pristine Mn₂O₃ and Ag-Mn₂O₃ composite thin films in dark and light (b) Chronoamperometry (I–t) profiles (on-off cycles) of pristine Mn₂O₃ and Ag-Mn₂O₃ composite thin films at an applied potential of +0.7 V versus Ag/AgCl under 100 mW cm⁻² illumination (AM 1.5) in 0.1 M Na₂SO₄ aqueous solution.

Figure 4.45b shows the photocurrent generated under visible light irradiation of Mn_2O_3 and $Ag-Mn_2O_3$ electrodes. A steady and stable photo response of 1.8 and 3.0 mA cm⁻² within 5 on-off cycles could be observed over a 5 min period (Figure 4.45b) revealing the

higher efficiencies and good stabilities of Mn_2O_3 and $Ag-Mn_2O_3$ photoelectrodes. Moreover, the transient photocurrents agrees well with LSV results and strengthened the PEC performance in the visible light region, as well as indicating the existence of the SPR effect of Ag nanoparticles on Mn_2O_3 .

Electrochemical impedance spectroscopy (EIS) was performed to scrutinize the conductivity of electrode material, charge transport in the electrode-electrolyte interface and mechanistic analysis of interfacial processes. Figure 4.46a displays the Nyquist plots of both pristine Mn₂O₃ and Ag-Mn₂O₃ composite films in the frequency range of 0.1 Hz to 10 kHz in 0.1M Na₂SO₄ electrolyte under dark and visible light illumination. As shown in Figure 4.46a, the diameter of the pristine Mn₂O₃ was much larger than that of Ag-Mn₂O₃ composite in the dark as well as under visible light irradiation. The diameter of the semicircle in the Nyquist plots at high frequency represents the charge transfer resistance (R_{ct}), which is associated with the electronic properties of the electrode. Under illumination, the R_{ct} of Ag- Mn₂O₃ (~127 Ω) is considerably lower than R_{ct} of Mn₂O₃ (~195 Ω). The decrease of the charge transfer resistance of Ag- Mn₂O₃ is attributed to the larger number of charge carriers in the electrode sample. It is believed that these charge carriers are produced only because of the presence of Ag inside the Mn₂O₃ which facilitates fastest electron transport and shortest ion-diffusion path inside the Ag- Mn₂O₃ electrode. Normally, the smaller arc radius on the EIS Nyquist plot indicates an effective separation of photo-generated electron-hole pairs and a fast interfacial charge transfer process (Ge et al., 2016). This implies that Ag decoration significantly facilitated the electron mobility by reducing the recombination of electron-hole pairs and contributing to the enhanced PEC performance induced by Ag- Mn₂O₃.



Figure 4.46: (a) EIS in the Nyquist plots of pristine Mn_2O_3 and $Ag-Mn_2O_3$ composite thin films in 0.1 M Na_2SO_4 aqueous solution. (b) Bode angle phase plots of the Mn_2O_3 and $Ag-Mn_2O_3$ composite thin films.

The frequency dependence phase angle plot (Bode plot) of both pristine Mn_2O_3 and $Ag-Mn_2O_3$ composite electrodes were recorded for the detailed understanding of the chargetransfer resistance phenomenon in these materials. The Bode phase plots found for the Mn_2O_3 and $Ag-Mn_2O_3$ thin films are shown in Figure 4.46b where the characteristic frequency peaks were affected under dark and light conditions. In dark environment, the Mn_2O_3 and $Ag-Mn_2O_3$ films showed the frequency peak maxima (f_{max}) at 13.7 and 9.79 Hz respectively, suggesting larger charge-transfer resistance at the electrode/electrolyte interface due to a lack of availability for electroactive species. However the f_{max} is observed to shift toward the low frequency region (~1 Hz) in presence of light indicating the rapid electron-transfer (conductive) behavior of the Mn₂O₃ and Ag-Mn₂O₃ films. It is worth noticing that the phase angle values of Mn₂O₃ and Ag-Mn₂O₃ are increased in dark, revealing the conducting nature of the films. Approaching the phase angle to towards -90° signifies the ideal capacitor behavior of the electrode (Sheng, Sun, Li, Yuan, & Shi, 2012). In the present case, still the phase angle of the pristine Mn₂O₃ and Ag-Mn₂O₃ in dark and under illumination is much less than 90° suggests that the electrode does not behave like an ideal capacitor. These characteristic frequencies can be used to calculate the electron recombination lifetime (τ_n) of the corresponding material with following relationship (Lim, Pandikumar, et al., 2014):

$$\tau_n = \frac{1}{2\pi f_{max}}$$

Where f_{max} is the frequency peak maximum. The recombination life time (τ_n) values for the pristine Mn₂O₃ and Ag-Mn₂O₃ composite films are calculated to be are 11.6 and 16.2 ms, respectively in the absence of light. It is well known that when Ag nanoparticles are deposited on metal oxide surface, the plasmon resonance energy transfer (PRET) from Ag to metal oxide would occur (Jana et al., 2009). This PRET process would establish an oscillating electric field which would reduce the recombination of photo-generated electron–hole pairs. Therefore, the lifetime of charge carriers in Ag-Mn₂O₃ is prolonged effectively compared to pristine Mn₂O₃.

Further Mott–Schottky (MS) experiments for pristine Mn_2O_3 and Ag- Mn_2O_3 composites were conducted to deduce information about the type of semiconductor, flat band potential and the charge density values (Figure 4.47).



Figure 4.47: Mott–Schottky curves for (a) pristine Mn₂O₃ and (b) Ag-Mn₂O₃ composite thin films.

Figure 4.47 shows that both the Mn_2O_3 and $Ag-Mn_2O_3$ show a positive slope in the MS plots, as expected for the n-type semiconductor. Importantly, the considerably smaller slope of $Ag-Mn_2O_3$ composite in MS plot represents higher carrier concentration compare to pure Mn_2O_3 . The flat band potential of $Ag-Mn_2O_3$ composite, -0.91 V/SCE, is observed to be lower than -0.22 V/SCE of pristine Mn_2O_3 , indicating better transportation of the photogenerated carriers in the $Ag-Mn_2O_3$ composite case. Also the

carrier densities of both pristine and composite films were calculated to be 1.62×10^{13} and 3.09×10^{13} cm⁻³ respectively. In Ag-Mn₂O₃ composite thin film, Ag is the source of extra charge carriers. A higher charge carrier concentration in the composite film has an influence on changing the work function of the material which enhances the charge transfer at the electrode electrolyte interface and an improved PEC performance.

The markedly enhanced photocurrent of Ag- Mn_2O_3 film electrode is a direct consequence of the synergetic effects of the uniformly dispersed Ag on to Mn_2O_3 structure. On the basis of PEC results, we have proposed a mechanism of electrons transportation from Ag to Mn_2O_3 as shown in Figure 4.48.



Figure 4.48: Charge transfer mechanism between Ag particles and Mn₂O₃ in visible light.

Under visible light irradiation, Ag nanoparticles could be photo-excited and generate hot electrons on its surface due to the surface plasmon resonance. Electrons are excited from valence band to conduction band by illumination with visible light and then migrate to Ag metal. The plasmon-induced hot electrons are introduced into the conduction band of Mn_2O_3 , and then to the FTO substrate through the Mn_2O_3 backbone. Finally, the electrons were transferred to the Pt electrode to reduce water and generate hydrogen. As a result, Ag nanoparticles attached on Mn_2O_3 could increase the photocurrent intensity under illumination of the entire solar spectrum.

4.5 Synthesis of Complex [Sn(dmae)(OAc)]₂ (5)

The new single source dimeric complex (**5**) was readily prepared by ligand exchange reaction of equimolar quantities of bis(dimethylaminoethanolato)tin(II), Sn(dmae)₂ (Wakeshima & Kijima, 1972; Hollingsworth et al., 2006; Nawar & Hosny, 2000; M. Veith, Haas, & Huch, 2004; B.-H. Ye, Li, Williams, & Chen, 2002) and Y(OAc)₃ xH₂O in (10 mL) of dry toluene. The complex is soluble in toluene and has a melting point of 147 °C. The overall reaction for the formation of (**5**) is shown below in equation 6

Chemical Equation 9

$$SnCl_{2} + 2(C_{2}H_{5})_{3}N \xrightarrow{CH_{3}OH} Sn(OCH_{3})_{2} + 2(C_{2}H_{5})_{3}NHCl$$

$$Sn(OCH_{3})_{2} + (CH_{3})_{2}NCH_{2}CH_{2}OH \longrightarrow Sn(OCH_{2}CH_{2}N(CH_{3})_{2}$$

$$Sn(OCH_{2}CH_{2}N(CH_{3})_{2} + Y(CH_{3}COOH) \xrightarrow{Toluene} Sn(OCH_{2}CH_{2}NCH_{3})(OOCCH_{3})$$

The single crystal analysis indicated that precursor 5 is stabilized by the establishment of an intramolecular coordinate $Sn \leftarrow N$ bond and the orthorhombic crystal system with space group Pna2(1).

4.5.1 Crystal Structure of Complex [Sn(dmae)(OAc)]₂ (5)

The X-ray crystal and structure refinement data for [Sn (OAc)(dmae)]₂ (**5**), selected bond lengths, bond angles and crystal parameters are listed in Table 4.9 and 4.10 respectively.
Empirical Formula	$C_{12} \ H_{26} \ N_2 \ O_6 \ Sn_2$	Limiting indices	-19<=h<=19, -7<=k<=7, - 24<-1<-24	
Formula weight	531.73 Reflection collected / ur		15567 / 3889 [R(int) = 0.0266]	
Temperature	100(2) K Completeness t theta = 26.50		100.0 %	
Crystal system, space group	Orthorhombic, Pna2(1)	Max. and min. transmission	0.9003 and 0.3474	
Unit cell dimensions	$\alpha = 15.6753(4) \text{ Å} \text{alpha} = 90^{\circ}.$ $\beta = 6.1527(2) \text{ Å} \text{beta} = 90^{\circ}$ $\gamma = 19.5022(6) \text{ Å} \text{gamma} = 90^{\circ}$	Refinement method	Full-matrix least-squares on F ²	
Volume	1880.90(10) Å ³	Data / restraints / parameters	3889 / 1 / 205	
Z, Calculated density	4, 1.878 Mg/m ³	Goodness-of-fit on F ²	1.040	
Absorption coefficient	2.681 mm ⁻¹	Final R indices [I>2sigma(I)]	R1 = 0.0137, wR2 = 0.0327	
F(000)	1040	R indices (all data)	R1 = 0.0140, wR2 = 0.0329	
Crystal size	0.50 x 0.04 x 0.04 mm	Absolute structure parameter	10(10)	
Theta range for data collection	2.09 to 26.50 deg.	Gest diff. peak and hole	0.605 and -0.255 e.Å ⁻³	

Table 4.9: X-ra	y crystal and s	tructure refinement dat	a for [Sn	(dmae)	$(OAc)]_2(5)$)
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Table 4.10: Bond lengths [Å] and angles [o] for complex $[Sn(oAc)(dmae)]_2$ (5)

Sn1-O1	2.1190(17)	O6-C11	1.225(3)	
Sn1-O2	2.1530(17)	O1-Sn1-O2	89.13(7)	
Sn1-O4	2.2339(16)	O1-Sn1-O4	68.52(6)	
Sn2-O1	2.2282(17)	O2-Sn1-O4	85.28(6)	
Sn2-O4	2.1179(17)	O1-Sn1-N1	72.41(7)	
Sn2-O5	2.1482(18)	O2-Sn1-N1	80.21(7)	
Sn1-N1	2.497(2)	O4-Sn1-N1	138.35(7)	
Sn2-N2	2.513(2)	O4-Sn2-O5	89.82(7)	
01-C1	1.419(3)	O4-Sn2-O1	68.64(6)	
O2-C5	1.297(3)	O5-Sn2-O1	85.28(7)	
O3-C5	1.227(3)	O4-Sn2-N2	72.47(7)	
O4-C7	1.415(3)	O5-Sn2-N2	79.71(6)	
O5-C11	1.302(3)	O1-Sn2-N2	138.17(6)	

The molecular structure (Figure 4.49) indicates that the centre of inversion lies at the centre of a Sn2O2 four-membered ring. Each tin(II) atom adopts a distorted trigonal bipyramidal geometry with the lone pair of electrons situated at the equatorial position. The stronger interactions between the lone pair of electrons and the bonding pairs of electrons push the other two bonding pairs at the equatorial positions towards the axial positions, thus giving rise to a distorted trigonal pyramidal geometry at the two tin sites as can be evidenced from the axial N2-Sn2-O1 and N1-Sn1-O4 bond angles of 138.17(6)^o and 138.35(7)^o, respectively.



Figure 4.49: The Ortep plot of complex [Sn (OAc)(dmae)]₂ (**5**) showing 30% probability displacement ellipsoids and the atom numbering. Hydrogen atoms are drawn as spheres of arbitrary radii.

The two covalent Sn-O bond distances are at Sn1-O1 and Sn2-O4 are 2.119(2) and 2.118(2) Å respectively while the other two bridging oxygen coordinate bonds, Sn1-O4 and Sn2-O1 bond distances are longer at, 2.339(2) and 2.282(2) Å respectively, to form

a four-membered Sn₂O₂ ring. The terminal Sn-O bonds are somewhat longer than the bridging Sn-O bonds. The Sn1-N1 and Sn2-N2 bond distances are 2.497(2) and 2.513(2) Å, respectively. The four membered Sn₂O₂ ring is planar (RMS deviation from planarity = 0.0294Å) whereas the chelate rings formed by Sn1 O1 C1 C2 N1 and Sn2 O4 C7 C8 N2 are puckered with RMS deviation from planarity of 0.1814 and 0.1856Å, respectively. These two chelate rings make an angle of 22.40(8)° and 19.99(9)°, respectively with the four-membered ring. The long separation of 3.5922(2) Å between the two tin atoms in the dimeric unit shows that there is no significant bond interaction between the two tin atoms. The marked difference in the C-O bond distances of the 153arboxylate group (O6-C11= 1.225(3), O5-C11= 1.302(3) Å and O2-C5= 1.297(3), O3-C5 = 1.227(3) Å) indicates that there is no intramolecular interaction between the carbonyl oxygen of the carboxylate and the tin atom.

4.5.2 Thermogravimetric Analysis of Complex [Sn(dmae)(OAc)]₂ (5)

The decomposition pattern thermal of complex (5) was examined by thermogravimetric/derivative thermogravimetric (TG/DTG) analysis, performed under a flow of N₂ (25 mL/min) at a heating rate of 10 °C/min. The (TG/DTG) (Figure 4.50) shows two stages of weight loss. The first minor weight loss of 5.33 % regime exists at 177 °C. Immediately after the first weight loss, the second major pyrolysis step begins at 178°C and is completed at 258.19 °C to yield 51.46 % of the solid residue. This decomposition step involves a total weight loss of 48.54 %. The weight of the residue agrees very well with the theoretically expected yield (51.15 %) of tin(IV) oxide from the precursor (5). Further heating of the residue to 900 °C did not bring any change in weight indicating complete decomposition of precursor 1 to furnish a residual mass of SnO_2 as expected from the complete decomposition of [Sn (OAc)(dmae)]₂. The FTIR study of the residue obtained from TG studies showed strong absorption at 588.6 cm⁻¹ that agrees well with the reported value for SnO_2 (Hollingsworth, et al., 2006; M. Veith, et al., 2004; B.-H. Ye, et al., 2002). Further no C-H vibrations were recorded indicating absence of any carbonaceous impurity in the residue. The residual mass of 51.47 % observe at 258 °C indicates the formation of expected SnO_2 oxide material from complex (**5**) as shown in following equation.

Chemical equation 10:



Figure 4.50: The TG and DTG plots of precursor (**5**) recorded under an inert atmosphere of nitrogen gas with constant flow of 25cm³/min and heating rate of 20 °C/min.

4.5.3 XRD Analysis of SnO₂

The XRD pattern displayed in Figure 4.51 confirms the formation of crystalline SnO_2 mesoporous micro balls. The weak diffraction peaks at 20 values of 26.7°, 34.0°, 38.2°, 52.1°, 54.6° and 65.0° are associated with (110), (101), (200), (211), (220) and (301) planes and are in complete match with the literature values reported in (JCPDPS card no.

41-1445) for tetragonal structure (Patil GE, Kajale DD, Gaikwad VB, & GH, 2012; Z. Wang, Luan, Boey, & Lou, 2011). Further sintering of the sample at 500 °C for two hours did not bring any change in the XRD pattern indicating ability of the micro balls to retain their morphology and structure at high temperature. The FTIR of the micro balls showed only one stretching absorption band at 588.67 cm⁻¹ due to Sn-O vibration confirming carbonaceous impurity-free SnO₂.



Figure 4.51: The XRPD pattern of the SnO₂ micro balls thin film on plain glass substrate deposited from a toluene solution of precursor (**5**) and sintered at 450 °C for 6 hours in air atmosphere

4.5.4 XPS Analysis of SnO₂

The XPS is appreciated technique to study the surface and sub surface chemical states of the prepared samples as the binding energy values of core levels are, to a certain extent dependent on the molecular environment. The 3d core of Sn splits in to 3d 5/2 (486.6 eV) and 3d 3/2 (495.0 eV) which are consistent with the reported values of 486.4(3d5/2) and 494.8 eV (3d3/2) for SnO₂ as shown in Figure 4.52(a). Also the binding energies found for O 1s core level from Si oxide (532.8eV) is clearly distinguishable from O1s of Sn oxide (530.7 eV) and are in good agreement with the previously reported values. The XPS data clearly shows the micro balls consist of only SnO₂.



Figure 4.52: The XPS spectra of SnO₂ micro ball thin films deposited on glass substrate (a) Sn 3d (b) O 1s.

4.5.5 Surface Morphology of SnO₂

The FESEM results indicate that the aerosol generated from toluene solution of Sn (IV) precursor and deposited onto plain and FTO coated glass substrates under the influence of electric fields and then annealed at 450 °C for 6 hours, led to the growth of amorphous mesoporous SnO₂ micro balls (Figures 4.53b) of uniform lateral dimensions in the range of 195-632 nm. The exterior porosity is visible in the form of small holes with pore sizes from 56-66 nm in Figure 4.53c. The interior surface of the particles seems to be rough, having pores of various sizes ranging from 8-160 nm as revealed by FESEM image of the milled balls by Focussed Ion Beam (FIB) at an ion acceleration of 30 keV with a milling and cleaning cross section current of 2 nA and 10 pA, respectively Figure 4.53d. The deposited films, as observed from the outer surface are highly homogenous and possess smooth features. The FESEM image of the films deposited by AACVD, without application of an electric field, on FTO substrate show formation of non-porous smooth surface micro balls as shown in (Appendix 7). When aerosol generated particles experience an electric field, these charged particles move in certain orientations. When deposited on the substrate certain orientations make the material porous as observed in Figure 4.53. While for AACVD without an electric field did not experience these orientations show smooth spherical morphology. Further the EDAX analysis (Appendix 8) confirmed that only tin and oxygen are present in the nanoball thin films.



Figure 4.53: Illustrate SEM images of SnO₂ micro balls thin films deposited on FTO glass substrates and (a) agglomerization of micro balls , (b) lateral dimensions, (c) pores of the exterior and (d) the interior surfaces of the micro balls.

4.5.6 Optical Band gap of SnO₂

The optical absorption spectrum of SnO₂ micro-ball thin films deposited at 400°C using toluene and having a thickness of 310 nm was recorded on a Lambda 35 Perkin-Elmer UV-Vis spectrophotometer in the wavelength range of 310-710 nm using FTO. The UV-Vis spectrum of SnO₂ micro ball thin films shows an absorption edge at 360 nm and the band gap was calculated by plotting Tauc plot of energy versus $(\alpha h \upsilon)^2$ to give a value of 3.8eV (Figure 4.54).



Figure 4.54: UV-Vis absorption spectrum of wavelength versus absorption and inset Tauc plot of energy versus $(\alpha h \upsilon)^2$ of SnO₂ microball thin films deposited from precursor using EFDAACVD showing a sharp absorption edge at 360 nm.

4.5.7 BET Analysis of SnO₂

The surface area of 136m²/g and 191.6m²/g of the tin oxide micro balls powder scratched from FTO substrate deposited by EFDAACVD was estimated by Brunauer-Emmett-Teller (BET) and Langmuir methods, respectively. The adsorption-desorption isotherm was shown in Figure 4.55a indicating hysteric loop characteristic of mesoporous materials. The pore volume and pore size determined by Barret-Joyner-Halenda (BJH) adsorption-desorption method is about 0.05 ml/g and 45A° respectively Figure 4.55b. The high surface area is due to high porosity in the interior and exterior surfaces and is about two and a half times more than the previously reported values for SnO₂.



Figure 4.55: (a) Nitrogen adsorption-desorption isotherm and (b) BJH pore size distribution for mesoporous SnO₂ micro balls.

4.5.8 Electrochemical Studies of SnO₂

Electrochemical impedance measurements of the SnO_2 microball coated FTO electrodes were conducted in a three electrode electrochemical cell in order to determine the resistance of the electrode/electrolyte interface. The resistance of the electrode/electrolyte interface can be determined from the high frequency x-axis intercept from the Nyquist plot, shown in Figure 4.56. The resistance was found to be 80 Ω which indicates that the SnO₂ microballs have suitable conductivity for application in batteries.



Figure 4.56: Impedance measurement (a) Nyquist Plot of the SnO₂ microball electrode conducted in a 3-electrode electrochemical cell, using an Ag/AgCl reference electrode and a Pt counter electrode in a 1 M LiPF6-EC:DMC (1:2 by volume) electrolyte at open circuit potential. (b) Expanded plot of showing the high frequency region of the Nyquist plot.

Tin (Sn)-based and tin oxide (SnO₂)-based anodes in **Li-ion batteries** typically show enhanced performance and improved cycle life only when incorporated with nanoscale or composite particles. The reaction mechanism of SnO_2 with lithium has been proposed to take place as indicated in the following two steps:

$$SnO_2 + 4Li^+ + 4e^- \rightarrow Sn + 2Li_2O \tag{4.1}$$

$$Sn + xLi^{+} + 4e^{-} \rightarrow Li_{x}Sn (0 \le x \le 4.4)$$

$$(4.2)$$

In the first reaction, SnO_2 is reduced to metallic Sn, which is partially irreversible. The second reaction is the Sn alloying/de-alloying reaction with lithium, which is usually reversible in most cases.

However, SnO_2 nanowires covered with Sn nanoclusters have exhibited an exceptional capacity of > 800 mAhg⁻¹ over hundred cycles. The reaction of SnO_2 with Li ions,

electrolyte decomposition, and solid electrolyte interface formation are believed to be some of the reasons for large irreversible capacity during the first cycle. This involves an additional step of formation of SnO which subsequently reduces to Sn.

$$SnO_2 + 2Li^+ \to SnO + Li_2O \tag{4.3}$$

$$SnO + 2Li^{+} + 2e^{-} \rightarrow Sn + Li_{2}O \tag{4.4}$$

$$Sn + xLi^{+} + xe^{-} \rightarrow Li_{x}Sn (0 \le x \le 4.4)$$

$$(4.5)$$

In addition to the pulverization of SnO₂ particles due to large volume expansion during cycling, agglomeration of the primary particle can drastically reduce the surface-to-volume ratio causing diminishing of the electrochemical activity. Several strategies have been utilized to mitigate the pulverization and particle agglomeration. In the past decade, great efforts have been devoted to synthesizing SnO₂ nanostructures with varying morphologies. Nanocrystalline SnO₂ with various crystallite sizes (Z. Wang, et al., 2011), SnO₂ nanomaterials with a hollow structures (Lou, Wang, Yuan, Lee, & Archer, 2006) uniform SnO₂ nanoboxes have been synthesized and tested for the anode material in Liin batteries.

Recent studies have shown that even 1-d SnO₂ nanostructures show low capacities ranging from 300 to ~ 620 mAhg-1 after 50 cycles (D.-W. Kim et al., 2007). SnO₂ nanowires and hetero-structured SnO₂/In₂O₃ nanowires retain a capacity of ~700 mAhg-1 up to 15 cycles, but quickly fade to ~ 300 mAhg-1 after 50 cycles. Similarly, SnO₂ nanorods have been shown to retain a capacity of only ~400 mAhg-1 after 60 cycles (Yong Wang & Lee, 2004).



Figure 4.57: (a) Charge-discharge curves of SnO₂ micro ball electrode measured in coin cell configuration in the voltage range of 2.2-0.005 V with a current of 100 mA/g. (b) Charge-discharge capacities vs. cycle number of SnO₂ electrode SnO₂ micro ball electrode measured in coin cell configuration in the voltage range of 2.2-0.005 V with a current of 100 mA/g. (c) Charge-discharge capacities vs. cycle number of SnO₂ micro ball electrode in the voltage range of 2.2 V-0.005V at varying current densities of 100, 200, 500 mA/g, 1.0A/g, and 2.0 A/g.

Therefore, the significantly enhanced performance of stand-alone SnO_2 micro-ball nanostructures without incorporating any supporting materials/strategies to increase the stability with high capacity retention is a useful information for the community who work in the energy storage area.

The charge-discharge curves of SnO_2 micro ball anode electrodes at the voltage range of 2.2-0.005 V using a current density of 100 mA/g are shown in Figure 4.57a. It has an

initial large discharge capacity of 2066 mAh g^{-1} during the first cycle. The high initial discharge capacity is believed to be due to the reduction of tin oxide to tin and the intercalation of Li into SnO₂. The initial capacity loss is mainly due to the solid-electrolyte-interface formation and the reduction of SnO₂ to Sn. During subsequent charge-discharge processes, SnO₂ micro ball anode shows the discharge capacities of 997, 788, 704, 649, 593, 542 mAhg⁻¹ after 2nd, 10th, 20th, 30th, 40th and 50th cycles, respectively.

Figure 4.57b summarizes the charge-discharge capacities vs. cycle number of SnO_2 micro ball electrode in the voltage range of 2.2-0.005 V with a current of 100 mAg⁻¹. The initial discharge capacity of 2066 mAh g⁻¹ during the first cycle is seen to fade away, but remains over 540 mAh g⁻¹ after 50 cycles.

Figure 4.57c shows the rate capability of SnO_2 micro ball electrodes at varying current densities of 100, 200, 500, 1000, and 2000 mAh g⁻¹. The discharge capacity decreased with increasing current density as expected. The initial discharge capacity of the SnO_2 micro ball electrodes at current density of 100 mAg⁻¹ remains 1691 mAhg⁻¹ and at 200, 500, 1000 and 2000 mA g⁻¹ current densities it shows an initial discharge capacities of 569, 399, 258, and 100 mAhg⁻¹, respectively. When the current density is reduced to 500 and 200 mAg⁻¹ after the initial rate performance testing, the SnO_2 micro balls can still provide discharge capacity close to formerly measured value of 382, and 430 mAhg⁻¹, indicating its good reversibility and high rate capability. The reversibility, high rate capacity and relative stability shown by SnO_2 micro-ball based anodic materials appeared to be strongly related to the specific morphology and texture of the materials we prepared and used in our study. Further work is currently underway to understand this phenomena.

4.6 Deposition of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO Thin Film by EFDAACVD Method

Metal carboxylates because of their distinct characteristics of high volatility, solubility, stability and suitable decomposition temperature during transport in gas phase make them favorable CVD precursor for the deposition of thin layers of metal oxides for photoelectrochemical applications. The different coordination modes of the carboxylate ligands force the metal into strict molecular regime that improves their potential to perform as CVD precursor. Metal oxide center enclosed by organic environment making the precursor soluble in suitable organic solvents like toluene, THF, methanol, ethanol and acetonitrile etc. We therefore selected carboxylates of Manganese, Iron, Copper, Nickle, zinc, cadmium and lead for the fabrication of thin films of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO and by using unique EFDAACVD method. The motive behind use EFDAACVD was to obtain films of well-defined uniform morphology, stoichiometry and structure that is reproducible in a single step with the instantaneous reduction in CVD parameters. The thin films produced by EFDAACVD were analyzed by XRD, XPS, Raman scattering, Uv-visible spectroscopy, FESEM and EDX and investigated for their photo electrochemical behavior.

4.6.1 XRD Analysis of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO Thin Films

Figure 4.58 shows the XRD patterns of Mn_2O_3 , α -Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films fabricated on the FTO by the EFDAACVD technique. The peaks indexed by the symbol (\blacklozenge) correspond to the SnO₂ in the FTO substrate (A. Chen et al., 2009; Klahr, Martinson, & Hamann, 2010; Mansoor, Mazhar, McKee, & Arifin, 2014; Sialvi et al., 2013; A. A. Tahir, Mazhar, Hamid, Zeller, & Hunter, 2009; A. A. Tahir, Wijayantha, Saremi-Yarahmadi, Mazhar, & McKee, 2009). The XRD pattern of cubic Mn₂O₃ with (211), (400) and (622) diffraction planes observed at 20 values of 22.5°, 37.8° and 65.6°

respectively matched well with the JCPDS card No. 00-002-0896 (Dakhel, 2006). Figure 4.58 shows three strong peaks, namely, (012), (104) and (110), which are the reflections of α-Fe₂O₃ (hematite) as indicated in JCPDS card No. 86-0550 (A. A. Tahir, Wijayantha, et al., 2009). The X-ray diffraction data have been recorded for NiO thin films as shown in Figure 4.58 displaying distinct peaks at 2 θ values of 37.1°, 43.1° and 62.6°. These peaks have been assigned to cubic NiO crystallites with various diffracting planes (111), (200) and (220) respectively revealing the formation of the NiO cubic phase (JCPDS card No. 47-1049) (Johan, Suan, Hawari, & Ching, 2011). The two broad peaks at 20 values of 35.5° and 38.7° match the reflections from the (111) and (200) planes respectively. which is attributed to the structure of cubic CuO (JCPDS card No. 01-085-1326) (Necmi, Tülay, Seyda, & Yasemin, 2005; M. Shahid, Mazhar, Tahir, Rauf, & Raftery, 2014). The XRD pattern of well-crystallized stoichiometric ZnO were observed at the 20 values of 31.7°, 34.3°, 36.2°, 47.5°, 56.5° and 62.7° with hkl lattice planes (100), (002), (101), (102), (110) and (103) and are in good agreement with those given in the standard data (JCPDS: 98-002-6170) for hexagonal ZnO (Cheng, Zhao, Huo, Gao, & Zhao, 2004). For comparing observed peaks of CdO thin film the (JCPDS: 96-101-1004) card was referred.

The main peaks for (111), (200), (220), (311) and (222) reflections originated at the 2 θ values of 33.1°, 38.5°, 55.3°, 66.5° and 69.4° which indicated the cubic phase of CdO (Maity & Chattopadhyay, 2006; R. S. Mane, Pathan, Lokhande, & Han, 2006). PbO thin film examined by XRD was identified by (JCPDS card No. 96-900-5762) for diffraction planes (111), (020), (200) and (111) at the 2 θ values of 29.2°, 30.1°, 32.4° and 53.7° shows the tetragonal structure of PbO (Madsen & Weaver, 1998).



Figure 4.58: XRD pattern of EFDAACVD-deposited thin films of Mn₂O₃, α-Fe₂O₃, NiO, CuO, ZnO, CdO and PbO on an FTO glass substrate at 400 °C.

4.6.2 Raman Analysis of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO Thin Films

Raman scattering is a sensitive means to reveal the crystallinity and phase purity of a material. The Raman spectra of synthesized nanoballs of Mn_2O_3 , α -Fe₂O₃, NiO and CuO recorded in the range of 200 to 1000 cm⁻¹ as shown in Figure. 4.59 are indicated by a strong peak at 620 cm⁻¹ with a left shoulder at 580 cm⁻¹ which is associated with a symmetric Mn-O stretching vibration as reported earlier (Dokko, Mohamedi, Anzue, Itoh, & Uchida, 2002). Iron oxide exists in several forms such as magnetite (Fe_3O_4), hematite $(\alpha$ -Fe₂O₃), maghematite (γ -Fe₂O₃) and wustite (FeO). Raman spectroscopy can identify each of these forms better than any other tool. The Raman spectrum of iron oxide Figure 4.59 shows the entire three strong bands at 222, 288, 401 cm⁻¹ and one peak of mediumstrong intensity at 659 cm⁻¹ as reported in the literature that are characteristic for α -Fe₂O₃. However, the Raman band for the magnetite (Fe₃O₄), maghematite (γ -Fe₂O₃) and wustite (FeO) also fall at 663 cm⁻¹ (Bersani, Lottici, & Montenero, 1999). The possibility of the existence of FeO is excluded because of the absence of its characteristic peak at 655 cm⁻ ¹ while the existence of maghematite is eliminated because its phase is formed only at temperatures above 400 °C. It can therefore be safely concluded that the thin film consists of mainly hematite (α -Fe₂O₃) with a minor impurity of magnetite. The Raman spectrum of NiO. Figure 4.59, shows a characteristic strong peak at 505 cm⁻¹ with a shoulder at 407 cm⁻¹ and a weak signal at 706 cm⁻¹ (S.-H. Lee et al., 2001). It is reported in the literature that the Raman spectrum, Figure 4.58, of CuO has three Raman active modes at 297, 337 and 558 cm⁻¹ (A. Chen, et al., 2009). All these modes of vibration have been identified in the spectrum and assigned to CuO with no extra peak due to Cu₂O found. Therefore, it can be inferred that CuO nanoball thin film is free from Cu₂O impurity.



Figure 4.59: Raman spectra of EFDAACVD-deposited thin films of Mn₂O₃, α-Fe₂O₃, NiO and CuO, ZnO, CdO and PbO on FTO glass substrate at 400 °C in THF.

A broad band that corresponds to symmetry mode of ZnO is observed at ~418 cm⁻¹. The onset and offset of this peak are at 320 and 518 cm⁻¹ respectively. Immediately after the offset a shoulder appears at 533 cm⁻¹ which ends at 625 cm⁻¹ (Saw, Ibrahim, Lim, & Chai, 2007; X. Q. Wei et al., 2007). The Raman spectra of CdO contain one broad intense feature spanning from 200 to 500 cm⁻¹ and a weaker band located at ~960 cm⁻¹. The weak broad band at 561 and 960 cm⁻¹ are in good agreement with the experimental values (Cuscó et al., 2010; S. Kumar, Ojha, & Singh, 2014). The Raman shift at 259cm⁻¹ is attributed to the litharge modification of PbO. (Madsen & Weaver, 1998). It is concluded form the Raman spectrum Mn₂O₃, α -Fe₂O₃, NiO and CuO ZnO, CdO and PbO thin films deposited by EFDAACVD have hexagonal, cubic and litharge tetragonal structures respectively and agree very well with the XRD findings.

4.6.3 Surface Morphology of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO

The field emission scanning electron micrographs of metal oxide thin films at magnification 100,000 are presented in Figure 4.59. The surface morphology of the thin films deposited on FTO by EFDAACVD affects the surface morphology of the films as compared with AACVD (Warwick, Smith, Furlan, Crane, & Binions, 2010). The application of electric field is one of the key process parameters to control the morphology of the deposited film by chemical vapour deposition. The effect of electric field on the morphology of the films was studied by depositing films using air as a carrier gas at 400 °C substrate temperature. In the presence of an electric field, the morphology of the thin films showed particles caked as nanoballs onto the substrate surface. The smooth surface spherical shaped nanoballs of α -Fe₂O₃, NiO and CuO appeared on the FTO surface while the surface morphology of the Mn₂O₃ films turned into independent nanoballs sticking on the rough surface of the bulk. The precursor was assumed to be completely deposited on

the substrate in the presence of an electric field of 9.5 kV. The distance of needle from the substrate, deposition time, and strength of the electric field play an important part in the morphology control of metal oxides thin films. The Mn₂O₃ aggregated rough-surfaced nanoballs and the spherical shaped smooth-surfaced α -Fe₂O₃ nanoball thin films have average sizes ranging from 396 to 898 and 325 to 529 nm respectively. The NiO films by AACVD adopted a columnar structure with flower-like surface morphology (Mat-Teridi et al., 2014), while with EFDAACVD method nanoballs with average sizes of 273 to 471 nm were formed. The morphology of the thin films of CuO fabricated by simple AACVD gave densely packed globular aggregates (Barreca et al., 2009) with particle sizes of 600 to 800 nm while the film deposited in the presence of the electric field yielded nanoballs of CuO with sizes ranging from 195 to 401 nm. The architecture of thin films fabricated by EFDAACVD process is influenced by the deposition conditions such as presence of electric field, physical properties of solvent (boiling point, heat of combustion viscosity, specific heat capacity and coordination ability), as well as the growth temperature and nature of the substrate. When films were deposited in the presence of electric field using THF solution, different morphologies of ZnO, CdO and PbO were detected on FTO substrate by using argon as a carrier gas at 400 °C are presented in Figure 4.59. The center of the thin film of ZnO consists of urchin like structure surrounded by okra like particles. (Deng et al., 2004). While the CdO thin film consist of agglomerates of particle (R. S. Mane, et al., 2006) and PbO thin films have compact slate like morphology. All these observations indicate that the morphology and size of the thin films can be controlled by the application of an electric field of appropriate strength independent of the nature of the metal precursors.

The EDX analysis of large areas of Mn_2O_3 , α -Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films confirms the presence of only Mn, Fe, Ni, Cu, Zn, Cd, Pb and O elements respectively and is shown in (Appendix 9). The tin and fluorine signals appear from the

FTO substrate. The EDX analysis recorded at randomly different places confirms the uniform distribution of all the components of the metal oxide in the respective thin films.



Figure 4.60: FESEM images of Mn₂O₃, α-Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films deposited at 400 °C from THF solution of metal acetates on FTO glass substrates deposited by EFDAACVD.

4.6.4 Optical Studies of Mn₂O₃, Fe₂O₃, CuO, NiO, ZnO, CdO and PbO Thin Films

The optical absorption spectra of EFDAACVD-deposited thin films were recorded in the wavelength range of 300 - 900 nm using a similar FTO coated glass substrate as a reference to exclude substrate contribution in the spectrum. The UV–visible spectra of the Mn₂O₃, α -Fe₂O₃, NiO, CuO, ZnO, CdO and PbO nanoball thin films were used to calculate the band gaps by means of Tauc's plot of $(\alpha hv)^2$ versus energy, Tauc's plot (Dolgonos, Mason, & Poeppelmeier, 2016) method by using the following equation given below.

$\alpha = \mathbf{A}(hv - \mathbf{E}_{g})^{1/2}/hv$

where α , E_g, and A are the absorption coefficient, band-gap energy and a constant, respectively. Figure 4.61, to give the values of 1.2, 2.2, 1.9 and 0.9 eV respectively for the direct band gaps. The band gap values for Mn₂O₃ and α -Fe₂O₃ are in good agreement with the corresponding values of 1.2 and 2.2 eV (Mansoor, et al., 2014a; A. A. Tahir, Wijayantha, et al., 2009), while the band gap values for NiO and CuO films showed lower band gap energies of 1.9 and 0.9 eV respectively as compared to the reported values of 3.2 and 1.7 eV (Mat-Teridi, et al., 2014; Johan, et al., 2011). This lower band gap energy may be due to absorption involving defect states. 3.1, 2.2 and 1.8 eV were obtained by extrapolation of the linear region in the plots of (αhv)² versus *E/eV* for the ZnO, CdO and PbO thin films respectively as depicted in Figure 4.61. The band gap energy values for ZnO, CdO and PbO respectively (Aly, Kaid, & El-Sayed, 2013; Carballeda-Galicia et al., 2000; Ilician*, Caglar, & Caglar, 2008).



Figure 4.61: UV-vis spectrum shows Tauc's plot of energy versus (αhv)² for Mn₂O₃, α-Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films deposited at 400 °C from THF solution of metal acetates on FTO glass substrates by EFDAACVD.

This scatter in reported values may be attributed to two factors. First, the optical properties depend critically on the physical properties of the films, which are subsequently affected by the deposition and post-deposition conditions. Secondly, different models have been used to extract the optical properties from measured quantities. For example, α , α^2 , $(\alpha E)^2$,

 $(\alpha E)^{2/3}$, and $(\alpha E)^{1/2}$ were all plotted against the photon energy to determine the band gap. This not only affects the value of the band gap but also affects the interpretation of the nature of the gap i.e. direct or indirect.

4.6.5 Photoelectrochemical Studies of Metal Oxide Thin Films

The photoelectrochemical behavior of the EFDAACVD-produced metal oxide (Mn₂O₃, α -Fe₂O₃, NiO and CuO) thin films were investigated for water oxidation using linear sweep voltammetry (LSV) technique under simulated solar AM 1.5G irradiation in the presence of 0.1 M Na₂SO₄ at a scan rate of 50 mV/s. Under applied bias, the metal oxide thin films undergo photo-induced charge separation thereby promoting the valence band electrons to the conduction band resulting in the formation of holes at the valence band. The holes produced at the valence band can be readily scavenged through water oxidation that produces O_2 and H⁺ ions. The electron present in the conduction band can be collected as a photocurrent generated by this EFDAACVD-produced metal oxide thin films. These overall photo-induced charge separation obtained for the metal oxide thin films in the photoelectrochemical cells are schematically shown in Figure 2.17. The photocurrent density-applied voltage responses observed for the various metal oxide thin films indicate that with increasing applied potential, the photocurrent density increases as depicted in Figure 4.62. It can be seen that among the various thin films, the Mn₂O₃ thin film showed a higher photocurrent density than the α -Fe₂O₃, NiO and CuO thin films due to its hierarchical and roughened morphology. The lowest photocurrent density was generated by the α -Fe₂O₃ thin film (120 μ A/cm²), whereas the maximum photocurrent density of 1.132 mA/cm² at 0.70 V potential versus Ag/AgCl (~1.23 V versus RHE) was found for the manganese dioxide (Mn₂O₃) thin film. In the case of CuO and NiO thin films, photocurrent densities of 129 and 226 μ A/cm² respectively, were obtained.



Figure 4.62: LSV plot obtained for the EFDAACVD- produced metal oxide (a) Mn₂O₃, α-Fe₂O₃, NiO, CuO and (b) ZnO, CdO, PbO thin films were dipped in to a solution containing 0.1 M Na₂SO₄ at a scan rate of 50 mV/s under dark and simulated solar AM 1.5G irradiation

The photocurrent LSV responses (Figure 4.62) observed for all the three metal oxide thin films shows that with increase in the applied potential, the photocurrent density increases. It can be seen that among the three oxides, CdO which has band-gap value of 2.2 eV and granular morphology, shows higher photocurrent density as compared with the ZnO and PbO thin films. Although band gap of PbO is lower than CdO yet the photocurrent produced by it is lesser than CdO. This observation suggests that in addition to band gap energy of the photocatalyst, other parameters such as microstructure, morphology, particle size and shape etc of the thin film play important role in photoelectrochemical events and hence these parameters need to be controlled during the deposition of thin films. These two factors significantly accelerated photocurrent generation in terms of light absorption, charge recombination and charge transport.

The variations in the photocurrent responses of the thin films were further understood by recording the electrochemical impedance spectroscopy (EIS) measurements in the frequency range of 0.01 Hz to 10 kHz. The Nyquist plots obtained from the EIS measurements in the presence of 0.1 M Na₂SO₄ are displayed in Figure 4.63.

It can be seen that the Mn_2O_3 , NiO and CuO thin films show a well-defined semicircle due to the charge transfer resistance of the thin films, whereas the α -Fe₂O₃ thin film exhibits a straight oblique line, which shows better conductivity and an increase in charge carriers due to low interfacial charge transfer resistance. Moreover, the Mn_2O_3 thin film shows a semicircle with a small diameter, which reveals a lower charge transfer resistance between the electrode and the electrolyte. It is known from the literature (Yusoff et al., 2015) that the corresponding value of the intercept on the X-axis at high frequency represents the ohmic resistance of the electrolyte and the internal resistance of the electrode (R_s). The lower values of R_s and R_{ct} for the Mn_2O_3 thin films result in an efficient charge transfer across the electrode-electrolyte interface, thereby minimizing charge recombination and enhancing the photocurrent response. The Nyquist plots obtained from the EIS measurements for the ZnO, CdO and PbO thin films are displayed in Figure 4.63. The ZnO thin film showed a semi-circle like oblique straight line due to the high charge transfer resistance (R_{ct}) value of 5225 Ω . In the case of CdO thin film, it showed well defined semicircle with the (R_{ct}) value of 3570 Ω . Interestingly, the PbO thin film showed a very small semi-circle with a straight-line and it showed the (R_{ct}) value of 6.5 Ω (Inset of Figure. 4.63) along with the residual phase element. The smaller in the R_{ct} causes better conductivity and an increase in charge carriers due to low interfacial charge transfer resistance and also lower charge transfer resistance between the electrode and the electrolyte interfaces.

The Bode phase plots obtained for the EFDAACVD-deposited metal oxide thin films are depicted in Figure 4.64. The characteristic frequency peak for different metal oxide thin films are as follows: Mn_2O_3 (794.3 Hz), α -Fe₂O₃ (5.851 Hz), NiO (5.011 Hz),CuO (7.943 Hz), ZnO (15.851 Hz), CdO (24.99 Hz) and PbO (1995 Hz). These obtained characteristic frequencies can be related to the electron recombination lifetime (τ_n) of the corresponding metal oxide thin films by referring to the equation below (Lim et al., 2014):

$$\tau_n = \frac{1}{2\pi f_{max}}$$

Where f_{max} is the frequency peak maximum. Among different metal oxide thin films, Mn_2O_3 showed a very low recombination life time (τ_n) value (0.0002 sec) compared to other metal oxide thin films (α -Fe₂O₃, NiO and CuO). Hence variations in τ_n values make a difference in the photocurrent values for different metal oxide thin films (Table 4.11).



Figure 4.63: Nyquist phase plots obtained for the Mn_2O_3 , α -Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films in the presence of 0.1 M Na₂SO₄ at frequencies ranges of 0.1 Hz to 10 kHz.



Figure 4.64: Bode phase plots obtained for the Mn_2O_3 , α -Fe₂O₃, NiO, CuO, ZnO, CdO and PbO thin films in the presence of 0.1 M Na₂SO₄ at frequencies ranges of 0.1 Hz to 10 kHz.

Thin films	R _{ct}	\mathbf{f}_{\max}	$ au_{n}$
	(ohm)	(Hz)	(sec)
Mn ₂ O ₃	102	794.3	0.0002
Fe ₂ O ₃	750	5.851	0.0271
NiO	4600	5.011	0.0317
CuO	3800	7.943	0.0200
ZnO	5225	15.85	167.44 × 10 ⁻⁵
CdO	3570	24.99	637.19× 10 ⁻⁵
PbO	6.5	1995	7.98× 10 ⁻⁵

Table 4.11: Charge transfer resistance, maximum frequency and recombination lifetime calculated for the EFDAACVD deposited metal oxide thin films.

Footnote: R_{ct} – Charge transfer resistance; f_{max} – Maximum frequency; τ_n – recombination lifetime.

Contribution of various morphology and band-gap causes difference in the recombination life time and thus significantly influence the photoelectrochemical performance.

4.7 Copper Lead Iodide (CuPbI₃)

The solid state synthesis of CuPbI₃ was carried out by using a precipitated mixture of copper(I) iodide and lead(II) iodide from an aqueous solution. Lead(II) iodide is soluble in dimethylformamide (DMF) while copper(I) iodide is insoluble. Therefore, we precipitated lead(II) iodide in slight excess over copper(I) iodide to ensure complete utilization of the latter in solid state reaction, while excess of the former was removed from the product by washing with DMF. Henceforth a dry mixture of co-precipitated copper(I) iodide - lead(II) iodide (1.65 g) was charged in a 5 mL pyrex glass ampule, then evacuated and sealed under vacuum. The charged ampule was placed in a horizontal tube furnace and heated at 620 °C for 72 hours before it was cooled to room temperature. The

mustard coloured final product was mechanically removed from the ampule, ground to a fine powder in an agate pestle and mortar and washed with several 5 mL portions of DMF to ensure complete removal of unreacted PbI₂ to yield 99.9% pure CuPbI₃ m.p. 307 °C. The synthesized CuPbI₃ is stable in air and is insoluble in common polar and non-polar solvents.

4.7.1 Thermal Studies of CuPbI₃

The decomposition thermal of CuPbI₃ examined pattern was by thermogravimetric/derivative thermogravimetric (TG/DTG) analyses, performed in the temperature range of 50- 900 °C, under a flow of dinitrogen (20 cm³min⁻¹) at a heating rate of 20 °Cmin⁻¹ (Figure 4.65). The (TG/DTG) plot (Figure 4.65) shows no appreciable loss in weight till the temperature reaches to 432 °C where its pyrolysis begins. This pyrolysis step is sharp and is completed at 693 °C with a mass loss of 53.31% of the original weight of the sample. TG/DTG curves also indicate that there is no mentionable loss in weight at the start in the temperature range of 50 to 400 °C, which indicates that CuPbI₃ is thermally stable from room temperature to above its melting point of 307 °C. Further heating to 900 °C yields a stable residual mass of 41.53% of the original weight of the sample indicating formation of Cu-Pb (1: 1) alloy with liberation of iodine as indicated in the following chemical equation.

Chemical equation 11:





Figure 4.65: The simultaneous TG and DTG plots of CuPbI₃ recorded under an inert atmosphere of nitrogen gas with constant flow of 20 cm³min⁻¹ and heating rate of 20 °Cmin⁻¹.

DSC trace of CuPbI₃ recorded under an inert atmosphere of nitrogen gas with constant flow of 20 cm³min⁻¹ and heating rate of 20 °C min⁻¹ is shown in Figure 4.66. The DSC curve displays two endothermic peaks at 240 °C and 307 °C. The well-defined sharp endotherm at 307 °C indicates melting point of CuPbI₃. The onset melting begins at 294.51 °C and melting process is completed at 315°C with maximum heat flow at 307 °C.

The sharp and well-defined endotherm at 307 $^{\circ}$ C indicates that material is highly crystalline in nature needing enthalpy of -19.00 J.g⁻¹ for melting. A weak endotherm with small enthalpy value of -2.79 J.g⁻¹ in DSC plot further suggests that CuPbI₃ passes through a phase change process at 240 $^{\circ}$ C before melting.



Figure 4.66: The DSC trace of CuPbI₃ recorded under an inert atmosphere of nitrogen gas with constant flow of 20 cm³min⁻¹ and heating rate of 20 °Cmin⁻¹.

4.7.2 XRD Analysis of CuPbI₃

X-ray diffraction patterns of the powder and electrophoretically deposited film of CuPbI₃ are displayed in Figure 4.67 and (Appendix 10) respectively. The XRD pattern of powdered CuPbI₃ agrees well with the pattern obtained for the films of CuPbI₃. This observation suggests that FTO does not chemically interfere during electrophoretic fabrication of CuPbI₃ film. The diffraction peaks at 20 values of 12.9, 25.7, 39.7 and 52.5 corresponds to (002), (004), (302) and (312) planes of the hexagonal CuPbI₃ lattice is in good agreement with literature data (T. A. Kuku, 1998; Titilayo A. Kuku & Salau, 1987). The crystallite size of the CuPbI₃ film is obtained by Debye Scherer formula $L = k \lambda/\beta cos\theta$ whereas k represents the Scherer constant, λ is the wavelength and θ the Braggs angle .The estimated crystallite size of CuPbI₃ is L = 62.5 nm which agrees well with the literature value (T. A. Kuku, 1998).



Figure 4.67: A comparison of powder XRD diffraction pattern of (a) as-synthesized CuPbI₃ powder with (b) reported in the literature (T. A. Kuku, 1998).

The XRD pattern of powdered CuPbI₃ agrees well with the pattern obtained for the films of CuPbI₃. This observation suggests that FTO does not chemically interfere during electrophoretic fabrication of CuPbI₃ film. The diffraction peaks at 20 values of 12.9, 25.7, 39.7 and 52.5 corresponds to (002), (004), (302) and (312) planes of the hexagonal CuPbI₃ lattice is in good agreement with literature data (T. A. Kuku, 1998; Titilayo A. Kuku & Salau, 1987). The crystallite size of the CuPbI₃ film is obtained by Debye Scherer formula $L = k \lambda/\beta \cos\theta$ whereas k represents the Scherer constant, λ is the wavelength and θ the Braggs angle .The estimated crystallite size of CuPbI₃ is L = 62.5 nm which agrees well with the literature value (T. A. Kuku, 1998).

4.7.3 Raman Spectroscopy of CuPbI₃

Raman spectroscopy with polarized laser beams ($\lambda = 514$ nm) at dissimilar geometries with respect to the crystal orientation should be used to investigate the distinguish Raman

active modes of different symmetries. The Raman scattering of as-synthesized CuPbI₃ film was recorded in the range of 100 - 1000 cm⁻¹ and is shown in Figure 4.68.



Figure 4.68: Raman spectrum of CuPbI₃ film

It is reported in the literature that pure CuI show Raman scattering mode at 140 cm⁻¹ (Irish, Stolberg, & Shoesmith, 1985), while an intense peak was observed at 120 cm⁻¹ which is attributable to the Pb-I bond vibration (Quarti et al., 2014) further PbI₂ modes are observed at 112 and 164 cm⁻¹ (Baibarac et al., 2015; Preda et al., 2008). It is found that Raman active modes related to CuI in CuPbI₃ fall at lower wave number with a difference of 4 cm⁻¹ and detected at 136 cm⁻¹ (Safdari, Fischer, Xu, Kloo, & Gardner, 2015). The broad band at 165 cm⁻¹ characteristic of PbI₂ has been found at its place as reported (Preda, et al., 2008). A new broad and intense Raman scattering mode that appeared at 213 cm⁻¹ is considered as characteristic mode for CuPbI₃ (Quarti, et al., 2014).

4.7.4 Surface Morphology of CuPbI₃

The surface morphology of the EPD deposited films have been investigated by FE-SEM and are shown in Figure 4.69(a). The CuPbI₃ films consist of compact grain structure with better surface coverage in the form of strips.



Figure 4.69: (a) Illustrates FESEM image of CuPbI₃ film deposited by Electrophoresis on FTO substrate, c(i) red, c(ii) green and c(iii) violet colour represent EDX mapping of Cu, Pb and I respectively

Films prepared by electrophoresis tend to grow with small grains grouped together in clusters of different sizes and show smooth uniform surfaces with presence of some randomly scattered voids in layers. This uniform, compact and granular morphology shows better performance for photocatalytic applications. The cross sectional view of CuPbI₃ film prepared by EPD is displayed in (Figure 4.69b).The growth of small grains on the boundary layer of the FTO substrate can be seen and the average film thickness was measured to be 96 μ m. The results of FE-SEM examination combined with EDX mapping for the elements Cu, Pb and I are shown in Figure 4.69c (i, ii and iii). The bright
regions with different colors correspond to the presence of the elements Cu, Pb and I, respectively, and indicate all these elements are distributed uniformly maintaining stoichiometric proportion of 1:1:3 throughout the whole area as indicated in (Appendix 11). The atomic concentration of Cu, Pb and I elements were also determined by XPS and compared with EDX results.

4.7.5 XPS Analysis of CuPbI₃

The surface and sub surface chemical states were investigated by high resolution narrow scan XPS spectra in the Cu2p, Pb4f and I3d region of CuPbI₃ film and is recorded as Figures 4.70(a, b and c). Figure 4.70a shows the binding energy of Cu $2p_{3/2}$ as 931.5 eV which is closer to the 931.9 eV that was found in CuI (M. Yang, Xu, Xu, Zhu, & Chen, 2004). The binding energies of Pb $4f_{7/2}$ and Pb $4f_{5/2}$ (Figure 4.70b) are 137.3 eV and 142.1eV respectively, indicating a spin orbital splitting of 4.8eV. These values are in good agreement for the reported energy values for Pb in Cs_{0.2}FA_{0.8}PbI₃ and PbI₂ (Morgan & Van Wazer, 1973; Yi et al., 2016; J. Zhang et al., 2015). The binding energies of the 13d values reported for I in CuI, Cs_{0.2}FA_{0.8}PbI₃ and PbI₂ (M. Yang, et al., 2004; Yi, et al., 2016; J. Zhang, et al., 2015).

For the precise measurement of the valance band maximum (VBM) energy position, 200 measurement scan cycles were carried out. A plot of normalized intensity and binding energy ranging from -6 to 8 eV is shown in Figure 4.71 (d). The valance band maximum was determined by linear extrapolation method and was found to be at 1.20 eV vs NHE. The position of conduction band minimum (CBM) was estimated on the basis of band gap energy determined by UV-vis spectrophotometry and VBM energy determined by XPS. The value obtained for CBM of CuPbI₃ was found to be -0.62 eV vs NHE as shown in Figure 4.72.



Figure 4.70: The XPS spectra of (a) Cu $2p_{3/2}$ (b) Pb $4f_{7/2}$, $4f_{5/2}$ (c) I $3d_{5/2}$, I $3d_{3/2}$ and (d) plot of normalized intensity and binding energy ranging from -6 to 8 eV of CuPbI₃ film.

4.7.6 Optical Band Gap of CuPbI₃

The optical band gap of CuPbI₃ film was studied by measuring the UV- visible absorption spectra recorded in the wavelength range of 300 - 900 nm using a similar FTO substrate as reference to minimize the contribution from the substrate. It can be seen that the Uv-vis spectrum (Figure 4.71) of the CuPbI₃ thin film shows wide range absorption which gradually increases towards lower wavelengths and shows the maximum absorption in the range of 330 - 790 nm. The Tauc's plot of energy versus $(\alpha hv)^2$ (Figure 4.71 inset) shows direct optical band gap energy of 1.82 eV.





This optical band gap value agrees well with the band gap value calculated for CH₃NH₃PbI₃ by Uv-visible spectroscopy (Y. Zhao & Zhu, 2016). It is also reported that presence of methylammonium cation or Cs⁺ does not affect the band gap region and it is the inorganic component of metal halide perovskites that plays dominant role in ascertaining the band gap energy. (Brivio, Walker, & Walsh, 2013; Yin, Shi, & Yan, 2014) In case of CuPbI₃ the band gap energy value remains unchanged inferring that replacement of CH₃NH₃⁺ or Cs⁺ by a univalent transition d¹⁰ metal ion e.g Cu⁺ did not affect the band gap. After successful deposition of high purity film of CuPbI₃ and evaluation of its thermal properties, structure, stoichiometric composition, surface morphology and optical band gap, we investigated its photoelectrochemical (PEC) behavior.



Figure 4.72: Shows energy of conduction band minimum calculated from XPS determined valence band maximum and Uv-visible band gap of CuPbI₃ film.

4.7.7 Photoelectrochemical Studies of CuPbI₃

The photoelectrochemical behavior of the CuPbI₃ film was investigated to evaluate its ability to perform water oxidation using linear sweep voltammetry (LSV) technique under simulated solar AM 1.5G irradiation in the presence of 0.1 M Na₂SO₄ at a scan rate of 50 mV/s. Under applied bias, the film undergoes photo-induced charge separation thereby promoting the valence band electrons to the conduction band resulting in the formation of holes at the valence band. The holes produced at the valence band can be readily scavenged through water oxidation that produces O₂ and H⁺ ions. The electron present in the conduction band can be readily collected as a photocurrent generated by the film. The H⁺ ions are transported through the electrolyte towards the counter electrode where they react with photo generated electrons to produce hydrogen. Further enhancement in photocurrent can be brought about by improving film thickness, morphology, surface roughness, structure and geometry. The photoelectrode shows active response under illumination and represents an anodic photocurrent pattern. The onset of photocurrent begins at -0.1 V under illumination and increases with increasing applied potential as depicted in Figure 9a. In the dark, however, no current can be observed until a bias of 0.1 V and after that small currents appear before it increases sharply beyond 0.8 V (vs. Ag/AgCl). Moreover, the most important and notable point in this case is that the CuPbI₃ requires an over-potential of +0.62 V vs Ag/AgCl, pH 7, which is similar to 1.23 V vs RHE i.e. the thermodynamic potential required for water oxidation according to the equation given below :(Yourey & Bartlett, 2011).



$$E_{RHE} = E_{Ag/AgCl} + 0.059 \, V. \, pH + 0.199 \, V \tag{4.6}$$

Figure 4.73: (a) Photocurrent density – applied voltage (J-V) plots obtained for the electrophoretic produced CuPbI₃ films dipped in 0.1M Na₂SO₄ at a scan rate of 50mV/s in light and dark. (b) Chronoamperometry (I–t) profiles (on-off cycles) of CuPbI₃ films at an applied potential of +0.65 V versus Ag/AgCl under 100 mW cm⁻² illumination (AM 1.5) in 0.1 M Na₂SO₄ aqueous solution.

Under illumination, a photocurrent density of 220 μ A/cm² can be observed at the thermodynamic potential of +0.62 V vs Ag/AgCl, pH 7. However, the dark current for the CuPbI₃ film has slightly increased probably due to the leakage of electrons from the

electrolyte to the FTO due to the pin hole effect. Nevertheless, many of the pin holes already have been cover by the compact thin film as seen in high resolution SEM picture shown in the Figure 5(a). We assume that the low band gap and compact morphology facilitates better electronic flow under illumination that enhances photocurrent density.

The role of Cu^+ with d^{10} configuration is just to balance the charge, it does not have any important contribution for the conduction and valence band states except for donating one electron to the Pb-I framework as is reported for CH₃NH₃⁺ and Cs⁺ ion in CH₃NH₃PbI₃ and CsPbI₃ respectively(Y. Zhao & Zhu, 2016) (Umebayashi, Asai, Kondo, & Nakao, 2003). The molecular orbital diagram of $[PbI_3]^{-1}$ ion (Appendix 13) depicts that I, (EN: 2.5) atomic orbitals (AO) are at low energy and Pb, (EN: 2.0) AO are at high energy. After linear combination of atomic orbitals these orbitals split into two sets of valence band and conduction band orbitals. The valence band orbitals are further divided into two, lowest and middle order energy state orbitals while, conduction band orbitals are highest energy orbitals. Hence σ Pb 6p – I 5s and σ Pb 6p – I 5p_z are in the lowest energy state of the valence orbitals while nonbonding Pb 6s, I 5px and 5py orbitals that are of intermediate energy remain as nonbonding orbitals. Pb 6s nonbonding orbital is at slightly high energy state than I $5p_x$ and $5p_y$. After crossing fermi level there begins a region where empty conduction band orbitals σ^* Pb 6p – I 5pz and σ^* Pb 6p – I 5s are located. The process of photoelectrochemical water splitting begins with the photo activation of VBM Pb 6s nonbonding electron that on solar activation cross fermi level (E_f) and fall into σ^* Pb 6p - I 5p_z conduction band orbitals from where they are removed by the applied bias. The hole generated by the photo activation reacts with water to split water into oxygen and H⁺ ions. It is believed that mostly Pb electrons are being used in photocatalytic process (Brivio, et al., 2013; Filippetti & Mattoni, 2014; Q. Liu et al., 2014; Umebayashi, et al., 2003; Yin, et al., 2014; Kang et al., 2015; Mansoor, Ehsan, et al., 2013).

The CuPbI₃ photoelectrode was further tested under on–off cycle illumination conditions to determine the stability of material. Figure 4.73b shows the photocurrent generated under visible light irradiation of CuPbI₃ electrode. A photo response of CuPbI₃ within 18 on-off cycles could be observed over a 60 min period (Figure 4.73b) revealing the efficiency and stability of CuPbI₃ photoelectrode. Initially the film is stable at 224 μ A cm⁻² for 15 min the current is dropped to 190 μ Acm⁻². Moreover, the transient photocurrents agree well with LSV results and strengthened the PEC performance in the visible light region, as well as indicating the stability of CuPbI₃ films after 40 minutes.

The CuPbI₃ has distinct advantages of its environmental stability, wide light absorption range due to its appropriate band gap and efficient charge transport due to structural defects. The combination of these unique properties enables this class of halide materials to adopt solar cell structure in which high efficiencies could be possible to achieve.

CHAPTER 5: CONCLUSION

It is concluded that reproducible and robust CuO-TiO₂, CoTiO₃-TiO₂ and MgTi₂O₅ composites and SnO₂ thin films can easily be designed from single source precursors $[Cu_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ ·THF (1)., $[Co_2Ti_4(\mu-O)_6(TFA)_8(THF)_6]$ ·THF (2), $[Mg_2Ti_4(O)_2(OH)_4(TFA)_8(THF)_6]$ ·THF (3) and $[Sn(dmae)(OAc)]_2$ (5) respectively, While the Ag-Mn₂O₃ semiconducting thin films can be deposited from dual sources of $[Mn(dmae)_2(TFA)_4]$ (4) and Ag(I) acetate by AACVD method.

All the precursors (1-5) are prepared viably in a quantitative yield by simple chemical reactions of their respective metal alkoxides in the presence of TFAH/dmaeH using THF or toluene as solvent. The stoichiometry of all the complexes are determined by elemental analyses, FT-IR, ¹H NMR, thermogravimetry and single crystal X-ray diffraction analysis. All complexes have adaptable physical and chemical characteristics are stable in air or moisture, highly soluble in many organic solvents and decompose at relatively low to normal temperatures making them suitable precursors for CVD to deposit metal oxide composite thin films in temperature range of 450 to 630 °C.

Thin films of SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO and PbO prepared under EFDAACVD indicate that morphology of the films can be controlled precisely by this technique but the PEC studies indicate a little improvement in photocurrent as compared to the films prepared in absence of electric field. UV-visible studies of thin films of Ag-Mn₂O₃ and MgTi₂O₅ indicate the band gap values of 1.8 and 3.4 respectively. While thin films of SnO₂, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO and PbO prepared under EFDAACVD depict band gap values of 3.8, 1.2, 2.2, 1.9, 0.9, 3.2, 2.2 and 1.9eV respectively. Thin film of CuPbI₃ prepared by electrophoretic technique indicate a band gap of 1.82eV. The electrochemical measurement of all fabricated thin films conducted

in conventional three-electrode electrochemical set-up employing an Ag/AgCl/ 3M KCl as the reference electrode and a platinum wire as the counter electrode studied by cyclic voltammetry, linear sweep voltammentry, chronoamperometery, electrochemical impedance spectroscopy and Mott schotty plot. These investigations that the thin films of CuO-2TiO₂ and CoTiO₃–TiO₂ are provides an attractive for the sensitive and selective detection of nitrite ion and dopamine, respectively. The reversibility, high rate capacity and relative stability shown by SnO₂ micro-ball based anodic materials in lithium ion batteries. The good photoelectrochemical behavior of Ag-Mn₂O₃, MgTi₂O₅, Mn₂O₃, Fe₂O₃, NiO, CuO, ZnO, CdO, PbO and CuPbI₃ thin films shows that these films could be a potentially valuable tool for photoelectrochemical water splitting.

Future Research Plan

The improvement of clean energy has become a main interest among recent research work. However, many routes to generate hydrogen have been introduced include both reforming and non-reforming hydrogen production. Further work is to develop trimetallic photocatalyst thin films electrodes by AACVD is under investigation to achieve high performance cells. In future effort is being carried out towards establishing stacked solar cells by connecting the photoelectrodes in series. Further improvement in photocurrent of the synthesized materials can be determined by producing dye sensitizes solar cells (DSSC). In future we will further expand the applications of ceramic-based nanostructures in fuel cells, supercapacitors, sensors, batteries and PEC to meet the environment- and energy-related demands.

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